ACADEMIC CURRICULA

Professional Elective Courses

NANOTECHNOLOGY

Regulations - 2018



SRM INSTITUTE OF SCIENCE AND TECHNOLOGY

(Deemed to be University u/s 3 of UGC Act, 1956)

Kattankulathur, Kancheepuram, Tamil Nadu, India

Cour Coc		18NTE301T Course Name	CARBON NANOTECHNOLO	GY	Cou	rse Ca	ategor	у	Е				Prof	fessio	onal E	lective)		-	L 3	T 0	P 0	C 3
	equisite urses	Nil	Co-requisite Nil			rogres Cours		Nil															
Course	Offering D	repartment Nanotechnology	Data Bool	k / Codes/Standards	Nil																		
Course		, ,	ning this course is to:	All Control of the Control	L	_earnir	ng			١			Progr	ram I	Learni	ng Ou	tcom	,					
CLR-1		knowledge various forms of carbon			1	2	3		1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		tands the use of carbon forms in applic <mark>a</mark>			E	(%	9		Φ		_						بح						
CLR-3		tands the physical and chemical prop <mark>erti</mark>		Section 1997	Thinking (Bloom)	5) t		o ge		Jen		4)				No.		Finance				
CLR-4		tands the physical and chemical properti			g (E	ien	mel)MC	<u>.v.</u>	ndc	-	age	ė			E		⊒a	Learning			
CLR-5		tands the physical and chemical properti			Ä	ofic	tain		Ž	alys	velc	5	S	Ħ	∞ >		Lea	.io	∞ర	arni			
CLR-6	Acquire	e knowledge about various synth <mark>esis forn</mark>	ns		ΙĖ	4	Att		ing	Ans	De G	_	<u>8</u>	ರ	ent		∞	icat	g.	Le			
					→	ted	ged		eer	E I	Nis	arc j	Ξ	ty 8	nno ina		gra	ш	≥ 5	ong	-	7	د .
Course	Learning (Outcomes (CLO): At the e <mark>nd of this c</mark> o	ourse, learners will be able to:	200	Level	Expected Proficiency (%)	Expected Attainment (%)	М.	□ Engineering Knowledge	Problem Analysis	Design & Development Analysis Design	Research	Modern Tool Usage	Society & Culture	Environment & Sustainability	Ethics	Individual & Team Work	Communication	Project Mgt.	Life Long I	PSO.	PSO.	PSO.
CLO-1		e the geometry of various carbon nanosti			2	80	75		Н			Н	М	М	М	Н	Н	Н	М	Н	Н	Н	Н
CLO-2		ntiate the structure and prop <mark>erties of d</mark> iffe			2	80	70						М	М	М	Н	М	Н	М	Н	М	М	М
CLO-3			ubes and Graphene in different applications	ALTER TO A	2	75	70	100		М			М	Н	Н	М	Н	Н	Н	Н	Η	Η	Η
CLO-4		e the geometry of various ca <mark>rbon nan</mark> o tເ		All the second second	2	80	75				Н		Н	Н	Н	Н	Н	Н	М	Н	Н	Н	Н
CLO-5			tion techniques of carbon nanostructures	The state of the s	2	80	70						Н	М	М	Н	М	Н	М	Н	Η	Η	Н
CLO-6	: Demor	strate the applications of ca <mark>rbon nan</mark> ostr	uctures	Hilliam Company Control	2	80	75		Н	М	M	Н	М	М	М	Н	Н	Н	М	Н	Н	М	Н
			- DE 200 A																				
	ration nour)	9	9	9			14.11				9			f					ç				
S-1	SLO-1	Introduction	Fullerenes	Carbon Nanotubes				Graph								Introd				าร			
0 1		Carbon molecules	Structure of fullerenes	Structure of Carbon Nanoti				Struct								Carbo							
	SLO-1	Nature of carbon bond	Bonding of fullerenes	Nomenclature of Carbon N				Synthe	esis o	f Gra _l	ohene					Amorp	phous	s natu	re				
S-2	SLO-2	New carbon structures	Nomenclature	Electronic properties of Ca (CNTs)	rbon l	Vanotu	ubes	Chara	cteriza	ation	of Gra	ohene)			Crysta							
S-3	SLO-1	Discovery of C60	C60 and higher fullerenes	Synthesis of Single Wall C	VTs (S	SWCN	VTs)	Prope	rties o	f Gra	phene					Chem Diamo	ond			,	CVD)	:	
	SLO-2	Structure of C60	Growth mechanisms	Production of SWCNTs				Electri								Struct							
S-4	SLO-1	C60 crystal	Production	Synthesis of Multi Wall CN	Ts (SI	WCN7		Magne					ene			Synth	esis c	of CVI	O diar	nond			
3-4	SLO-2	From graphene sheet to a nanotube	Production of MWCNTs				Band .	structu	ure of	^f Graph	ene				Physic	cal pr	operti	es of	CVD	diamo	ond		
9.5	SLO-1 Single wall and multi walled nanotubes Fullerene preparation by pyrolysis of hydrocarbons			Growth mechanism of CN1	-			Phono	n mod	des ir	Grapi	hene				Chem	ical p	roper	ties o	f CVD	diam	ond	
SLO-2 Zigzag nanotubes Partial combustion of hydrocarbons diffrac				Analysis of Carbon Nanotu diffraction				Rama	n mod	les in	Graph	ene			CVD diamond as we			wea	vear resistant coatin				
S-6 SLO-1 Armchair nanotubes Physical properties Analysis of can Spectroscopy				Analysis of carbon nanotuk Spectroscopy	es by	Rama	an	Layer	deper	ndend	e of R	aman	spec	ctra		CVD (diamo	ond as	s bio-c	chemi	cal se	nsors	;
	S-6 SLO-2 Chirality in nanotubes Chemical properties Spectroscopy Carbon nanotubes as				sistor	S		Rama	n spe	ctroso	copy of	Grap	hene	e una	ler	Optica	al app	licatio	ns: ir	nfrared	d wind	lows,	

					strain	lenses, X-ray Windows
S-7	SLO-1	Structure of defective nanotubes	Hydrogenation	Carbon nanotubes as Field Effect Transistors (FET)	Infrared spectroscopy of Graphene	Amorphous carbon thin films
	SLO-2	Bonding of defective nanotubes	Applications of fullerenes	Carbon nanotubes as sensors	X-Ray diffraction of Graphene	Amorphous carbon films (a:C)
	SLO-1	Cylindrical nanotubes	Fullerenes in solar cell	Carbon nanotubes as bio-sensors	EELS of Graphene	Hydrogen amorphous carbon films (a:C-H)
S-8	SLO-2	Euler's theorem	Fullerenes as donor systems	Carbon nanotubes as gas sensors	Graphene in solar cell applications	Physical properties of amorphous carbon film
S-9	SLO-1	Euler's theorem in cylindrical nanotubes	Fullerenes as acceptor systems	Carbon nanotubes in dye degradation	Graphene as gas sensors	Chemical properties of amorphous carbon film
5-9	SLO-2	Euler's theorem in defective nanotubes	Fullerenes as chemical sensors	Carbon nanotubes in photo-catalytic activities	Graphene in dye degradation (photocatalytic activities)	Amorphous carbon film as anti-reflection and anti-corrosive coatings

Learning Resources	1. 2. 3.	Anke Krueger, "Carbon Mater <mark>ials and N</mark> anotechnology", Wiley-VCH, 2010 Yury Gogotsi, "Carbon Nano <mark>materials</mark> ", Taylor and Francis, Second edition, 2014 C. N. R. Rao, Ajay K. Sood <mark>, "Graphe</mark> ne: Synthesis, Properties, and Phenomena"- Wiley- VCH, 2013	4.	Wonbong Choi, Jo-won Lee, "Graphene: Synthesis and Applications" CRC Press, Taylor and Francis, 2012	
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Learning Assess	sment			4 (1)	1410/1976	200	21 NO.				
	Dloom'o			Conti	nuous Learning Ass	essment (50% weig	htage)			Final Examination	n (FOO/ woightage)
	Bloom's	CLA -	1 (10%)	CLA -	2 (15%)	CLA -	3 (15%)	CLA – 4	I (10 <mark>%)</mark> #		n (50% weightage)
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %		30 %		30 %	The State	30 %	- 1-	30%	-
Level 2	Apply Analyze	<mark>40 %</mark>	4	40 %		40 %		40 %	-	40%	-
Level 3	Evaluate Create	30 %		30 %	Sie-	30 %	20 - M	30 %	-	30%	-
	Total	10	00 %	10	0 %	10	0 %	100	0 %	10	00 %

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
1. Dr. D.K. Aswal, National Physical Laboratory, dkaswal@nplindia.org	1. Dr. V. Subramaniyam, IIT Madras, manianvs@iitm.ac.in	1. Dr. M.Navaneethan, SRMIST
2. Dr. S. Sudhakar, CSIR-CECRI, sudhakar@cecri.res.in	2. Dr. S. Balakumar, University of Madras, balakumar@iunom.ac.in	2. Dr. E. Senthil Kumar, SRMIST

Course Code		18NTE302T	Course Name	PHYSICS OF SOLID STATE D	EVICE	S				_	ourse Itegory		Ξ	ı	Profess	sional	Electiv	/e		L 3	T 0	P 0	C 3
Pre-requ Course				Co-requisite Nil Nil					essive irses	Nil													
Course Offe	ering Depar	tment Nanc	technology	Data Book / Codes/St	andard	S	٨	lil															
		nale (CLR):		f learning this course is to:		_earnin	g						Pro	gram	Learnir	ng Ou	ıtcome	s (PLC	D)				
CLR-1: (Get knowled	ge in the design and v	vorking principle	of solid state devices	1	2	3		1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-3: // CLR-4: // CLR-5: // CLR-6: // Course Lea	Familiarize v Describe the Understand Acquire knot cells, Photoc arning Outco	operation of basic se the theory of various t wledge on the materia letectors, Lasers, etc omes	tal/semiconductor miconductor dioc ypes of transistor als and working of At the end of the		Level of Thinking (Bloom)	S Expected Proficiency (%)	Shected Attainment (%)		Engineering Knowledge	⊥ Problem Analysis	□ Design & Development	⊤ Analysis, Design, Research	Modern Tool Usage Modern Tool Usage	☐ Society & Culture	Environment & Sustainability	H Ethics	エ Individual & Team Work	Communication Com	Project Mgt. & Finance	⊤ Life Long Learning	H PSO - 1	т PSO - 2	н PSO - 3
				ngof semiconductor devices	2	80	70		H	Н	Н	Н	M	M	M	Н	Н	H	I	Н	M	M	M
		lytical approaches to unde			2	75	70	H.	H	1	Н	H	H	Н	H	H	H	H	M	H	Н	Н	Н
				working of different solid state devices	2	80	75		Н	Н	Н	Н	M	M	Н	H	Н	H	M	Н.	Н	H	Н
		he design principles o			2	80	70	71.6	H	М	Н	H	M	М	Н	Н	Н	H	ï	Н	Н	Н	Н
		erminal and three-terr			2	80	70		Н	Н	Н	Н	М	М	M	Н	Н	Н	L	Н	М	М	М
	ation our)	9		9)		1	ľ			9							9			
S-1	SLO-1	Concept of p-n juncti	on	Understand what a metal-semiconductor contact is. Study f	iundam	entals o	of BJT	opera	tion		ciple a sistors	nd type	es of fie	eld-eff	ect			rstand -n jund		al gene	eration	of car	riers

	ration our)	9	9	9	9	9
S-1	SLO-1	Concept of p-n junction	Understand what a metal-semiconductor contact is.	Study fundamentals of BJT operation		Understand optical generation of carriers in a p-n junction
3-1	SLO-2	Physics of the p-n junction formation	Qualitative characteristics of energy band formation	Operation modes of a BJT	Principle of operation of JFET	Types of Photodiodes
S-2	SLO-1	Energy band diagram of a p-n junction		Understand the structure and working of p-n-p and n-p-n transistors	If oncent of ninch-off and caturation	Solar radiation and ideal conversion efficiency of a solar cell
3-2	SLO-2	Estimation of the electric field, electric potential, and built-in potential	Theoretical considerations in estimating the barrier height	Band diagram and static characteristics	Derive I-V characteristics of JFET	Physics of solar cell
S-3	SLO-1	Depletion approximation and estimation of space charge width	Nonideal effects on the barrier height	Factors involved in transistor amplification		Device configuration and technology roadmap, solar cell materials
5-3	SLO-2	Depletion layer capacitance and its estimation	Qualitative explanation of image-force- induced lowering of the potential barrier	BJT fabrication	Concept of high-electron mobility transistors - III-V semiconductor materials	Familiarize with the solar cell parameters and efficiency calculation
	SLO-1	Linearly graded junction in thermal equilibrium	Current transport processes in metal- semiconductor contacts	Analysis of minority carrier distribution	Basic working and fabrication of MOSFET	Design principle of photodetector
S-4	SLO-2		Comparison of the Schottky barrier diode and the p-n junction diode	Solution of the diffusion equation in the base region	Knowledge on modes of operation and short channel MOSFET	Types of photodetectors and characteristics

S-5	SLO-1	Qualitative description of charge flow in a p-n junction	Metal-semiconductor Ohmic contacts	Evaluation of the terminal currents	Short channel effects in MOSFET	How light-emitting diodes work?
3-0	SLO-2	Ideal current-voltage characteristics of a p-n junction	Concept of ideal nonrectifying and tunneling barriers	Non ideal effects in BJT	Advanced MOSFET structures	Basic device structure and the concept of radiative recombination
S-6	SLO-1	Derivation of Shockley equation (ideal- diode equation)	Methods to experimentally measure the barrier height	Deviations from the basic theory and indicate situations in which each effect is important	Metal Gate-High-k and Enhanced Channel Mobility Materials and Strained Si FETs	Materials of choice and technology roadmap
	SLO-2	Generation-recombination process and its effect	Current-voltage and capacitance-voltage measurements	The physical mechanisms of the current gain limiting factors	Complementary MOS structure and its formation	Specifications used in denoting the practical LED bulbs
	SLO-1	Reverse bias breakdown mechanisms in a pn junction	Photoelectric measurements	The voltage breakdown mechanisms in abipolar transistor	CMOS process integration	Physics of laser action
S-7	SLO-2	Zener and Avalanche breakdown	Figure of merit of ohmic contacts and its determination, the concept of specific contact resistance	The current-limiting factors from the current components in the transistor	Concept of modulation doping in HEMT	Gain knowledge of stimulated emission and population inversion
S-8	SLO-1	Transient behavior of a p-n junction	Isotype and anisotype semiconductor heterojunctions - energy band diagrams	Frequency limitations of transistors	Basic device structure of AlGaAs/GaAs HEMT and I-V characteristics	Fabrication of p-n junction laser
3-0	SLO-2	Concept of Noise in semiconductor devices	Current density equations and physical interpretation	The voltage breakdown mechanisms in a bipolar transistor	Output characteristics and channel related phenomenon	Emission spectra
S-9	SLO-1	Terminal functions of a p-n junction diode, The concept of tunnel diode	Introduction to two-dimensional electron gas	Heterojunction BJT	Dynamic effects in MOS capacitors – The Charge-coupled device	Familiarize with the structure and need of heterojunction lasers
3-9	SLO-2	ρ-n junction as rectifi <mark>er, Zene</mark> r diode, Varistor, and Varactor	Concept of quantum well and superlattice structures	Schottky and Photo transistors	Basic CCD structure and its applications	Materials for semiconductor lasers and quantum cascade lasers

Learning	1.	S M Sze, Kwok k. N <mark>g, "Physi</mark> cs of semiconductor devices" – John Wiley & Sons, Inc., 2007	3.	Donald A. Neamen, "Semiconducto <mark>r Physics</mark> and Devices: Basic Principles" – McGraw
Resources	2.	Ben G. Streetman, Sanjay Kumar Banerjee, "Solid State Electronic Devices", Pearson Education Ltd, 2016		Hill, Fourth Edition, 2011.

Learning Assessr	nent										
	Bloom's		100	Conti	nuous Learning Asse	essment (50% weig	htage)			Final Evamination	n (50% weightage)
	Level of Thinking	CLA –	1 (10%)	CLA -	2 (15%)	CLA -	3 (15%)	CLA – 4	1 (1 <mark>0%</mark>)#		ii (50% weightage)
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %	- f	30 %		30 %	//	30 %		30%	-
Level 2	Apply Analyze	40 %	- 2	40 %		40 %		40 %	-	40%	-
Level 3	Evaluate Create	30 %	78. ·	30 %	ARC AS I	30 %	FEWN	30 %	-	30%	-
	Total	100) <mark>%</mark>	10	0 %	100	0 %	10	0 %	10	0 %

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
1. Dr. D.K. Aswal, National Physical Laboratory, dkaswal@nplindia.org	1. Prof. M.S. Ramachandra Rao, IITM Chennai, msrrao@iitm.ac.in	1. Dr. S. Chandramohan, SRMIST
2. Dr. S. Sudhakar, CSIR-CECRI, sudhakar@cecri.res.in	2. Prof. T. Som, Institute of Physics, tsom@iopb.res.in	2. Dr. E. Senthil Kumar, SRMIST

Cou		18NTE303T Cours	e Name MOLE	CULAR SPECTROSCOP	Y AND ITS APPLICATIONS			Course		Ε			Pr	rofess	ional E	Elective				L 3	T 0	P 0	C 3
	requisite ourses	Nil	Co-requisite Courses	Nil			ogres: Course		Nil														
Course	Offering [Department Nanotechnology		Data Book	/ Codes/Standards	Nil																	
					ALLMAN																		
Course	_	, , ,	arning <mark>this course i</mark> s to	11.7%	III and the same of the same o	Le	earnir						Pr	ogran	n Learr	ning Ou	utcom	•					
CLR-1		e the knowledge in the basic concepts o		on with matter and rotatior	nal spectroscopy	1	2	3	1	1 :	2 3	3 4	1 5	6	7	8	9	10	11	12	13	14	15
CLR-2		rehend the principles of vibrational spec				om)	(%)	(%)		ge	7	_					놑		Ф				
CLR-3 CLR-4		stand the principles and techniques in <mark>vo</mark> asize the significance of various tec <mark>hni</mark> q				(Bloom)	Expected Proficiency (%)	Expected Attainment (%)		# Engineering Knowledge	8	Analysis, Design,	<u>a</u>	2			Individual & Team Work		Project Mgt. & Finance	_			
CLR-4		e to concepts and applications of <mark>magn</mark> e		шовсору		ng (cier	JE L		o :	SIS	gn,	Research Modern Tool Usage	<u>g</u>	5		gam	_	Ë	Life Long Learning			
CLR-6		on relevant theory, concepts, and techn		na the spectrum of molecu	iles	evel of Thinking	Profi	∖ttai		g A	Problem Analysis	Analysis, Design,		Society & Culture	Environment &	€	× ⊢	Communication	t. &	-ear			
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Course	Loorning	Outcomes (CLO): At the end of this	oouroo loornoro will b	o oblo to:		ole	ect	ect		gine	ple	alys	Research Modern To	i i	iro i	<u>S</u>	vidt	E	ject	P	PS0 - 1		
		` '	course, learners will b				Ехр	EX		E C	5 5	Ang	Re Re	S.		Sustair	<u>p</u>	Ö	Pro		PS	PSO	PSO
CLO-1		et the processes of absorptio <mark>n and rad</mark> i			cules	2	80	75			M I	1 F	$H \mid H$		I M	H	Н	Н	М	Н	Н	Н	Н
CLO-2		te the vibrational spectra of d <mark>iatomic a</mark> nd			The second second	2	80	70				1 H					М	Н	М	Н	М	М	М
CLO-3 CLO-4		re the Raman spectra and v <mark>arious no</mark> n- ate the various optical proces <mark>ses invo</mark> lve			ACTIVE TO SERVICE	2	75 80	70 75			M I						H	H	H M	H	H	H	H
CLO-4 CLO-5		ate the various optical proces <mark>ses involve</mark> the concept magnetic resona <mark>nce in ch</mark> ei				2	80	70			H I M I						М	Н	M	Н	Н	Н	Н
CLO-6		e the applicability of a spectr <mark>oscopic a</mark> p				2	80	75				1 H					Н	H	M	H	Н	M	H
	, ,			And the second second													1	1					
	ıration hour)	9	-	9	9	¥.		w				9							9				
S-1	SLO-1	Electromagnetic spectrum, spectral regions	Vibrational energ	y of a diatomic molecule	Born oppenheimer approxim	nation			Quantı	ım the	ory of	Rama	an sc <mark>at</mark>	ttering	7	Magn	etic m	oment	ts				
-	SLO-2	Types of molecular energies	Classical approac		Vibrational coarse structure				Classic	al the	ory of	Rama	an s <mark>cat</mark>	tering		Quan	tizatio	n					
	SLO-1	Interaction of light with matter	Wave mechanica		Band system and vibrationa	l trans	sitions	S	Rotatio	nal Ra	aman	specti	a					cessio					
S-2	SLO-2	Methods of obtaining a spectrum, components of a spectrometer	Morse curve and diatomic molecule	energy levels of a e	Progressions and sequence	s			Vibratio	onal R	aman	spect	ra			Reson reson		condii (NMR)		n Nucl	ear n	nagne	∍tic
S-3	SLO-1	Spectral line width and broadening of spectral lines	Selection rules fo	ON THE PROPERTY.	Franck condon principle				Mutual	exclu	sion p	rincipi	e			Spin -	-spin	relaxai	tion				
3-3	SLO-2	Intensity of spectral lines	Fundamental ove the vibrational sp	ertones and hotbands in ectrum	Intensity of vibrational electr	onic s	spectr	ra	Polariz	ation (of Rar	nan so	attere	d ligh	t	Spin-l	attice	relaxa	ition				
S-4	SLO-1	Absorption and emission of radiation	Accidental degen	eracy	Rotational fine structure				Ramar							NMR	spect	romete	er				
3-4	SLO-2	Spontaneous and stimulated processe	s Diatomic vibrating	g rotator	Assignment of bands in a fir				Analys.							Chem	ical s	hift					
S-5	SLO-1	Einstein's co-efficients and its derivation	on Selection rules fo	r vibration-rotation	Dissociation energy and diss products	sociat	ion		Structu spectro	scopy	/		•					ntributii	_		_		
	SLO-2	Laser as a spectroscopic light source		ratomic molecules	Predissociation				Ramar	inves	stigatio	n of p	hase ti	ransit	ions	Doub	e reso	onance	etech	nnique			
S-6	SLO-1	Classification of molecules based on moment of inertia	s of CO ₂ <mark>and H₂O</mark>	Electronic absorption spectr	а			Resona	ance F	Ramai	scati	ering			NMR	imagi	ng	_			_		
	SLO-2	Rotational spectra of rigid diatomic	Electronic angular momentum in diatomic Surface enhanced Raman scattering Fourier transform							NMF	Rtechr	ique	s										

		molecules		molecules		
S-7		Rigid rotator	Group frequencies and various regions in IR spectrum	It lissination of energy by excited molecule	Non-linear Raman phenomena- preliminaries	¹³ C NMR
3-1	SLO-2	Isotope effect in rotational spectra, Intensity of rotational lines	Perturbation of group frequencies: mass effects	Jablonski diagram	Hyper Raman effect	Electron spin resonance
S-8	SLO-1	Non-rigid rotator	Perturbation of group frequencies: inductive effects	Phosphorescene	Stimulated Raman scattering	Resonance condition in Electron spin resonance (ESR)
3-0	SLO-2	Vibrational excitation effect and Λ doubling	Fourier transform infrared spectroscopy: principle and interferometer arrangement	Fluorescence	Inverse Raman effect	ESR spectrometer
S-9	SLO-1	Microwave spectrometer	Elucidation of molecular structure using IR spectroscopy	Photoelectron spectroscopy: principle	Coherent Antistokes Raman scattering	Nuclear- electron spin coupling
3-9	SLO-2	Applications of rotational spectroscopy		Photoelectron spectroscopy: instrumentation	Photo acoustic Raman scattering	Applications of ESR spectroscopy

1 Peter Atkins, Julio de Paula Atkins, "Physical Chemistry", W. H. Freeman and Company, New York,	
Learning Resources Resources Resources Learning Resources Resource	_

Learning Assessi	ment				THE RESERVE	Transition of the second	100						
_	Bloom's			Final Evaminatio	n (50% weightage)								
	Level of Thinking	CLA –	1 (10%)	CLA – 2	2 (15%)	CLA -	3 (15%)	CLA – 4	· (10 <mark>%)#</mark>	Final Examinatio	ii (50% weightage)		
	Level of Trilliking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice		
Level 1	Remember Understand	30 %	4 E	30 %		30 %		30 %	-	30%	-		
Level 2	Apply Analyze	<mark>40 %</mark>		40 %	1	40 %	20 F M	40 %	-	40%	-		
Level 3	Evaluate Create	30 %	120	30 %		30 %		30 %	-	30%	-		
	Total	10	0 %	100	1%	10	0 %	100) %	100 %			

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2. Dr. Krishna Surendra Muvvala, Saint Gobain Research India, India, Krishna.muvvala@saintgobain.com	2. Dr. M. S. Ramachandra Rao, IIT Madras, msrrao@iitm.ac.in	2. Dr. E.SenthilKumar, SRMIST

Cou		18NTE304T	Course Name	NANOTE	RIBOLOGY			ourse itegor		Ε			Prof	ession	nal Ele	ective	Course)			L 3	T 0	P 0	C 3
	requisite ourses	Nil	Co-requisite Courses	Nil				gress ourse		Nil														
Course	Offering I	Department Nanotechnology		Data Boo	Codes/Standards	100	Nil																	
		·		- 64																				
Course	e Learning	Rationale (CLR): The purpose of learning	ng <mark>this course is</mark> to):	William III		Le	arning	g					Prog	gram I	_earni	ng Out	come	es (PL	O)				
CLR-1		re knowledge on nanotribology					1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		rstand lubrication and related theories					Œ	(%	9	Ф								*						
CLR-3		nsight on surfaces forces and its meas <mark>urem</mark>		<u> </u>	AND IN TARREST		of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge		Design & Development		40				Nor		Project Mgt. & Finance				
CLR-4		about mechanisms involved in tribology rela		roperties	5-12-17-17		g (E	ien	me	N N	.00	лдс	ر'	age	മ			m/		ina	ng			
CLR-5		nce the knowledge on friction and wear and			Control of the Contro		Ϋ́	ofic	äi	X	alys	velo	sign	ns N	草	∞ >		Теа	ion	& F	aru			
CLR-6	: Attain	knowledge on tribological applications in da	y to day life	A		Ē	<u>-</u>	¥	i.i.	Ans	De	De	8	\vec{c}	nent bilit		∞	icat	lgt.	Le				
							of.) ted) jed	eer	E	n &	sis,		ty 8	nnc inal		dua	unu	χN	buc	-1	-2	က
Course Learning Outcomes (CLO): At the end of this course, learners will be able to:							Level	bed	bed	gi	Problem Analysis	ssig	Analysis, Design, Research	ge	Society & Culture	Environment & Sustainability	Ethics	Jivic	Communication	ojec	Life Long Learning	PSO.	PSO.	PSO.
								Ω O	<u>й</u>	山山	4			T Modern Tool Usage		<mark>ந</mark> ்	i ii	□ Individual & Team Work				<u> </u>		87
CLO-1							2		75	H	M	Н	Н		М	M	Н		Н	M	Н	Н	Н	Н
CLO-2: Identify, formulate, and solve engineering problem of interacting surfaces in relative motion CLO-3: Emphasize the knowledge of scientific disciplines in understanding tribological phenomenon							2	80 75	70 70	H	M	M H	H	M H	M H	M H	H	Н	M H	Н	H M	M H	М	M H
CLO-3 : Emphasize the knowledge of scientific disciplines in understanding inbological phenomenon CLO-4 : Realize the significance of lubrication, friction and wear							2		75	Н	Н	М	М	М	Н	Н	Н	Н	M	М	Н	Н	H	M
CLO-4		e the significance of lubricati <mark>on, inctio</mark> n and iar in the importance of modif <mark>ying surf</mark> ace pr				-	2		70	H	М	Н	H	Н	М	M	Н	М	Н	М	Н	М	М	Н
CLO-5		ar in the importance of modifying surface pr nanotribological principles fo <mark>r any app</mark> licati							75	H	M	М	Н	Н	M	M	Н	Н	Н	M	М	Н	M	Н
CLO-0	. Othize	nanounbological principles for any applicati	DIIS	Commission of the last				00	73		IVI	IVI	- 11		IVI	IVI	п	П	П	IVI	IVI	П	IVI	П
Di	uration					-		-			-													$\neg \neg$
	hour)	9		9		9			1.11				9							9				
	SLO-1	History of tribology-origin	Surface Forces		Lubrication			-	- 1	Scale Effe	ects in	Mech	nanica	l Prop	erties		Applica	ations	s of Tr	ibolo	av			
S-1	SLO-2	Significance of micro/nanotribology		study surface forces	Lubricant States					Nomencla		W					Introdu phenoi	ıction	to va			ogica	ıl	
S-2	SLO-1	Tribology in design-Methods of solution of tribological problems	Force laws	rce laws Viscosity of lubi											Bio-Tri	bolog	ЗУ							
	SLO-2	Purpose of lubrication	Surface force apparatus (SFA) Fluid film lubrication			-				Shear stre	ength	at the	interf	ace			Tribolo	av in	the h	umai	ı bodv	,		
0.0	SLO-1	Modes of lubrication- hydrodynamic	Force between di	Theories of hydrodyr	amics I	ubrica	ation		Scale dep and conta	ende	nce or	n <mark>sur</mark> fa		ughne	.00	Tribolo								
S-3	SLO-2	Hydrostaticlubrication	Force between su	urfaces in liquid	Lubrication design of elements	typical	mech	anica	1	Depende				ramete	ers on	load	Tribolo	gy in	medi	cal d	evices	i		
C 4				Transformation					Scale effe	cts in	frictio	n				Natura	l hun	nan sv	novi	al joint	ts			
5-4	SLO-2	Elastohydrodynamic lubrication	Capillary forces				aphy		/	Adhesi <mark>on</mark>	Friction	on					Total jo							
C E	SLO-1	Extreme pressure lubrication	Modes of deformation Friction- Basic Is												Wind turbine Tribology									
S-5	SLO-2	Lubricants - types and lubricating oils			Static and kinetic fric	atic and kinetic friction					dy def	ormati	ion				Biorefi	ning						
S-6	SLO-1	Lubricant properties-effect of temperature and pressure					Ratchet mechanism						Coating applications- sliding bearings											
	SLO-2	Oxidation stability	Surface roughnes	SS	Solid – solid contact		Meniscus Analysis						Rolling contact											
S-7	SLO-1	Thermal conductivity	Friction force		Liquid mediated cont	act				Total valu			ent of	frictio	n		Bearings							

	SLO-2	Type of additives	Scratching	Interfacing temperature of sliging Surfaces	Transformation from elastic to plastic regime	Gears
S-8	SI ()-1	Bearings- classification based on mode of lubrication	Wear and machining	Wear-Laws of wear	Tribological properties of SAMs	Erosion and scratch resistant
3-0		Bearing-Classification based on relative motion between contact surfaces	Surface potential measurements	Mild and Severe wear	Tailoring surfaces	Magnetic recording devices
S-9	SLO-1	Comparison of sliding and rolling contact bearing	Nanoindentation measurement		Modifying surface composition for application in Tribology	Micro components
3-9	SLO-2	Solving numerical problems on above topics	Boundary lubrication		Modifying Structurefor application in Tribology	MEMS/NEMS

Learning Resources 1. G. Phakatkar and R.R. Ghorpade, "Tribology", Nirali publication, 2009 2. Bharat Bhushan, "Nanotribology and Nanomechanics", Springer Publication, Second edition, 2011 3. Bharat Bhushan, "Principles and Applications to Tribology", Wiley Publication, 2013	4. S. M. Sze, "Semiconductor Sensors", Wiley-Interscience, 1994 5. C. Mathew Mate, "Tribology on the Small Scale" Oxford University Press, 2008 6. Nicholas D. Spencer, "Tailoring surfaces", World Scientific IISC Press, 2011
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Learning Assess	ment			A PYV	LATER AND STREET	1344							
	Dloom's			Conti	nuous Learning Asse	Final Examination	n (FOO/ weightege)						
	Bloom's Level of Thinking	CLA -	1 (10%)	CLA –	2 (15%)	CLA -	3 (15%)	CLA – 4	4 (10%)#		n (50% weightage)		
	Level of Thirking		Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice		
Level 1	Remember	30 %		30 %	THE PROPERTY.	30 %	* 12 C 10 C	30 %		30%			
Level I	Understand	30 /		30 /6	12.00	30 /6		30 /6		30%	-		
Level 2	Apply	40 %	- M	40 %	d Wester	40 %	AND CO. YES	40 %		40%	_		
Level 2	Analyze	40 70		40 70		40 /0	10000000000000000000000000000000000000	40 70		7070	_		
Level 3	Evaluate	30 %		30 %		30 %		30 %		30%			
Level 3	Create	30 %		30 %		30 %	224/7-170	30 %		30%	-		
	Total	10	00 %	10	0 %	10	0 %	10	0 %	100 %			

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Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
1. Dr. Shinji Yamada, Kao Corporation, Tokyo, Japan, Yamada.s@kao.co.jp	1. Dr. M. Balasubramanian, IIT Madras, mbala@iitm.ac.in	1. Dr. S. Yuvaraj, SRMIST
2. Dr.Sridhar M. R, Senior Engineer, GE Global Research, Bangalore, India.	2. Dr. M. S. Ramachandra Rao, IIT Madras, msrrao@iitm.ac.in	2. Dr. Kiran Mangalampalli, SRMIST

Cour Cod		18NTE305T		Course Name	NANOTECHNOLOGY LE	EGAL ASPECTS		ourse		Ε				Profes	sional	Electi	ive Co	urse				L 3	T 0	P 0	C 3
	equisite urses	Nil		Co-requisit Courses	e Nil				ogress Course		Nil														
Course	Offering D	Department Nanotechn	ology		Data Book	/ Codes/Standards		Nil																	
Course	Learning	Rationale (CLR): The purpose	e of learning	g this course is	to:	All India	Ħ	10	earnin	ıa.		Ħ			Pro	aram	Learni	na Ou	tcome	ae (DI	O)				
	•				10.					_		.					Leann			•		40	40		-
CLR-1:		arize with the concept of patent a						1	2	3		1	2	3 4	5	6	7	8	9	10	11	12	13	14	15
CLR-2:		stand the concept of trade mark, t						Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)		ge		=					돗		Ф				
CLR-3 :								8	ρ	ent		T Engineering Knowledge		Design & Development Analysis, Design, Besearch	e				Individual & Team Work		Project Mgt. & Finance	_			
CLR-4 :								Dg (cie	Ĕ		ا م	Sis -	이 네	sac	<u>le</u>			am	_	Ë	Learning			
CLR-6:			e concept of taxation, trad <mark>e, security</mark> , privacy, export import of nanomaterials					iż	rofi	ttai		2	aly	eve		III.	± ≥	7	Le Te	atio	∞ŏ	eari			
CLIN-0.	Onders	stand the concept of taxation, trac	ie, security,	privacy, expor	t import of fianomaterials			드	Р	φ		<u> </u>	Problem Analysis	Design & Developn Analysis, Design, Besearch	Modern Tool Usage	Society & Culture	Environment & Sustainability		a 8	Communication	Mgt	g L			
						CONTRACTOR OF THE PARTY OF THE		evel of	cte	cte			e	gn	E L	ety	in in	တ္တ	ign	E	덩	Life Long	-		د
Course	Learning	Outcomes (CLO): At the end	<mark>of this c</mark> ours	se, learners wil	l be able to:		4.0	eve	хре	xpe		ng	<u>6</u>	nal	ğ	OCİ	nvi ust	Ethics	ρĺ	E O	ŢŌ.	<u>ie</u>	PSO	PSO	PSO
CLO-1 :	Δοσμίτ	e the concepts of patent and cop	vright laws	Project 1		THE RESERVE		2	80	75	V .	Н		H M	. <u>2</u>	M	М М	H	H	Н	М	Н	Н		Н
CLO-2 :		the knowledge of trade mark <mark>, trac</mark>		d IP infringeme	ent	The Bully You		2	75	70				M M	М	M	M	H	М	H	M	Н	М		М
CLO-3: Get familiarize with the government policies and rules related to nanotechnology						1		2	75	70			M	Н Н	Н	Н	Н	M	Н	H	Н	Н	М		Н
	CLO-4: Acquire the knowledge on environmental degradation and current regulations					West Control		2	80	75				M M	Н	Н	Н	H	Н	Н	М	Н	M		H
CLO-5		miliarize with the current soc <mark>ial a</mark>						2	80	75				M M	Н	М	М	Н	М	Н	М	Н	Н		Н
CLO-6:		the knowledgeof taxation, tra <mark>de, s</mark>						2	80	75			М	м н	Н	М	М	Н	Н	Н	Μ	Н	Н	М	Н
Du	ration							100			-	-		=											
	nour)	9			9		9							9							9				
S-1	SLO-1	Introduction			licies and rules	Environmental degra								anotechi				Trade	and b	busine	ss in	nano	techn	ology	
3-1	SLO-2	Patents		Quality of infori	mation	Current environment	tal regui	lations	S	ı	Econoi	nic in	npact	of nanot	echnol	logy		Trade	restri	ictions					
S-2	SLO-1	Patentability requirements – strupatent	ucture of	Food and drug	s evaluation method	Classification					Implica	tions	of na	notechno	ology			Taxatı	ion sy	stem					
	SLO-2	Utility patent		Food and drug		Sources of pollutants	S			į,	Effect of	n the	qual	ity of lif <mark>e</mark>				Taxati	ion of	goods	s too	small	to be	seen	
S-3	SLO-1	Design patent, monopoly power	s (Classification c	f medical products	Pollution – air					Short t	erm ii	mplica	tions				Laws							
3-3	SLO-2	licensing strategies and arrange	ements 3	<mark>Safe</mark> workplace		Pollution – water					Long te	rm ir	nplica	tions				Rights	of ne	ew life	form				
	SLO-1	Classification of patent applicati	ions S	Self-regulation	Valley to the NAS	Industrial waste water	er			W.	Ethical	issue	es in n	anotech.	<mark>nol</mark> ogy	/		Gover	nmen	nt surv	eillan	се			
S-4	SLO-2 Willful infringement issues, claim scope Liability – responsibility of a scientist			Control and quality c	heck				Social and environmental issues in nanotechnology							Privac	y viol	ations							
0.5	SLO-1	Reexamination of patents	(Civil laws		Dispersion methods					Artificia							Secur	ity an	d mon	itorin	g			
S-5	SLO-2	Patent treaties	(Crimin <mark>al laws i</mark> i	nanotechnology	Monitoring								intellect	5			Eaves							
S-6	SLO-1	Copyright laws – fixation	1	Neglige <mark>nce to I</mark> duty causation	nanotechnology – breach of						Nanote	chno	logy a	nd life e	xtensi	on		R&D i			nolog	ЭУ			
3-0	SLO-2	Originality, creativity	á	and defense	nanotechnology – damage	Solid waste – industrial			Nanotechnology for national security						R&D regulation										
S-7	SLO-1	Integrated circuit topographies		Risk associate	d with nanopa <mark>rticles</mark>	Hospital waste					Nanote	chno	logy f	or space	explo	ration		Curre	nt indi	ustrial	desi	gn lav	/S		
3-1	SLO-2	Industrial designs, artistic work -	- 1	Nanoparticles (ise and effects on health	Hazardous chemical	waste				Nanote	chno	logy f	or medic	al app	licatio									

		arrangement of atoms				
S-8	SLO-1	Technology transfer	Liability for nanoparticles side effects	LOVICITY DESITE ISSUES	Moral issues of Nanotechnology applications	Export – import regulations
3-0	SLO-2	Trademarks	Role and responsibilities	Safety issues	Public perception of Nano-technological risk	Crimes using Nanoparticles
S-9	SLO-1	Trade secrets	Class action	Risk assessment and analysis	Education of public about Nanotechnology	Corporate criminal liability,
3-9	SLO-2	Ownership of IP	Certification Certification	Responsibility and rules	Training of public about Nanomaterials	prevention and detention

Learning Resources 1. Patrick M. Boucher, "Nanotechnology: Legal aspects" CRC press, 2008 2. Fritz Allhoff, Patrick Lin, James Moor, John Weckert, "NanoEthics: The ethical and social implications of nanotechnology" Wiley publication, 2007	3. Louis Theodore, Robert G. Kunz, "Nanotechnology: Environmental implications and solutions" Wiley Publication, 2005
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earning Assess				Contin	uous Learning As	ssessment (50% weig	htage)	10		E 15	(500/ : 1.()
	Bloom's	CLA –	1 (10%)	CLA – 2		CLA -		CLA –	4 (10%)#	Finai Examinatio	n (50% weightage)
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 <mark>%</mark>		30 %	She many	30 %	Year Char	30 %	114-1	30%	-
Level 2	Apply Analyze	40 %	1571	40 %	STATE N	40 %	18 4.00	40 %	1	40%	-
Level 3	Evaluate Create	<mark>30 %</mark>	- In	30 %		30 %	Date of	30 %	-	30%	-
	Total	10	0 %	100	%	100) %	10	0 %	10	00 %

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
1. Dr. Narayanasvamy Vijayan, National Physic <mark>al Labora</mark> tory, nvijayan@nplindia.org	1. Prof. V. Subramaniam, IITM, Chennai, manianvs@iitm.ac.in	1. Dr. Malay Adhikari, SRMIST
2. Dr. Krishna Surendra Muvvala, Saint Gobain Research India, India, Krishna.muvvala@saintgobain.com	2. Prof. D. Arivuoli, Anna University, arivuoli@annauniv.edu	2. Dr. A. Karthigeyan, SRMIST

Cou		18NTE306T	Course Name	LITHOGRAPHIC T	ECHNIQUES AND FAB	RICATION	Cour Categ		Ε				Profe	essiona	al Elec	ctive Co	ourse				L 7	P 0	C 3
	requisite ourses	Nil		Co-requisite Courses	Micro and Nanofabrica	ition		Progres Cours		Nil													
Course	Offering [Department	Nanotechnology		Data Boo	k / Codes/Standards	Ni	1															
						ALC: NA			_	1													
Course	e Learning	Rationale (CLR)	The purpose of le	earning <mark>this course is</mark> to:	15			Learn	ing					Р	rogran	n Leari	ning O	utcome	es (PL	.O)			
CLR-1				rap <mark>hy tools in m</mark> icro/nar			1	2	3	1	1	2	3 4	4	5 6	7	8	9	10	11	12 1	3 14	1 15
CLR-2					hy, its merits and demer		_ [2	(%)	(%		<u>o</u>		-					논		4)			
CLR-3					n beam for lithography a	nd their applications	_ 2	Expected Proficiency (%)	Expected Attainment (%)		□ Engineering Knowledge		Design & Development Analysis, Design,	,	D I			⊤ Individual & Team Work		Project Mgt. & Finance			
CLR-4 CLR-5			knowledge of different		aranhy injection moldin	a and others	_ z	Sien	Jme		Mor	Sis	lop In,	Research	Society & Culture	2		am	_	Fine	Life Long Learning		
CLR-6		e knowledge on aware of VLSI te		ich as nano imprint inno	graphy, injection molding	g and others.	- -		ttail		조	laly	eve	=		t &	≥	L e	atio	∞ઇ	eari		
OLIN-0	. Wake	aware or viorite	connology				į		A b		ering	Ar	ω ω ω	ج ا ج	5 2	mer :	ap	a 8	nic	Mgt	J G		
_						75.00		Expected Proficie	ecte		ine	olen	lgi İysi	ear	ie V	Environment &	s lan	/idu	שור	ect	ر اد ز اد	- -	
Course	e Learning	Outcomes (CLO)): At the end of this	s course, learners will be	e able to:		ð	EX C	Exp		Eng	Problem Analysis	Des	Res	Society & Culture		Sustainability Ethics	ligi	Communication	Proj	El E	PSO - 2	PSO
CLO-1	: Make	use of top-down	approach for micro/na	no fabrication		2.5 The HOLD ST		2 80	75			М	H	1 1	H M	1 M	Н		Н	М	M	1 h	l H
CLO-2	: Analyz	e the limitation o	of masked lit <mark>hography (</mark>	with respect to incident i				2 80		1	Н				1 N			М	Н	М		1 N	
CLO-3			for the creati <mark>on of nan</mark> c		ALC: NAME OF			2 75			Н				1 H			Н	Н	Н		1 h	
CLO-4				n using light and heavy i	ion beams			2 80			М		H I		H H			Н	Н	М		1 h	
CLO-5 CLO-6			ass producti <mark>on replica</mark> ti nanoscale d <mark>evices</mark>	on tools				2 80 2 80		- 1	H				H M			M H	H H	M M		1 h	
CLO-0	. IIIIayii	ie importance or	Tidiloscale devices		The Secretary of the			2 00	13		П	IVI	IVI I	1 1	i lv.	ı ıvı	П	П	П	IVI	п	1 IV	П
Dı	uration		_				-	7															
(hour)		9		9	9							9							9			
0.4	SLO-1	Micro/nano fab	orication	Optical(photo) lithe	ography	Introduction-maskless/o	direct liti	hograpi	hy	lon be	eam lit	thogra _l	ohy (IE	L) typ	es		Micro	/ Nand	replic	cation	tools		
S-1	SLO-2	Top-down & bo	ottom-up approa <mark>ch</mark>	Process steps	N.	Difference between ma lithography	sked an	nd masi	kless	Heav	y and	light io	ns for	lithogr	aphy		Nece	ssity fo	or repl	icatio	n		
0.0	SLO-1	Necessity for c	clean room, types <mark>of cle</mark>	ean Optical lithography	y mask	Advantages and disadv maskless lithography	rantages	s of		Focus	sed io	n bean	n pr <mark>o</mark> pe	erties				cation n/nano			IS/NEN	IS,	
S-2	SLO-2	Construction as room,	nd maintenance of clea	an Mask definition, ar	nd different materials	Principles of electron be (EBL) system	eam lith	ograph	у	Bean	scan	ning					Soft	ithogra	aphy				
	SLO-1	Clean room sta	andards, protocols	Different light sour	rces	Electron properties for I	lithograp	ohy		Resis	ts for	ion bea	am lith	ograph	ıy		PDM	S Casi	ting				
S-3	SLO-2	Lithography- pi	rocess steps	Contact and proxii	mity exposures	Design of electron bear system	n lithogi	raphy		Electi	on lith	ograpi	hy prod	ess fl	ow.		Mold	fabrica	ation f	or sot	t lithogi	aphy	
S-4	SLO-1	Photo resists n characteristics	naterials, types and	Diffraction limit and enhancement met		Operation of electron be system	eam lith	ograph	y	Focus prope		n bean	<mark>ı lith</mark> og	raphy	- Incid	ent ion	Micro	inject	ion mo	olding			
	SLO-2	Spin coating m	nethods	Projection lithogra		É-beam resists				Prince	ple, d	<mark>esi</mark> gn a	and op	eratior)	Hot embossing							
S-5	SLO-1	Exposure dose	9	Extreme UV (EUV	') lithography	E-beam resist properties Masked ion beam structuring: Broad beam patterning				beam Nano imprint lithography NIL principles													
	SLO-2	chemical devel	lopment, optimization	EUV: Scope and c	demerits	Comparison with optical	l lithogr	aphy re		Atom	lithog						Mold fabrication for hot embossing and				nd NIL		
S-6	SLO-1	Etching method	ds, resist and other	Interferometric and	d holographic tools				Mold fabrication for injection molding														

		materials				
-	SLO-2	Dry and wet methods	Lithography masks	Significance of beam blanking	Comparison of electron, proton and gallium for resist patterning	Process flow and requirements
S-7	SLO-1	Wet etching chemicals, Si etching	The state of the s	Patterning resolution comparison with other methods	Limitation and suitability of each technique in comparison with one another	Polymers for imprinting
3-1	SLO-2	Wet etching examples	Synchrotron radiation for lithography processes	EBL for mask preparation	IBL resists, dose calculation and process optimization	Polymer characteristics and performance
S-8	SLO-1	Reactive ion etching	X-ray lithography mask	Nanofabrication with EBL – MEMS	INANOTADRICATION WITH IBI - MEMS	Master mold preparation for replication tools, comparison
	SLO-2	Isotropic and non isotropic etching	X-ray lithography, merits and demerits	Nanofabrication with EBL – NEMS	Nanofabrication with IBL - NEMS	Application-microfluidics
S-9	SLO-1	Types of lithography : classification	Comparison of all masked lithography tools	Nanofabrication with EBL –microfluidics applications	Nanofabrication with IBL –microfluidics applications	Application-nano fluidics
3-8	SLO-2	Introduction to next generation lithography tools		Nanofabrication with EBL – Nanofluidics applications	Nanofabrication with IBL – Nanofluidics applications	Industrial applications

Learning Resources	1.	Chris A. Mack, Fundamental Principles of Optical Lithography: The Science of Microfabrication, John Wiley & Sons, London 2007	2.	Stefan Landis, "Lithography and nanolithography", Published by Wiley - ISTE, 2010	
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earning Assess.	sment				21/22/10/19	10000000	7 10 20 100 100	7 7 /						
	Bloom's		7.00	Conti	nuous Learning Asse	essment (50% weig	ntage)	400		Final Evamination	Final Examination (50% weightage)			
	Level of Thinking	CLA -	1 (10%)	CLA –	2 (15%)	CLA –	3 (15%)	CLA – 4	· (10 <mark>%)#</mark>	Filiai Examinado	iii (50% weigiilage)			
	Level of Thiriking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice			
Level 1	Remember Understand	30 %		30 %		30 %	. J. A. A.	30 %	-	30%	-			
Level 2	Apply Analyze	40 %		40 %	-	40 %		40 %	-	40%	-			
Level 3	Evaluate Create	3 <mark>0 %</mark>	12	30 %		30 %	-	30 %	1 4-	30%	-			
	Total	10	0 %	10	0 %	10	0 %	100) <mark>%</mark>	10	00 %			

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
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2. Dr. Krishna Surendra Muvvala, Saint Gobain Research India, India, Krishna.muvvala@saintgobain.com	2. Dr.N. N. Murthy, IIT Tirupati, nnmurty@iittp.ac.in	2. Dr. P. Malar, SRMIST

Cou		18NTI	E307T	Course Name	SENSORS ANI	D TRANSDUCERS		Cours	e Cate	gory		Е		Profe	ssional	Electi	ve Co	ourse		L 3	T 0	P 0	C 3
	requisite ourses	Nil		Co-requis Courses			Progre Cour		Nil														
Course	Offering D	Department	Nanotechnology		Data Book	k / Codes/Standards	Nil																
Course	Learning	Rationale (CLR):	The purpose of learni	ng t <mark>his course</mark> i	is to:		Learn	ing					Pi	ogram	Learni	ng Ou	tcome	es (PL	.O)				
CLR-1			s and characteristics o		ransducers		1 2	3		1	2	3	4 5	6	7	8	9	10	11	12	13	14	15
CLR-2			nical and electrom <mark>echa</mark>				(m) (%)	8		Φ							논		45				
CLR-3			al sensors and it <mark>s types</mark>			Contract to the second) (한) (한)	ıt (edg		ne l		1)			Wol		nce				
CLR-4			sors and radiatio <mark>n sens</mark>	ors	<u> </u>		g (F	me		No	<u>.s.</u>	odo L		<u>e</u>			am		i.	Learning			
CLR-5		nowledge on electro			1 " "	and the second second	를 를 등	ta:		조	alys	evel skin			د د ک		Teg	tion	∞	arn			
CLR-6	: Apprei	nena knowieage on i	recent trends <mark>in sensor</mark>	technologies a	nd applications		I E G	¥		ring	Ā	عٌ احّ	ے ا	3 0	ne i		چ ا	ica	∕lgt.	J Le			
Course	Learning	Outcomes (CLO):	At the e <mark>nd of this c</mark> ou	ırse, learners w	ill be able to:	1000	Level of Thinking (Bloom) Expected Proficiency (%)	Expected Attainment (%)			Problem Analysis	Design & Development Analysis Design	Research Modern Tool Heads	Society & Culture	Environment & Sustainability	Ethics	Individual & Team Work	Communication	Project Mgt. & Finance	Life Long I	PS0 - 1	PS0 - 2	PSO - 3
CLO-1	· Analyz	e calibration technio	ues and <mark>signal typ</mark> es o	f sensors	FF4:37	THE RESERVE TO SERVE THE PARTY OF THE PARTY	2 80	75		Н	M		H F	i M	M M	Н	H	Н	M	М	Н	Н	Н
CLO-2			of Senso <mark>rs & Tran</mark> sduc		orking principles	The Park of the Pa	2 80		TO I	Н			Η Л		M	H	М	Н	М	М	M	M	М
CLO-3			racteristi <mark>cs of diffe</mark> rent			12 A 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	2 75			Н			H F		Н	М	Н	Н	Н	М	Н	Н	Н
CLO-4			ed perfor <mark>mance of</mark> vario		A PROPERTY OF	Will be a real	2 80	75		М			M F		Н	Н	Н	Н	М	Н	Н	Н	Н
CLO-5	: Develo	pp advance techniqu	es in se <mark>nsor tech</mark> nolog	у	The Control of the Co	TOWN THE THE	2 80			Н	М	Н	H F	I M	М	Н	М	Н	М	Н	Н	Н	Н
CLO-6	: Devise	smart sensors for re	eal time <mark>applicatio</mark> ns				2 80	75		Н	М	М	H F	I M	М	Н	Н	Н	Μ	Н	Н	Μ	Н
_		T			10/20/20/20/20																		
	iration hour)		9	5	9	9	11.55	la d				9							9				
S-1 +	SLO-1	Measurements-Bas measurement	sic metho <mark>d of</mark>	Mechanical ar Resistive pote	nd electro <mark>me</mark> chanical sensor entiometer	sensors			Magne	etic se	nsors.	-Introd	luction			Electro	oanal	ytical .	sens	ors-in	troduc	tion	
3-1	SLO-2	Errors		Strain gauge	1	Thermal expansion type the sensors	ermometrio		Princip	les b	ehind		м			Electro							
S-2	SLO-1	Classification of en	rors	Inductive sens	sors	Acoustic temperature sens	or		Yoke o	oil se	nsors					Senso electro		ctrode	s-Mo	lecula	r sele	ctive	
3-2	SLO-2	Error analysis		Sensitivity and	d linearity of sensor	Dielectric constant and refithermosensors	active inde	x of	Coaxia displac	ceme	nt sens	sors			ChemFET								
S-3	SLO-1	Statistical methods		Ferromagnetic	c plunger type transducers	Helium low temperature the Nuclear thermometer	ermometer		Magne magne					sotropi		Recen						-	
	SLO-2	Sensors/Transduce	ers-Introduction	Electromagne	<mark>tic t</mark> ransducer	Magnetic thermometer			Semic	ondu	tor ma	agneto	resisto	rs		Film s	ensor	's- Thi	ick ar	nd thir	film s	senso	rs
S-4	SLO-1 Principles of Sensors/Transducers Magnetostrictive transducer Resistance change type them sensors			ermometrio		<u>Active</u>							Semic										
3-4	· ·			Metal resistance thermome	rmometric sensors Hall effect sensor-sensor geometry and fabrication Micro electro mechanical micromachining				cal sy	stem	(MEM	S)-											
S-5	SLO-1	LO-1 Static Characteristics of Sensors/Transducers Parallel plate capacitive sensor The			Thermistors			Variable inductance sensors					Some application examples										
	SLO-2			Serrated plate	Thermo emf sensors		Eddy current sensors Nanosensors																

		detectable signal				
S-6	SLO-1	Threshold-Sensitivity-Selectivity and specificity-Non-linearity	Variable thickness dielectric capacitive sensor	Materials for thermo emf sensors	Radiation sensors-Introduction-basic characteristics	Onboard automobile sensors-flow rate sensors-pressure sensors
3-0	SLO-2	Hysteresis-Output impedance-isolation and grounding	Stretched diaphragm variable capacitance transducer	E (emf)-T(Temperature) relations	Types of photoresistors/photodetectors	Temperature sensors-oxygen sensors
S-7	SLO-1	Dynamic Characteristics	Electrostatic transducer	Thermosensors using semiconductor devices	Photoemissive cell and photomutliplier	Torque and position sensors
	SLO-2	Zero order and First order sensors	Piezoelectric elements	Thermal radiation sensors	Photoconductive cell-LDR	Home appliance sensors
	SLO-1	Second order sensors	Piezoelectric materials	Detectors	Photocurrent	Aerospace sensors-Fluid velocity sensors
S-8	SLO-2	Electrical characterization	Deformation modes and multimorphs	Pyroelectric thermal sensors	Photoresistors and photoFETs and other devices	Sensing direction of air flow- Monitoring strain, force, thrust and acceleration
	SLO-1	Mechanical and thermal characterization	Lead zirconatetitanate (PZT) family	Quartz crystal thermoelectric sensors	Fibre optic sensors	Medical diagnostic sensors
S-9	SLO-2	Optical characterization- Chemical/biological characterization	Force/stress sensors using quartz resonators	Heat flux sensors	Temperature sensors-microbend sensors	Sensors for environmental monitoring

Learning	1.	Ernest O Doebelin, "Measurement Systems – Applications and Design", 4th ed., Tata McGraw-Hill, 2009	3.	D. Patranabis, Sensors and Transducers, 2 nd ed., Prentice Hall of India, 2010
Resources	2.	John P. Bentley, "Princip <mark>les of Me</mark> asurement Systems", 4 th ed., Pearson Education, 2000.	4.	D.V.S Murthy, Transducers and Instrumentation, 2nd ed., Prentice Hall of India, 2001.

Learning Assessr	ment				THE RESERVE						
	Bloom's			Contir	nuous Learning Asse	essment (50% weig	htage)	20 / 10		Final Evamination	o (E00/ woightage)
	Level of Thinking	CLA –	1 (10%)	CLA – 2	2 (15%)	CLA –	3 (15%)	CLA – 4	(10 <mark>%)#</mark>	Filiai Examinatio	n (50% weightage)
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %	- E	30 %		30 %		30 %	-	30%	-
Level 2	Apply	40 %		40 %		40 %	BUILTING TO	40 %		40%	
Level 2	Analyze	40 %		40 %		40 %		40 %		40%	-
Level 3	Evaluate	30 %		30 %		30 %	-	30 %		30%	-
	Create Total	10	0 %	100	0/	10	0 %	100) 0/	10	0 %
	าบเลเ	10	U /0	100	/0	10	0 /0	100	/0	10	U /0

[#] CLA - 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
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2. Dr.Shyam Sunder Tiwari, Sensors technology Private Limited, India, sst@sensorstechnology.com	2. Dr. M. S. Ramachandra Rao, IIT Madras, msrrao@iitm.ac.in	2. Dr. A. Karthigeyan, SRMIST

Co.	irse de	18NTE308T		Course 2-D LAYERED N	ANOMATERIALS		ourse I <mark>tegory</mark>		Ε			Pi	ofessi	onal E	lectiv	e Cou	rse				L 3	T 0	P 0	C 3
	requisite ourses	Nil	Co-red Cou					gressi ourses		iil														
Cours	e Offering I	Department Nanotechnol	ogy	Data Book	k / Codes/Standards		Nil																	
Cours	e Learning	Rationale (CLR): The purpose of	of learning <mark>this cour</mark>	se is to:			Lea	arning	1	Г	Ħ			Progr	am L	earnir.	ng Ou	tcome	s (PL	-O)				
CLR-1	: Under	standing the electronic properties of	f 2D m <mark>aterials, es</mark> pe	cially Graphene			1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		e knowledge on the different synthe		4.1	The state of the s		(m	(%	98	Φ								ᆠ						
CLR-3	: Descri	be the difference in various propert	ie <mark>s of 2D-laye</mark> red st	ructure	AND IN TARREST		000))	1	gp		ieni		-				Work		Finance				ı
CLR-4		fication of 2D layered Nanomaterial			STEWNSON.) (E	euc	ner	W/e	S	ppr		age	Φ.			E		in a	ng			ı
CLR-5	: Gain k	nowledge on application of layere <mark>d</mark>	Nanomaterials				Ř.) Jici	aju	Ş	İŞ	velc	iĝ	N		જ ્		Team	ы	∞ π	in i			ı
CLR-6	: Under	stand the principles of various <mark>char</mark> a	<mark>acterizat</mark> ion tools to	study the properties of 2D mater	rials		Thinking (Bloom)	Pr	HE	D D	Ana	De	Design,	00	Culture	ent		~გ	cati		Learning			ı
					4.55 S. 14		of T	ted	ted	eri	Ē	۵۲	/sis, l arch	T	∞ >	nm nab		na	Ē	₹	bug	-	7	က
Cours	e Learning	Outcomes (CLO): At the end of	<mark>this c</mark> ourse, learner	s will be able to:	15/11/	4.3	Level of	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	Problem Analysis	Design & Development	Analysi: Resear	Modern Tool Usage	Society	Environment & Sustainability	Ethics	Individual &	Communication	Project Mgt.	Life Long	PSO-	PSO-	PSO -
CLO-1	: Apply	the concept of atomic and ele <mark>ctroni</mark>	<mark>c str</mark> ucture to under	stand the physical and chemical	properties of graphene		2	80	75	М	Н	Н	Н	Н	М	М	Н	Н	Н	М	Н	Н	Н	Н
CLO-2	: Utilize	the procedure to synthesize layere	<mark>d m</mark> aterials and the	concept of Raman spectra over	synthesized materials	-	2		70	М	Н	Μ	Н	М	М	М	Н	М	Н	М	Н	М	М	М
CLO-3	: Utilize	the spectroscopic concepts to anal	<mark>yze</mark> the properties o	f layered materials			2		70	М	Н	Н	Н	Н	Н	Н	М	Н	Н	Н	Н	Н	Н	Н
CLO-4	: Apply	the concept and the uses of <mark>semicc</mark>	<mark>nd</mark> ucting and metal	dichalcogenides based material	ls		2	80	75	М	Н	Н	М	Н	Н	H	Н	Н	Н	Μ	Н	Н	Н	Н
CLO-5	: Utilize	the application of layered materials	in various fields.	T			2	80	70	Н	Н	Н	Н	Н	М	M	Н	Μ	Н	Μ	Н	Н	Н	Н
CLO-6	: Utilize	the concept of sensor to analyze th	<mark>e </mark> material nature.	Mark State of	Hill San Marie	- 1	2	80	75	М	Н	М	Н	Н	М	М	Н	Н	Н	Μ	Н	Н	Μ	Н
D	uration					0	100				Ŧ													—
	(hour)	9		9		9							9							9				
S-1	SLO-1	Introduction of graphene		n to Scotch-tape method hanical cleavage)	Introduction to X-ray spectroscopy	photoe	missioi	n	Gr	aphene	and i	ts pro	perties	3		li	ntrodu	ıction	to Ga	as sei	nsors			
3-1	SLO-2	Vander Walls force	Preparation method	n of graphene using Scotch-tape	Limitation and applica	ation of	XPS		Ре	nta-gra	ohene	and	its pro	p <mark>erties</mark>			Gas se sensoi	•	med	hanis	sm an	d type	s of	
	SI O-1	Covalent bond	Introduction	n and principle of Chemical	Introduction to X-ray	diffract	ion stu	dv	h-l	3N strue	ture	svnth	esis ar	nd pror	nertie	, (Chemi	ical se	neor	۰				

Introduction to X-ray diffraction study

Limitation and application of optical

Introduction and limitations of Scanning

Limitation and application of XRD

Introduction to Optical absorption

Measuring mechanical properties

absorption spectroscopy

1806

Tunneling Microscopy

spectroscopy

SLO-1

SLO-2

SLO-1

SLO-2

SLO-1

SLO-2

SLO-1

S-2

S-3

S-4

S-5

Covalent bond

freedom

SLO-2 Band structure

Dimension of carbon allotrope

Crystal plane of 2D graphene

Electronic structure of graphene

Free standing model

Transition of metal dichalcogenides

Manipulation of quantum degree of

vapor deposition

solution exfoliation

exfoliation

Preparation of graphene by CVD

Introduction to Solution-exfoliation

Introduction to Solution-exfoliation

Preparation of 2D layered material by

Preparation of graphene using solution-

h-BN structure, synthesis and properties

SiC structure, synthesis and properties

Si structure, synthesis and properties

Application of h-BN

Application of SiC

Application of Silicon

Chemical sensors

Uses smart materials in sensors

2D materials based membranes

Uses of 2D materials in enhance the

Application of membrance

Oxygen reduction reaction

activity

						production
S-6	SLO-1	Fermi levels in graphene	Principles of Raman spectroscopy	Introduction and limitations to VSM analysis	Types of oxide materials	Electronic devices
3-0	SLO-2	Carrier density	Limitations of Raman spectroscopy	Magnetic properties	Properties of oxide materials	Difference between electronic and electric device
S-7	SLO-1	Role of defect and dopant	Raman spectrum of graphene	Types of interactions	Introduction and types of transition metal dichalcogenides	Optical materials
	SLO-2	Electronic structure of graphene	Analysis of D band Raman spectra	Catalytic properties	Introduction and application of MoS₂	Solar absorber materials
	SLO-1	Tensile strength	Analysis of G band Raman spectra	Metal support interactions	Introduction and application of VS ₂	Magnetic devices
S-8	SLO-2	Physical properties of graphene	Raman shift dependence on number of layer	Changes in the properties due to metal support interaction	Introduction and application of WS ₂	Materials used
	SLO-1	Functional properties of graphene	Raman shift dependence on defect	Non-metal support interactions	Introduction of Si2BN and its application	Types of magnetic devices
S-9	SLO-2	Chemical properties of graphene	Raman shift dependence on doping concentration	Difference in properties due to non-metal support interactions	Introduction of BCN and its applications	Applications of magnetic devices

	1.	Houssa, Michel, Athanasios Dimoulas, and Alessandro Molle, "2D Materials for Nanoelectronics" - CRC Press,	3.	Tiwari, Ashutosh, and Mikael Syväjä <mark>rvi, eds. "A</mark> dvanced 2D Materials" - John Wiley & Sons,
Learning		2016.	100	2016.
Resources	2.	Banks, Craig E., and Dale AC Brownson, eds. "2D Materials: Characterization, Production and Applications"-	4.	Dragoman, Mircea, and Daniela Dragoman,"2D Nanoelectronics: Physics and Devices of
		CRC Press, 2018.		Atomically Thin Materials"- Springer, 2016.

Learning Assess	ment				The state of the state of	WARRIED TO					
	Bloom's			Conti	nuous Learning Ass	essment (50% weig	htage)	39		Final Evaminatio	n (FOO) weighters)
	Level of Thinking	CLA –	1 (10%)	CLA -	2 (15%)	CLA –	3 (15%)	CLA – 4	· (10%)#	Final Examinatio	n (50% weightage)
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %		30 %	Birth.	30 %		30 %	-	30%	-
Level 2	Apply Analyze	4 <mark>0 %</mark>	12	40 %		40 %	S. Carrier	40 %		40%	-
Level 3	Evaluate Create	30 <mark>%</mark>	P.S.	30 %	- 1/	30 %	-	30 %	<u>-</u>	30%	-
	Total	10	0 %	10	0 %	100	0 %	100	%	10	00 %

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Cou		18NTE309T	Course Name	SUPRAMOLECUI	AR SYSTEMS		ourse tegory	/	Ε				Profess	sional	Electiv	ve Col	urse				L 3	T 0	P 0	C 3
	requisite ourses	Nil	Co-requisite Courses	Nil				gress ourse		Nil														
Course	Offering [Department Nanotechnology		Data Book	/ Codes/Standards	1	Nil																	
					ALLANA																			
Course	Learning	Rationale (CLR): The purpose of learn	ing <mark>this course</mark> is to:	1. 2.			Le	arnin	g					Pro	gram I	Learni	ng Ou	tcome	s (PL	•				
CLR-1		e the concepts of supramolecular chemis <mark>tr</mark>						2	3		1 2	2 3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		designing new materials of metal-organic	frame works				(Bloom)	Expected Proficiency (%)	9		υ							논		4				
CLR-3		be the concept of nanostructured objects			and in the later		300	<u>ئ</u>	nt (S C	nen		(I)				Mo		nce.				l
CLR-4		stand the principles of supramolecul <mark>ar chir</mark>	ality) g	ië.	me		5 .	Si Jao	_ c	sag	<u>e</u>			E	_	i⊒	ing			
CLR-5		nowledge on host-guest complexes	ur daviaca and infinita	multinomenoment avatar			ş	jje	Itair	2		al y	esig	Š	ultu	± ≥		ĕ	ţi	∞	ar			
CLR-0	: Unaer	stand the principles sophisticated <mark>molecul</mark> a	ir devices and iminite	municomponent system	18		Thinking (d P	d A		5	Z Z	ے کے	100	8 C	ner abili		<u>چ</u>	<u> </u>	Mgt	g Le			
					1000	-	o	octe	Expected Attainment (%)		Englineeming Knowledge	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society & Culture	Environment & Sustainability	တ္တ	Individual & Team Work	Communication	Project Mgt. & Finance	Life Long Learning	PS0 - 1	- 2	- 3
Course	Learning	Outcomes (CLO): At the e <mark>nd of this c</mark> o	urse, learners will be	able to:		A 14	evel	xpe	xpe		5	lon jesi	Inal	bol	oci	invii	Ethics	ĕ	E	ō	<u>le</u>	SO	PSO	PSO
CLO-1	: Recog	nize the main types of supram <mark>olecular</mark> ass	emblies	100	A DOMESTIC OF THE PARTY OF THE		2	80	75		1 A			H	M	Ш O) M	Н	<u>=</u>		M	Н	Н	Н	Н
CLO-2		the importance of the bottom <mark>-up appro</mark> ach		(nanoscale) systems	W. C. C. C.			80	70			1 M		М	М	М	Н	М		М	Н	М	М	М
CLO-3		the main supramolecular forces involved				77		75	70		1 A			Н	Н	Н	М	Н	Н	Н	М	Н	Н	Н
CLO-4	: Analyz	e and understand the interm <mark>olecular f</mark> orce	s to rationalize the fo				2	80	75		1 H	1 H	М	Н	Н	Н	Н	Н	Н	М	Н	Н	Н	Н
CLO-5		te the needs of sustainable f <mark>uture, de</mark> velo _l				117.7		80	70		1 A			Н	М	М	Н	М	М	М	М	Н	Н	Н
CLO-6	: Apply	through feasible approaches <mark>, and ass</mark> emb	e with the prior know	ledge to fabricate novel	designs/architectures		2	80	75		√ ∧	1 M	H	М	M	М	Н	Н	Н	М	Η	Η	М	М
D.					-		-	-				-												
	uration hour)	9		9				e de la			И		9							9				
S-1	SLO-1	Basic concepts and principles of supramolecular chemistry	Introduction to cool	rdination chemistry	Biological inspiration to the chemistry	or sup	ramole	ecula	ar	Supran	olecu	lar Ch	irality				Specia	al Clas	ss Mai	terial	s			
5-1	SLO-2	Classification of supramolecular compounds	Hosts for cation bir	nding	Alkali metal cations in	bioche	emistr	у		Chiralit	ıin Se	elf-Ass	embled	Syste	ems		Birth o		w ma	crom	olecu	lar ch	emist	ry
S-2	SLO-1	Host-guest compounds	Cation receptors		Co-ordination Polyme	rs				Chiralit	of H	ost-Gu	iest C <mark>ol</mark>	<mark>np</mark> our	nds		Ration	al De	sign					
5-2	SLO-2	Receptors, coordination compounds	Crown ethers		Clathrates								red S <mark>ys</mark>				Molec							
S-3	SLO-1	Lock and key analogy	Cryptands	41 11 19	Cavitands								ne <mark>wor</mark> ks		=s)		Artifica							
0-0	SLO-2	Binding constants	Spherands -		Binding by cavitands					Covale	nt Org	anic F	ramew	orks			Supra							
S-4	SLO-1	Cooperative effect	Calixarens		Cyclodextrins	Œ.		1		Polymo	rphisr	n					The pa	endroi	าร					
J -4	SLO-2	Chelate effect	Selectivity of cation		Cucurbituril				,	Solvate	s						Suprai dendri	mers					drons	and
	SLO-1	Thermodynamic selectivity	Macrocyclic effects	3	Porphyrins and tetrap	yrrole i	macro	cyles	S	Co-Cry	stals						Synthe							
S-5	SLO-2	Kinetic selectivity and discriminations	Template effects		Transport processes					Princip	es of	suprar	nolecul	ar Exti	action	n 1	Chara structu		ation c	of dei	ndritic	archi	itectui	al
S-6	SLO-1	Nature of supramolecular interactions	Host for anion bind	ling	Dynamic Combinatori	al cher	mistry			Extract equilibr		hniqu	e, the e	xtracti	on		Nanon	nedica	al and	adva	anced	mate	rials	
	SLO-2	Solvation effects	Concepts in anion	host design	Supramolecular featu	res of p	olant			Examp	es of	suprar	nolecul	ar exti	action	7	Diagno	ostics	and a	dvar	nced ii	nagin	ng	

				photosynthesis		
S-7	SLO-1	Hydrophobic effects	Anion receptors	Uptake and transport of oxygen by haemoglobin	I Binding Constant	Characterization of dendritic architectural structures
3-1	SLO-2	Supramolecular concepts and design	Shape and selectivity	Enzymes and coenzymes	Binding constant determination by UV/Vis spectroscopy	Nanoscience applications
S-8	SLO-1	Hydrogen bonding and supramolecular interactions	Neutral receptors	Neurotransmitters and hormones	Instrumentation of mass spectrometry, Limitations of mass spectrometry	Molecular and Supramolecular devices
3-0	SLO-2	Secondary Electrostatic Interactions in Hydrogen Bonding	From cation host to anion host – a simple change in pH	Enzymes, Metallobiosites	Scanning probe microscopes: - scanning electron microscopy	Molecular Electronic Devices
	SLO-1	Molecular recognition	Hosts for binding of neutral guests	Heme analogues	Transmission electron microscopy	Switches
S-9	SLO-2	Types of recognition	Inert metal- containing receptors	Semiochemistry in natural world, Biochemical self-assembly	Confocal laser scanning microscopy	Molecular Machines

Learning	1. Jonathan W. Steed and Jerry L. Atwood, "Supramolecular Chemistry"J. Wiley and Sons; 1st Ed. 2000	3. Donald A. Tomalia, Jørn B. Christensen, Ulrik Boas, "Dendrimers, Dendrons, and Dendritic
Resources	2. J.M. Lehn, Supramolecular Chemistry, VCH, Wiley and Sons, 1st Ed. Weinheim, 1995	Polymers: Discovery, Applications and the Future", MPG books group, UK, 2012

Learning Assess	sment			4000	2010年1月17日	377 321	21 NO.				
	Bloom's			Con	tinuous Learning As	sessment (50% wei	ghtage)			Final Examination	n /FO0/ woightage)
	Level of Thinking	CLA -	- 1 (10%)	CLA –	2 (15%)	CLA -	3 (15%)	CLA – 4	(10 <mark>%)</mark> #		n (50% weightage)
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %	3 10	30 %		30 %		30 %	-	30%	-
Level 2	Apply Analyze	40 %	4 E	40 %		40 %	115 P	40 %	-	40%	-
Level 3	Evaluate Create	30 %		30 %	Direct Control	30 %	20 - IN	30 %		30%	-
	Total	1	00 %	10	0 %	10	0 %	100	0 %	1(00 %

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
1. Dr. P. Sudhakara, CLRI – CSIR, Jalandhar, sudhakarp@clri.res.in	1. Dr. Kothandaraman Ramanujam, IITM Chennai, rkraman@iitm.ac.in	1. Dr. Angeline Little Flower, SRMIST
2. Dr. Sudhakar selvakumar, CSIR-Central Electrochemical Research Institute, ssudhakar79@gmail.com	2. Dr.Arthanreeswaran, NIT, Trichy,arthanareeg@nitt.edu	2. Dr. S. HariniPriya, SRMIST

Cour Cod		18NTE310T Cour	rse Name		ME	MS and NEMS				Course atego		Е					Prof	essior	al El	ective					L 3	T 0	P 0	C 3
Co	equisite urses	Nil		Co-requisite Courses	Nil					(ogres Cours		Nil															
Course	Offering D	Department Nanc	otechnology			Data Bo	ook / C	Codes/Standards	1	Nil																		
								ALC: N	_				1 [
			·	ig <mark>this course is t</mark> o	o <i>:</i>	100				- 1	earnir	_						Prog		Learnii				· ·				
CLR-1:		what are MEMS? and wher			- 1					1	2	3	1	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		stand the basics of fabricati					and n	nodeling		of Thinking (Bloom)	(%)	(%)		ge		¥						폱		a)				l
CLR-3 : CLR-4 :		stand the principles of sensi e magnetic materials for sui			nicai sy	ystems	11/5			l 읇	JC/	ent		/led		mer		e e				×		Finance				i
CLR-5 :		nowledge on thermal, micro				_		2010 175		ing	iciel	i.		Nou	Sis	dole	gu,	Jsac	an	_ •		am	_	뜶	ini			ı
CLR-6:		e knowledge on the fabricat			ions of	RF. optical, MEI	MS Ur	nderstand the		i X	Ju	∖ttai		gK	nal)eve	lsə(ol L	SET	nt 8		× =	atio	∞ŏ	-ear			l
0 = 11 0 1	1 4	<u> </u>				, , , , , , , , , , , , , , , , , , , ,			75.	Ė	ed F	pe /		erin	μ	∞ .	S, L	o To	8	mre labi		la c	unic	Mg	ng L	_	2	က
Course	Learning	Outcomes (CLO): At the	e e <mark>nd of this c</mark> our	rse, learners will b	oe able	to:	100			evel o	Expected Proficiency (%)	54 Expected Attainment (%)		□ Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society & Culture	Environment & Sustainability	Ethics	□ Individual & Team Work	Communication	Project Mgt.	Life Long Learning	PS0 - 1	PSO - ;	PSO - (
CLO-1	Utilize	mechanics principles to an	alyze the mechai	nical performance	of mic	crosystems.	777	The House		2	80	75		H	M	Н	Н	H	M	M	Н	H	Н	М		H	H	H
CLO-2		optics, electrical and mecha					rmanc	e of MOEMS	State of the	2	80	70	177	Н	М	М	Н	М	М	М	Н	М	Н	М		М	Μ	М
CLO-3	Use the	e radio frequency and therr	m <mark>al principl</mark> es to a	analyze the perfo	rmance	of RF and therr	mal Mi	EMS		2	75	70		Н	М	Н	Н	Н	Н	Н	М	Н	Н	Н	М	Н	Н	Н
CLO-4:		agnetic and fluid principles			gnetic	MEMS and micro	rofluidi	c devices	7.00	2	80	75		М	Н	Н	М	Н	Н	Н	Н	Н	Н	М	М	Н	Н	Н
CLO-5		re the tools and processes ι				17/11/2014				- 2	80	70		Н	М	Н	Н	Н	М	М	Н	Μ	Н	Μ		Н	Η	Н
CLO-6	: Apply t	the principles of physics to a	analyze and desi	ign MEMS, includ	ling ser	nsors and actuate	tors.			2	80	75		Н	М	М	Н	Н	М	М	Н	Η	Η	Μ	М	Н	Μ	Н
D																-	ъ.											
	ration nour)	9			9	N. W.Y.			9			4.10				9			i					9				
S-1 -	SLO-1	Micro and nanoelectro me systems (MEMS and NEM	NS)	Photolithography		100		Principles <mark>of sensi</mark>	_				Magn	etic n	ateri	als: pr	operti	ies,			Princip Applica			EMS	techno	logy,		
3-1	SLO-2	Importance of MEMS in da		Surface machining etching	ng, bulk	k machining,		Role of mi <mark>crose</mark> nse vith examples	ors and r	nicroa	ctuato		Magn magn							ı	Hybrid	syste	ems, a	applic	ation,	adva	ntage	98
S-2	SLO-1	MEMS and NEMS - Scalin	ng Laws	Structural materi	als		C	Components of me	chanica	MEN	1S		hard i consid						als	,	MOEM	1S co	mpon	ents				
3-2	SLO-2	Conventional electromech	hanical systems	Sacrificial materi	als	WAT N	В	Beam, cantilever, i	nicroplat	es			Magn	etic s	ensin	g and	desig	ın			∟ight n ens,	nodul	ators,	bear	n splitt	ers, I	Micro)
S-3	SLO-1	Mathematical Modeling		Thin film depositi etching	ion, Im _l	purity doping,		liaphragm structui liaphragms	es theor	y, cor	rugate		Prese object				n dete	ection	of lar	ge I	nicro i	mirroi	r, digit	tal mi	cromiri	ror de	evice	
3-3	SLO-2	Important steps for analys of engineering steps	_	Bulk and surface			C	Components in se					Magn								MOEN	1S de	vices					
	SLO-1	Microsensors and microad	ciuaiors	Physical <mark>and che</mark> methods,			n	Capacitive effects, nechanics,	piezo el	emen	t, piez		Princi effect					e sens	sor, h	nall	Optica	l swit	ch, w	ave g	uide aı	nd tu	ning,	
S-4	SLO-2	Principle of sensing and a capacitive sensors, pressu	ura sansors	P and N-type dop surface machinin microscales.				<mark>/leasurement met</mark>	hods				MEM.	S ma	gnetic	sens	ors ar	nd acti	uator	s	shear	stress	s mea	surer	nent			

Strain measurement, pressure

Construction of a MEMS magnetic sensor, Lab-on-a-chip, Important considerations on

Wafer bonding and LIGA, MEMS

S-5 SLO-1 Mechanical MEMS, Thermal MEMS

			Assembling and Packaging	measurement	principle of operation, sensitivity of the	microscale fluid
					sensor	
	SLO-2	Strain measurement	Anodic bonding, fusion bonding,	Flow measurement using integrated	Review of RF based Communication syste-	
	OLO-Z		Lithography, electroforming and molding.	paddle-cantilever structure		nature of flow, surface tension
-6	SLO-1	MEMS gyroscope, inchworm technology	Basic Modeling elements in mechanical and electrical systems	MEMS Gyroscopes		Fluid actuation methods,
-0	SLO-2	Thermistors, thermal flow sensors, shape memory alloys	Ampler element, mass/inertia element, capacitor, resistor and inductor	Shear mode MEMS, principle	phase shifters, RF MEMS application area, advantages	Dilectrophoresis, electrowetting
-7	SLO-1	MOEMS, Magnetic MEMS, NEMS Architectures	Basic Modeling elements in fluid systems	Compensation in gyroscope, gripping piezoactuator, design and working principle,	Review of RF based Communication system-II	Electrothermal flow
	SLO-2	Properties of light and their exploitation with respective to MOEMS	Inertance, fluid resistance, fluid capacitor	Inchworm technology, principle, controlling signal	Design scenarios, planer inductor	Thermo capillary effect
-8	SLO-1	optical switching, beam splitters and microlenses	Thermal systems modeling	Thermal sensors and actuators	RF MEMS, varactors, tuner/filter	Electroosmosis flow
-0	SLO-2	Introduction to RF Communication systems and applications.	Thermal capacitance, thermal resistance	Thermal energy basics and heat transfer processes,	Fabrication process, varactors,	Optoelectrowetting
-9	SLO-1	Varactors, RF tuners, filters, switches, phase shifters	Translational and rotational pure mechanical systems with spring	thermistors, thermocouple, Thermal actuators	Trunermier resonator Resonators	Micropumps: design consideration, Microneedle,
- 9	SLO-2	Microfluidic systems, Concept of lab-on- a-chip, properties of fluids	damper and mass	Thermodevices, micromachine thermocouple probe, thermal flow sensors	I SWITCHAS Phase shitter	Construction of a micropump, modeling working principle

Lograina	1.	Mahalik N P, "MEMS", <mark>Tata McG</mark> raw-Hill Education, 2008	3. C. T. Leondes, MEMS/NEMS Handbook Techniques and Applications, Vol. 1, Sringer, 2006.
Learning Resources	2.	Sergey Edward Lyshevski, "Micro-Electro Mechanical and Nano-Electro Mechanical Systems, Fundamental of	4. Mohamed Gad-el-Hak, MEMS- Introduction and Fundamentals, 2nd Edition, Taylor and Francis
Resources		Nano-and Micro-Engin <mark>eering", CRC Press, 2005</mark>	Group, LLC, 2006.

Learning Assess	sment			Land Section		450					
	Bloom's		100	Cont	inuous Learning Ass	Final Examination (50% weightage)					
	Level of Thinking	CLA –	1 (10%)	CLA –	2 (15%)	CLA –	3 (15%)	CLA -	4 (10%)#	Filiai Examinado	on (50% weightage)
	Level of Trilliking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 <mark>%</mark>	-	30 %	- 1	30 %		30 %	-	30%	-
Level 2	Apply Analyze	40 %	- 2	40 %		40 %		40 %	-	40%	-
Level 3	Evaluate Create	30 %		30 %	W. York	30 %	FHAM	30 %	-	30%	-
	Total	10	0 %	10	00 %	10	0 %	10	0 %	10	00 %

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Design	gners									
Experts from	Industry	Exper	ts from Higher Technical Institu	Internal Experts	Internal Experts					
1. Dr. Hemai	nt Dixit, GlobalFoundaries,USA, aplahemant@gmail.com		1. Pro	of. V. Subramaniam, IITM <mark>, Cher</mark>	<mark>nnai, mania</mark>	<mark>anvs@iit</mark> m.ac.in		1. Dr. M. Kiran, SRMIS	:T	
	a Surendra Muvvala, Saint Gobain Research India, India, vala@saintgobain.com		2. Pro	o <mark>f. M. Ghanashyam Krishna</mark> , UC	OHYD, mgl	ksp@uohyd.erne	et.in	2. Dr. A. Karthigeyan, S	SRMIST	
Course	18NTE311T	Course	SURFAC	CE AND INTERFACES		Course	Ε	Professional Elective	L T P	С

Code				Name						Cate	gory										3	0	0 3
	quisite N	lil		Co-requisite Courses	Nil		П			Progre		Nil											
	Offering Dep	partment	Nanotechnology		Data Book / Codes	/Standards				Nil		'											
Course L	earning Ra	tionale (CLR):	The purpose of learning this	course is to:	(c C)	TNO	L	_earnir	ng					Prog	ram L	earnir	ng Out	tcome	es (PL	_O)			
CLR-1:			faces are important in nanotech				1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14 15
CLR-2 :	Explain v		sms involved in surfaces/i <mark>nterfa</mark>	ces and fundamentals	of various types of b	onding at		11	17	30													
CLR-3:		strategies for m lified surface	anipulating the surfaces and ho	w those strategies help	o them depending up	oon the application of	(E	(%	(%)	0			arch			ability		~					
CLR-4:			equations and the <mark>rmodyna</mark> mic រ ii component sy <mark>stems</mark>	properties of gas-surface	ce interactions al <mark>on</mark> g	with the concepts of) (Bloo	ency (nent (9	wledge	S	pment	, Rese	age	(I)	ustain		m Wor		nance	БU		
CLR-5:			Adsorption a <mark>nd desorpt</mark> ion kine			5. 200 5.00	king	ofici	ainr	S S	alysis	velo	sign	Us	Hure	∞ ∞		Teal	<u>io</u>	& Fi	Learning		
CLR-6:		h surface-analytetry and its signi	tical tools suc <mark>h as phot</mark> oemissio	n spectroscopy, Kelvin	probe microscopy,	spectroscopy	evel of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society & Culture	Environment & Sustainability	σ.	Individual & Team Work	Communication	Project Mgt. & Finance	₽ l	-	-2
Course I	earning Ou	tcomes (CLO):	At the end of this course, le	arners will be able to:	1000	The Breathan	evel	xbe	xbe	ngir	robl	esiç	naly	lode	ocie	nVir	Ethics	iği	om	roje	ife L	PS0 -	PSO PSO
CLO-1 :			urfaces; their structure and physical		es. and interfaces be	etween solids	2	85	70	H	M	M	M	<u> </u>	M	М		M	Н	М	М	Н	HH
CLO-2:	Analyze a	a surface recons	truction & anticipate the stabilit	of a given interface.	V. 10		2	80	70	Н	М	Н	Н	М	М	М	Н	М	Н	Μ	Н	М	м н
CLO-3:			ry (statisti <mark>cal) therm</mark> odynamics		n interface are.		2	70	70	Н	М	Н	Н	Н	Н	Н		М	Н	М	Н	Н	H M
CLO-4:			rstanding <mark>of theorie</mark> s involved a			V - V - 1963	2	75	75	H	M	M	M	M	М	M		М	Н	M	М	L	H M
CLO-5 : CLO-6 :	Compare	different surfac	nding in co <mark>llective p</mark> henomena a e characte <mark>rization te</mark> chniques in			uction of methods and	2	75 80	70 75	H	M	M	M	M M	M M	M H		M M	H H	M M	Н	M M	<u>Н</u> М
	sensitivity	/							ii T		1												.
Dura (hou			9	5 VIII	9	11/12	9				М		9								9		
S-1	SLO-1	Definition of a importance/sig	Surface and <mark>an Interf</mark> ace - its gnificance	The Hierarchy of Equ		Adsorption and Desorp	tion k	(inetic	s	Structure	e of S	urface	es				Electr	onic I	Prope	rties	at the	surfa	ces
01	SLO-2	Liquids and Li	quid Surfaces	Thermodynamics of I Interfaces	Flat Surfaces and	Physiosorption and Ch	emisc	orption		Surface	Crysta	allogr	aphy				•				Selectio		
S-2	SLO-1		to Volume Ratio	The Interface Free Er	nergy	General Issues of Isoth	nerms			Surface				٠.			and S	Surfac	e Roi	ughn		ation	Length
	SLO-2		lid Surface Roughness	Surface Excesses	ALMEN	Isosters, and Isobars			14.7	Relaxati							Many	Body	effec	cts			
S-3	SLO-1	Molecular Inte		Charged Surfaces at	Constant Potential	The Langmuir Isothern	1		2313	General Dynami	cs						Surfac						
0.0	SLO-2	Free Energy	epts of Internal Energy and	Charged Surfaces at	Driven potential	Lattice Gas with Mean	Field	Intera	ction	Diffraction Superla	ttices						Multip	ole E	xcita	tions			sion and
S-4	SLO-1	Molecule by C	Forces: Formation of a Chemical Bonding	Maxwell Relations	The Fowler-Frumkin Iso			point defects Cons					Electromagnetic Field Enhancement – Conservation laws for atomic collisions										
0-4	SLO-2	Interatomic for geometry	rces, bonds - Molecular	Their Applications		Reduction to the Langr				Vibrational Excitations at Surfaces - Empty and image – potential surfa Surface Phonons of Solids states													
S-5	SLO-1	Dipole momer	nts	Solid and Solid interfa	aces	Experimental Determin	ation	of the	Heat	Surface	Stress	s and	the N	earest	Neig	hbor	Scatte	ering (of Lig	ht at	Rough	Surf	aces-

				of Adsorption	Central Force Model	From Nanowires to Quantum Conduction
	SLO-2	Intermolecular Forces and Potential Energies	Solid-Liquid Interfaces	Underpotential Deposition	Surface Phonons in the Acoustic Limits	Classical limit of particle scattering
S-6	SLO-1	Coulomb Interactions	Step Line Tension	Symmetry of Adsorption Sites -	Diffusion at Surfaces	Linear Optical Techniques at Surfaces and Interfaces
3-0	SLO-2	Polar Interactions	Stiffness at its interfaces	Vibrational Frequencies of Isolated Adsorbates	Observation of Single Atom Diffusion Events-Statistics of Random Walk	Spectroscopic Ellipsometry (SE)
S-7	SLO-1	van der Waals Interactions	Equilibrium Fluctuations of Line Defects and Surfaces	Desorption - Desorption Spectroscopy	Absolute Rate Theory	Reflection Difference Techniques (Surface Differential Reflectivity (SDR)
5	SLO-2	Induction effects	The Terrace-Step-Kink Model - Basic Assumptions and Properties	Theory of Desorption Rates	Calculation of the Fre-factor	Reflection Anisotropy Spectroscopy (RAS))
C 0	SLO-1	Collective phenomena at interfaces – Superconductivity	Step-Step Interactions on Vicinal Surfaces	Specific Adsorption of Ions	The Ehrlich-Schwoebel Barrier- The Concept of the Ehrli <mark>ch-Schwoe</mark> bel Barrier	
S-8	SLO-2	Superconductivity at interfaces – A simple model for transport through normal-superconductor interface	The Ising-Model	Specific Adsorption of molecules	Mass Transport on Stepped Surfaces	General Aspects of inverse photoemission
S-9	SLO-1	Collective phenomena at interfaces - Ferromagnetism	Application to the Equilibrium Shape of Islands	The Chemical Bond of Adsorbates of Hydrogen, Oxygen molecules	The Kink Ehrlich-Schwoe <mark>bel Barrier</mark>	Work Function changes induced by the adsorbates – 2D phase transition
J-9	SLO-2	Ferromagnetism at interfaces- Magnetic layer coupling	Simple Solutions for the Problem of Interacting Steps	The Chemical Bond of Adsorbates of Water, Hydrocarbons	The Atomistic Picture of the Ehrlich- Schwoebel Barrier	Kelvin Probe measurements for the study of work-function changes

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Learning	
Resources	
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- 1. G. Bordo Vladimir and Horst-Günter Rubahn, Optics and Spectroscopy at Surfaces and Interfaces, WILEY-VCH Verlag GmbH & Co. KGaA, Weinheim 2005
- Harald Ibach, Physics of Surfaces and Interfaces, Springer-Verlag Berlin Heidelberg 2006
 H. Yıldırım Erbil, Surface Chemistry Of Solid and Liquid Interfaces, First published in 2006 by Blackwell Publishing Ltd, Oxford, UK
- John C. Riviere, Sverre Myhra, Handbook of Surface and Interface Analysis: Methods for Problem-Solving, 2nd Edition, CRC Press Taylor & Francis Group 2009
 - Klaus Wandelt, Surface and Interface Science, Volume 6: Solid-Gas Interfaces II, Wiley VCH Verlag, Weinheim, Germany 2015

Learning	Assessment

	Bloom's		-	Continuo	us Learning Ass	sessment (50%	weightage)			Final Examination	on (EOO/ woightogo)
	Level of Thinking	CLA –	1 (10%)	CLA –	2 (15%)	CLA -	3 (15%)	CLA –	4 (10%)#	Fillal Examination	on (50% weightage)
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %	· Ja	30 %		30 %		30 %		30%	-
Level 2	Apply Analyze	40 %	. 2	40 %		40 %	1	40 %		40%	-
Level 3	Evaluate Create	30 %		30 %	TAREA	30 %	450	30 %	87.	30%	-
	Total	100	0 %	10	0 %	10	00 %	10	00 %	1	00 %

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
1. Dr. D.K. Aswal, National Physical Laboratory, dkaswal@nplindia.org	1. Prof. V. Subramaniam, Physics Department, IITM, Chennai, manianvs@iitm.ac.in	1. Dr. A. A. Alagiriswamy, SRMIST
2. Dr. Krishna Surendra Muvvala, Saint Gobain Research India, India, Krishna.muvvala@saintgobain.com	2. Prof. Gridhar U. Kulkarni, Director at CeNS, Bangalore, guk@cens.res.in	2. Dr. E. Senthil Kumar, SRMIST

Cou		18NTE312T	Course NA	NOTECHNOLOGY IN FOOL	PRODUCTION	Course Categor		Ε				Profes	sional E	Elective					L 3	T 0	P C 0 3
Co	requisite ourses	Nil		Co-requisite Nil					Co	ressiv urses		il									
Course	Offering D	Department Nanotechnolog	ay	Data Book / C	Codes/Standards	Circ.			Nil												
Course	Learning	Rationale (CLR): The purpose of	learning <mark>this course i</mark>	is to:	The state of	-	earni	ng				P	rogram	Learni	ng Ou	tcome	es (PL	O)			
CLR-1	: Know t	the various types of interactions at m	olecul <mark>ar scale</mark>	- 17.		1	2	3	1	2	3	4	5 6	7	8	9	10	11	12	13	14 15
CLR-2		stand the effect of nanoparticles on a			Section 1	(mc	(%	(%	<u>a</u>		t					논		4			
CLR-3		nowledge of the types diagnostic tool			1000	evel of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge		Design & Development		ט			Individual & Team Work		Finance			
CLR-4 CLR-5		e knowledge about the newer techn <mark>o</mark> miliarized with the new concepts of <mark>N</mark>			production		cien	nme	WOL	Sis	lopi	u,	Jre Jre			am	_	Fin	Learning		
CLR-6		the toxic effect of nanomaterials u <mark>sec</mark>			production	- i	rofi	∖ttai	g Z	naly)eve	Design,		nt ⊗ j₹		× Te	atio	ھ	earı		
02.10	. 1.0.000	the toxic of for all familiarity and a decar	m rood processing a	and reducted minerally	1 TO 1 TO 1	Ę	ed F	ed /	erin	ηA	8 L	is, D	8	amr Jabil		al 8	ini	Mg	_	_	3 2
Course	Loarning	Outcomes (CLO): At the end of the	nis course, learners w	vill he able to:	The same	o o	pect	Sect	gine	Problem Analysis	sign	Analysis, Design, Research	Society & Culture	Environment & Sustainability	Ethics	ivid	Communication	Project Mgt. &	Life Long I		
	-	· · ·						Ä	<u>п</u>					SU EN		<u>I</u> nd		Pro		S	PSO PSO
CLO-1		the concept of interactions with in the		ctures at molecular scale	A STATE OF THE STA	2	80	75	M	M	Н	M I		Н	Н	Н	Н	Н	Н		H H
CLO-2 CLO-3		the assay techniques in agric <mark>ultural a</mark> the concepts of nanotechnol <mark>ogy in fo</mark>			2 2	80 75	70 70	M	H	M		Л Н Л Н	H	H	M H	H	H	H		M M H H	
CLO-3		eer food ingredients which ar <mark>e capabl</mark>			The letter	2	80	75	H	Н	Н		л <u>и</u>	H	Н	M	Н	Н	Н		H H
CLO-5		the preferred packaging mat <mark>erials for</mark>				2	80	70	M	Н	М		л <u>М</u>	M	H	М	Н	Н	Н		H H
CLO-6		s the toxic effects of the nan <mark>omateria</mark>				2	80	75	М	Н	М	M I	<i>М</i>	М	Н	М	Н	М	Н	Н	М Н
				To be hard the							- /*										
	iration nour)	9		9		9	.3	la d										9			
S-1	SLO-1	Intermolecular interactions a <mark>nd</mark> supermolecular structures – I <mark>ntrodu</mark>	ction diagnostics	logy in Agriculture and Food	Food products and Introduction	its production	_	li	ntroductio	roduction Introduction								d -			
0-1	SLO-2	Water - hydrophobic and hydrophilic interactions	Nanodiagno microbial ag	stic approaches in detecting ents	Food and new ways	s of food produ	uctior	fo	Crop improod	ıcts				nanomaterials							
S-2	SLO-1	dispersion interaction, electrostatic interactions	Biosensors, diagnostics	Enzyme biosensors and	Need for new food p	processing me	ethod	s	Physical p	nysical properties of packaging materials					s Unique issues for characterization of engineered nanomaterials for food applications						
3-2	SLO-2	Atoms and small molecules	DNA-based	biosensors and diagnostics	Efficient fractionatio	Strength Safety assessn engineered nar					engineered nanomaterials for application				Safety assessment of oral-exposure engineered nanomaterials for food application						
0.0	SLO-1	Polymers, particles, and surfaces	Radiofreque	ncy identification	Efficient product str	ucturing		E	Barrier pro	pertie	es				Experimental design considerations for toxicology studies					s for	
S-3	SLO-2	Introduction to Steric interactions		anosensor networks: nd Response	Optimizing Nutrition	nal value		li	g <mark>ht abs</mark> o	rption									ology	food	products
S-4	SLO-1	Steric interactions involving soluble polymers		nical biosensors – Gold	Nanotechnology in	Food Product	ion	s	tructuring	g of in	terior	surfaces			Toxico	ology (of nan	opart	icles	•	rticles -
3-4	SLO-2	Aggregation	1 '	anoparticles in diagnostics	Applications of nand	otechnology ir	n food	ds A	Antimicrobial functionality Antimicrobial functionality Molecules in foodallergies					s in foods involved in triggering							

S-5	SLO-1	Depletion aggregation of particles by non-adsorbing polymers	Fluorescent Nanoparticles in diagnostics	Sensing, packaging	Visual indicators	Impact of nanoscale structures on allergenic potential of foods
3-0	SLO-2	Bridging aggregation of particles by adsorbing polymers	Silica Nanoparticles in diagnostics	Encapsulation	Quality assessment	Toxicokinetics
	SLO-1	Stabilization of dispersed particles by adsorbing polymers	Safety of nanotechnology in food and the impact in consumer health	Nano Engineering food ingredients to improve bioavailability	Food safety indication	Adme (absorption)
S-6	SLO-2	Polymer brushes to prevent particle aggregation and particle deposition at surfaces	Transduction Principles	Nanocrystalline food ingredients	Product properties	Adme (distribution)
S-7	SLO-1	Self Assembly	Microfluidic Assays	Nano-emulsions	Information and Communication technology	Adme (metabolism)
3-1	SLO-2	Organized self-assembled structures	Lateral flow (immuno) assay	Nano-engineered protein fibrils as ingredient building blocks	Sensors	Adme (excretion)
S-8	SLO-1	Langmuir layers	Nucleic acid lateral flow (immuno) assay	Preparation of food matrices	Radiofrequency identification technology	Toxicodynamics
S-0	SLO-2	Lipid bilayers	Flow-through (immuno) assays	Risks of Nanotechnology	Health Risks	In vivo toxicity
S-9	SLO-1	Solid-supported lipid bilayers	Antibody microarrays	Concerns about using nanotechnology in food production	Environmental Risks	In vitro toxicity
o-9 ⁻	SLO-2	Micelles, Vesicles	Surface plasmon resonance spectroscopy	Rational argumentation versus Human feelings	Consumer and societal acceptance	Study Reliability

Learning Resources Learning Resources Learning Resources Lynn J. Frewer, Willem Norde, Arnout Fischer, and FransKampers, "Nanotechnology in the Agri-Food Sector", Wiley VCH, 2011 (ISBN:9783527330607) Learning Resources Lynn J. Frewer, Willem Norde, Arnout Fischer, and FransKampers, "Nanotechnology in the Agri-Food Sector", Wiley VCH, 2011 (ISBN:9783527330607) Lynn J. Frewer, Willem Norde, Arnout Fischer, and FransKampers, "Nanotechnology in the Agri-Food Sector", Wiley VCH, 2011 (ISBN:9783527330607)	Lograina	1	. Nicholas A. Kotov, "Nanoparticle Assemblies and Superstructures", CRC, 2006 (ISBN 9780367392284)	3.	David S Goodsell, "Bionanotechnology", John Wiley & Sons, 2004 (ISBN 0-471-41719-X)
Wiley VCH, 2011 (ISBN:9783527330607) Woodrow Wilson International, 2006		, 2	Lynn J. Frewer, Willem Norde, Arnout Fischer, and FransKampers,"Nanotechnology in the Agri-Food Sector",	4.	Jennifer Kuzma and Peter VerHage, "Nanotechnology in agriculture and food production",
	Resource	`	Wiley VCH, 2011 (ISBN:9783527330607)		Woodrow Wilson International, 2006

Learning Assess	ment					C 10 / 12 / 12 / 12 / 12 / 12 / 12 / 12 /	TOWN THE WAY				
	Bloom's			Contin	uous Learning Ass	essment (50% weig	htage)	1 50		Final Evansination	n (FOO/ waightoga)
	Level of Thinking	CLA -	1 (10%)	CLA – 2	(15%)	CLA -	3 (15%)	CLA – 4	(10 <mark>%)#</mark>	Filiai Examinatio	n (50% weightage)
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 <mark>%</mark>	1	30 %	- 1/	30 %	-	30 %	<u>-</u>	30%	-
Level 2	Apply Analyze	40 <mark>%</mark>	- 6	40 %	- 1	40 %	- 77	40 %	-	40%	-
Level 3	Evaluate Create	30 %		30 %		30 %		30 %	1 11 -	30%	-
	Total	10	0 %	100	%	10	0 %	100	0 %	10	00 %

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

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2. Mr. Saravanan Lokasundaram, Agro Crops, Chennai, India, sara@agrocrops.com	2. Dr. A Lakshmanan, TNAU, Coimbatore, microlaxman@yahoo.com	2. Dr. E.Senthilkumar, SRMIST

Course Code	18NTE313T	Course Name	ADVANCED DRUG DELIVE	RY SYS	TEMS		Cou		E			Profe	essiona	al Elec	tive			L 7	Γ F		C 3
Pre-requis	s INII		-requisite Nil						Progre		Nil										
Course Offe	ring Department Physics a	nd Nanotechnology	Data Book / Codes/Stan	dards	-	-		I I	lil												
(CLR):		ne purpose of learning this co	urse is to:	l	_earnin	g	3/				P	rogram	n Learr	ning O	utcome	es (PL	O)				
CLR-1:	Understand the concept of drug deli		=	1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2: CLR-3: CLR-4: CLR-5:	Acquire knowledge on controlled dru Learn the concept of targeted drug of Know about the methods of drug del Learn about various nanocarriers	delivery	ers will be able to:	evel of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society & Culture	Environment & Sustainability	Ethics	ndividual & Team Work	☐ Communication	Project Mgt. & Finance	Life Long Learning	PSO - 1	PSO - 2	PSO - 3
CLO-1 :	Explain various drug delivery system	10		2	80	75	<u> </u>		H	H	H	H	<mark>Н</mark>	H	<u></u> M	C	<u> </u>	H	Н	Н	H
CLO-1:	Analyse a controlled drug release p			2	80	70	H		Н	Н	M	M	M	Н	M	Н	ī	Н	M	М	M
CLO-3:	Formulate different drug delivery sys		Stational State of	2	75	70	E		Н	Н	Н	H	Н	Н	М	Н	L	H	Н	Н	Н
CLO-4:	Apply the concept of drug targeting		THE PERSON NAMED IN COLUMN	2	80	75	T.		Н	Н	Н	Н	Н	Н	М	Н	L	Н	Н	Н	Н
CLO-5:	Differentiate among various nanocal	rriers	MINISTER CANADA	2	80	70	H		Н	Н	Н	Н	Н	Н	М	Н	L	Н	Н	Н	Н
Durat (hou	ı y	-	9)		Ť			9							9			

	uration (hour)	9	9	9	9	9
	SLO-1	Drug delivery systems	Targeted drug delivery system	Metal nanoparticles for drug delivery	Cancer therapy	Theranostic metal nanoshells
S-1	SLO-2	Traditional drug delivery	Site specific drug release	Gold based drug delivery systems	Drug delivery to cancer	Photothermally-modulated drug delivery using nanoshell
S-2	SLO-1	Advantages and disadvantages of various traditional drug delivery systems	Types of drug targeting	Multifunctional nanoparticles	Targeted drug delivery to cancer	Hydrogels
3-2	SLO-2	Modes of drug delivery	Active targeting	Multifunctional gold nanoparticles for drug delivery and imaging	Enhanced permeability and retention	Nanoporous systems for drug delivery
S-3	SLO-1	Routes of administration	Passive targeting	Virus based drug delivery system	Cancer markers	Molecularly-derived therapeutics
5-3	SLO-2	Novel drug delivery system	Barriers for drug targeting	Polymeric nanoparticles	Folate receptor	transdermal drug delivery
S-4	SLO-1	Pharmacokinetics	Strategies for site specific drug delivery	Classifications of polymers	Angiogenes <mark>is</mark>	low-frequency sonophoresis
	SLO-2	ADME studies	Receptors	Polymer micelles	Leaky vasculature	implants for controlled drug delivery
S-5	SLO-1	Kinetics of drug delivery	Ligands	Synthesis of polymeric nanoparticles for drug delivery	Cancer specific targeting	Responsive release system
3-0	SLO-2	Zero order kinetics	Antibodies based drug delivery	Dentrimers	Combinational therapy	Fabrication and Applications of Microneedles
S-6	SLO-1	First order kinetics	Metabolism base <mark>d drug delivery</mark>	Magnetic nanoparticles for drug delivery	Neutron capture therapy	Micropumps
3-0	SLO-2	Mixed order kinetics	Surface modification of nanoparticles	Nanoscaffolds	Targeting tumor vasculature for imaging	microvalves
S-7	SLO-1	Controlled drug delivery	Bioconjugation of nanoparticles	CNT in drug delivery	Anticancer drugs	Implantablemicrochips

	SLO-2	Mechanism of controlled drug release	PEGylation of nanoparticles	Liposomes	Pharmacodynamics	Quantum Dot Probes
S-8	SLO-1	Therapeutic index	reticuloendothelial system	Protein drug delivery	Photothermal therapy	Applications Nano biotechnologies for Single-Molecule Detection
	SLO-2	Drug release profile	Opsonaization	Gene delivery	Cancer imaging	Nanorobots
S-9	SLO-1	Rate controlled drug delivery	Renal clearance	Gene transfection	Nanoparticle–Aptamer Conjugates for Cancer Cell Targeting and Detection.	Drug delivery to Central Nervous systems
3-9	SLO-2	Time controlled drug delivery	Steric repulsion	Methods of gene transfection	Fluorescent Silica Nanoparticles for Tumor Imaging-	Drug delivery across Blood brain barrier

Learning Resources 1. Drug Delivery: Engineering Principles for Drug Therapy, M. Salzman, Oxford University Press, 2001. Drug Delivery and Targeting, A.M. Hillery, CRC Press, 2002.	 Drug Delivery: Principles and Applications, B. Wang, Wiley Intersceince, 2005. Nanoparticle Technology for Drug Delivery, Ram B. Gupta, Uday B. Kompella Taylor & Francis, 2006
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	Dia a mai'a	Continuous Learning Assessment (50% weightage)								Final Evamination	n (50% weightage)
	Bloom's Level of Thinking	CLA –	1 (10%)	CLA – :	2 (<mark>15%</mark>)	CLA -	3 (15%)	CLA – 4	l (10%)#		ii (50% weigiilage)
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember	3 <mark>0 %</mark>	100	30 %		30 %		30 %		30%	
Level I	Understand	30 78		30 /8	31711	30 /6		30 /6		3070	_
Level 2	Apply	40 %		40 %	THE STATE OF	40 %	A DEVI	40 %		40%	_
Level 2	Analyze	40 /0	- 10	40 /8	A REALES	40 70	1111 20 11	40 /0		4070	_
Level 3	Evaluate	30 %		30 %		30 %	16号作品。	30 %		30%	
Level 3	Create	30 %		30 %		30 %		30 %	_	30%	-
	Total	10	0 %	100) %	100	0 %	100	0 %	10	0 %

Course Designers		
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1. Mr. K. ChandruTrivitron Healthcare Pvt. Ltd. Chennai, chandru.k@trivitron.com	1. Dr. AsifkhanShanavas, INST Mohali, asifkhan@inst.ac.in	1. Dr. G. Devanand Venkatasubbu, SRMIST
2. Dr. AchuthPadmanaban, Baylor College of Medicine, USA, achuthz@gmail.com	2. Dr.MukeshDoble, IIT M, mukeshd@iitm·ac	2. Dr. Selvamurugan, SRMIST

Cou		18NTE314T	Course NANOMED	IC INIES	ourse		Ε				Profe	ssion	al Ele	ctive				L 3	T 0	P 0	<u>C</u>
Co	requisite ourses	Nil Department Nanotechnology	Co-requisite Courses Nil	Codes/Standards				Progre Cou		Nil											
Course	Offering L	repartment wanotechnology	Data Book / C	Soues/Standards				IVII													
Course	Learning I	Rationale (CLR): The purpose of learning	ng this course is to:	Charles and the same of the sa		_earni	ing					Prog	ıram L	.earnir	ng Outo	omes	(PLO)				
CLR-1		standing the basis of medicine			1	2	3	1	2	3	4	5	6	7	8 !) 10) 11	12	13	14	15
CLR-2		the various classification of nanomedicine	41				7				-G			ilf.							
CLR-3		knowledge about interaction of nano <mark>mater</mark>		- 11 TA 15 T	Level of Thinking (Bloom)	(%)	(%)	e de		#	Analysis, Design, Research			Environment & Sustainability	÷	₹	a				
CLR-4 CLR-5		broad understanding about the nanosyste			8	Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	e.	Design & Development	Res	<u>a</u>		stail	7/4	H individual & Team work	Project Mgt. & Finance	_			
CLR-5:		quainted with future aspects of na <mark>noimprint</mark> whend the principles behind nano <mark>medicine</mark>	ed bioserisor) gu	Ser	nme	WOL	Sis	dol	Ju, I	⊤ Modern Tool Usage	<u>e</u>	Su	1	<u> </u>	Ë	Learning			
CLIN-0.	Compi	eriena trie principies beriina nanomedicine			: 동	lol	ıttai	A Y	Jaly	eve	esić		JHT.	٦ ح	ľ		∞ ∞	earı			
				ASSAULT STATE	Ę	D D	DQ P	ering	٦Ar	∞ □	s, D	P	8	mei	-	<u>a</u> <u>a</u>	Mgf	g L		0.1	_
		2 (2) 2) 1 (4) 1 (4)			- 	Expected	ecte	inee	Problem Analysis	ign	lysi	lem	Society & Culture	<u>io</u>	S	Communication	ect	Life Long I	-1)-2	PSO - 3
Course	Learning	Outcomes (CLO): At the e <mark>nd of this</mark> cou	rse, learners will be able to:	A DOMESTIC OF THE PARTY OF THE	ek	N.	l x	ling.	Jo C	Sec	Ana	Moc	300	N	Ethics		Poj] <u>.</u>	PSO	PSO	SS
CLO-1	: Apply t	the principles of medicine in <mark>nanomedi</mark> cine	Total Control of		2	80	75	H	M	Н	H	Н	M	М	H	1 H			H	H	H
CLO-2		e the shortcomings of conve <mark>ntional m</mark> edicin			2	80	70	Н	М	М	Н	М	М	М		<i>1</i> Н			М	М	М
CLO-3		concepts of nanomedicine to <mark>a focuse</mark> d clini		WHITE PALE	2	75	70	Н	М	Н	Н	Н	Н	Н		1 H			Н	Н	Н
CLO-4		these nanosystems for the d <mark>iagnosis </mark> and th			2	80	75			Н	Μ	Н	Н			H H			Н	Н	Н
CLO-5		the current techniques for n <mark>ovel appli</mark> cation			2	80	70		М	Н	Н	Н	М	М		1 H		_	Н	Н	Н
CLO-6	: Apply t	the principles of 3D printing f <mark>or future a</mark> spec	ts of nanoimprinted biosensor		2	80	75	Н	М	М	Н	Н	М	М	H I	H H	M	Н	Н	М	Н
D.					4	-3															
	ration nour)	9	9	9						9								9			
	SLO-1	Carbon nanotubes for Bone regeneration	Biocompatibility of traditional medical implants	Introduction to biomedical in	naging	g		Drug delive	ry to (CNS			i	31	D Biopi	inting	– intro	ductio	n		-
S-1	SLO-2	Carbon nanotubes for Electroporation	Adhesive interactions with implant surface	s Types of biomedical imagin	а			Drug delive	ry acr	oss bl	ood b	rain b	arrier	31	D Biopi	intina	uses				
					_			(BBB)	у.												
	SLO-1	Hexagonal array of gold nanorods	Nanorobot immunoreactivity	The emergence of nanopar imaging platform in biomed		as		EEG for mo	nitorii	ng br <mark>a</mark>	in act	ivity		T_{j}	ypes of	3D bi	oprinti	ng			
S-2			771 77 17	Magnetic resonant imaging		inle a	nd		-					3/	D Biopi	intina	tochno	nlogias	· ink i	ot has	has
	SLO-2	Gold nanorods in sensing	Nanopyrexia Nanopyrexia	techniques	princi	ipic ai	1	Vanowires	for mo	onitorir	ng bra	in act	tivity		וקטום ט	iiiiiig	icomic	Jogics	. IIIN J	ci ba	Jou
	SLO-1	Isohelical DNA-binding oligomers	Mutagenicity	Magnetic resonant imaging methodology	workin	g		Veuroreger	neratio	on				P	ressure	assis	ted				
S-3	SLO-2	Nanospearing- multifunctional glyco- nanoparticles	Carcinogenicity	Magnetic resonant imaging contrast agents	-Paran	nagne	etic	Veuro <mark>su</mark> rge	ery					La	aser as	sisted					
	SLO-1	Nanoarchitecures	Thermocompatibility	USPIOS for imaging				Vanoneuro	<mark>sur</mark> gei	ry				S	olenoid	valve	based	d			
S-4	SLO-2 ordered nucleic acid molecules Mechanocompatibility SPIOS for imaging					Lipoblockers Acoustic jet based															
C E	SLO-1	DNA self assembly	Cell membrane disruption	MPIOS for imaging	1		-	Vanolipoblo	ockers	- anti	rester	nosis	drugs		halleng						
S-5	SLO-2	DNA self-assembling nanostructures	Systemic nanoparticle distribution	Magnetic nanosensors				Myocardial							uture d					nting	

		induced by trivalent ions				
S-6	SLO-1	Assembling by polycations	Nanoparticle phagocytosis	Nanosensors- radio labeled nanoparticles	Cell therapy for myocardial infarction	Nanoparticles sensors
3-0	SLO-2	Wang tiles	Nanomaterial volumetric intrusiveness	Ultrasound imaging	Stem cell types	Calorimetric sensing
C 7	SLO-1	Biological examples of Nanomotors and devices	Intusiveness of Nanobots	Acoustically reflective nanoparticles	Regeneration of the cardiovascular system	Vapor phase sensing
S-7 SLC	SLO-2		Nanobiotechnology in tissue engineering	Acoustically reflective nanoparticles: application in ultrasound imaging	Nanobone implants	Raman sensing at surfaces
	SLO-1	Kinesine motor	Nanobiotechnology for organ replacement	Iodinated liposomes	Nanobone scaffolds	Electro analytical sensing
S-8	SLO-2	Dynein motor	Liver and kidney transplant	Application of Iodinated liposomes	Nanoparticle drug formulations for spray inhalation - wound healing	Plasma sensing
S-9	SLO-1	Polymer-based capsules	Nanobiotechnology for assisted function	Quantum dots	Nanogeriatrics	Optical sensing
J-9	SLO-2	Oral drug delivery	Organ assists	Quantum dots in optical imaging	Orthodontal application	Sensors for cancer detection

Learning	1. Understanding Nanomedicine: An Introductory Textbook by Rob Burgess. 2012 CRC Press	3. Medical Nanotechnology and Nanomedicine by Harry F. Tibbals. 2010 by CRC Press
Resources	2. Nanomedicine for Drug Delivery and Therapeutics, Editor(s): Ajay Kumar Mishra, 2013, Wiley	4. Introduction to Nanomedicine and Nanobioengineering, by Paras N. Prasad. 2012, Wiley

Learning Assess	sment			- 100	经 机构设置的	201	V						
	Bloom's			Conti	nuous Learning Ass	essment (50% weig	htage)			Final Evamination	n /F00/ woightage)		
	Level of Thinking	CLA -	1 (10%)	CLA – 2 (15%)		CLA –	3 (15%)	CLA – 4	1 (10 <mark>%)#</mark>	Final Examination (50% weightage)			
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice		
Level 1	Remember Understand	30 %	34	30 %		30 %	The A lot	30 %	-	30%	-		
Level 2	Apply Analyze	40 %		40 %		40 %	115	40 %	-	40%	-		
Level 3	Evaluate Create	30 %		30 %	151-4	30 %	Fig Ind	30 %		30%	-		
	Total	10	00 %	100	0 %	10	0 %	10	0 %	10	00 %		

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Course Code) 18NT	E315T	Course Name		MICROELE	ECTRONICS	S AND VLSI					urse egory		Ε				I	Profes	siona	l Elec	tive					L 3	T 0	P 0	C 3
Pre-red Cour Course O		rtment	Nanoteci	hnology		equisite Ni	il ata Book / Coo	des/St	tandards							gress ourse		Nil												
										W.	Α,																			
Learning	Rationale (Cl	LR):	The purpo	ose of learning <mark>t</mark>	his is to:		100					L	earnir	ng						Progr	am L	earni	ng Ou	utcom	es (Pl	LO)				
CLR-1:			importance of i				المنت					1	2	3		1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2:		the physic	cal effects of ser	miconduc <mark>tor-se</mark> r	<mark>nico</mark> nductor junct	ion, its elect	trostatics, dev	ice an	nd circuit	level		(1				ج.			Environment & Sustainability								
CLR-3:	operation	owledge on	digital languag	o of Boolean ald	gebra, basics of lo	ogic gates fr	or advanced n	omor	v annlica	tions		Level of Thinking (Bloom)	Expected Proficiency (%)	Attainment (%)		ge		Ħ	Analysis, Design, Research			inab		¥		e e				
CLR-4:							n auvanceu n	iemoi.	у аррііса	illoris		(Blc	ncy	ent		Med	0	Jme	Re	ge		nsta		Š		Janc	D			
CLR-5: Understand intricacies of designing micro/nanoscale rules, flow of fabrication and IC testing print					ciples	100	7		king	ficie	ainm	k.	0	ysis	elop	ign,	Usa	ture	S S		ean	E	违	Ë						
CLR-6:									725		hink	Pro	Atta		g .	lual	Dev	Des	00	Culture	ent		∞	catic	gt. 8	Learning				
						THE REAL PROPERTY.	100			34	of T	ted	ted		<u>%</u> .	Ē	∞ _	sis,	<u></u>	∞ >	u u		lnal	Ĭ.	Ĭ	bug	_	2	e-	
Learning	earning Outcomes (CLO): At the end of this, learners will be able to:						-				vel	cbec	Expected	M.	Engineering Knowledge	Problem Analysis	Design & Development	alys	ode	Society	virc	Ethics	divic	Communication	Project Mgt. & Finance	Life Long	PSO-	PSO-	PSO-	
_	O-1: Interpret difference between macro and micro electronics					-		-			2	80 80	<u>1</u> 75				H	H	H Modern Lool Usage	M	山 M	H H	Individual & Team Work	З Н	M M	当 H	Н	H	H 8	
	LO-1: Interpret difference between macro and micro electronics Apply basic semiconductor physics which is important to understand the working of semic					of semiconduc	tor-se	micondu	ctor																					
CLO-2:			circuit level o <mark>pe</mark>		t to and crotain tr	ic working o	n demiconduc	101 30	moonaa	0101		2	80	70	21	Н	М	М	Н	М	М	М	Н	М	Η	Μ	Н	М	М	М
CLO-3:					operation of logi			iits	- 20			2	75	70				Н			Н	Н	М	Н	Н	Н	М	Н	Н	Н
CLO-4:					circuit formation							2	80	75				Н			Н	Н	Н	Н		М	Н	Н	Н	Н
CLO-5:					IC testing at high							2	80	70				Н				М	Н	М		М	Н	Н	Н	М
CLO-6:	Analyze po	wer consur	mption and need	d for optimizatio	n in on <mark>-</mark> chip devid	es, its effec	t on switching	spee	ed			2	80	75		H	М	М	Н	М	М	М	Н	Н	Μ	М	Н	М	Μ	Η
Dı	uration	1														-	-	-												$\overline{}$
	hour)		9		- N	9				9								9								9)			
	ŚLO-1	Introducti	ion to classificat	ti <mark>on of ma</mark> terials	Number system	S		Intro	oduction	to IC Tec	hnolo	ogies		(Overvi	ew of	VLS	desi	gn me	thodo	ologie		Usag							
S-1	SLO-2	Types of	semiconductors	S	Binary and octai	l numbering		Nee	eds of VL	SI					Veeds	of de	signi	ng					Overv				nsum _i nips	ption,	low a	and
S-2	SLO-1	Concept	of energy band	gap	Hexadecimal nu	imbering		VLS	SI design	styles					Steps i	n des	ignin	g					On-cl							
5-2	SLO-2	Doping in	n semiconductor	rs	Conversions bet	tween numb	er systems		out rules						Casca	ding c	f pro	cess									ging o			
S-3	SLO-1	Formation	n of p-n junctior	1	Boolean algebra	,	LINK		oduction de Semic				Metal	16	Introdu	ction	to M	OFET	-				Curre		nd vol	ltages	in Cl	MOS .	short	
	SLO-2	Electrosta	atics of junction	operation	Logic gates				SI for CM		10	00)	711		VLSI fo	or MO	SFE	T							ırrent.	, stati	ic curr	ent		
0.4	SLO-1 Diode as circuit element Truth tables for AND, OR, NOT gates			IOT gates		sitive chai ative cha						DC op				ЕТ				Gate-										
S-4	SLO-2 Basics of bipolar and unipolar junction transistors Truth tables for NAND, NOR gates			₹ gates		MOS and			/		,	AC ope	eratio	of I	10SF	ET				transi	stor a	nd ga	ate siz	zing						
0.5	SLO-1 Current-voltage characteristics and operation of transistors Circuits with logic gates					СМ	OS inver	ter					Modell	ing of	МОЗ	SFET					Powe	r ana	lysis							
S-5 SLO-2 Comparison of transistors Combinational circuits and sequential circuits					equential	СМ	OS logic	circuits					Small :	signal	mod	el					Data	correl	ation	analy	sis .					

S-6	SLO-1	AC operation of transistor	Flip-flops	Combinatorial CMOS Logic	Need of high frequency operation	Random logic signals, signal entropy
3-0	SLO-2	Small signal model	SR and JK flip-flops	pMOS and nMOS in logic operation	high frequency MOSFET models	Switching activity analysis
S-7		Small signal model for bipolar junction transistor (BJT)	Basics of counters	D-latch	Testing of transistor	Parallel architecture
3-1		Small signal model for junction field effect transistor (JFET)	Asynchronous and synchronous counters	CMOS for D-latch	Need for testing	Digital CMOS circuits
	SLO-1	Amplifiers	Overview of memory devices	Triggering of flip-flops	Testing principles	CMOS amplifiers
S-8	SLO-2	Transistor connections in various modes	Logic gates for memory applications	Edge triggered Flip Flops	design for testability	CMOS amplifier topologies
S-9	SLO-1	Feedback concept	Read only memory	Transistor logic	Error analysis	Common-Source topologies
3-9	SLO-2	Ideal F/B amplifiers	Random access memory	Pass transistor circuits	Safety in testing	Parallel architecture with voltage reduction

Learning	 Behzad Razavi, Fundamentals of Microelectronics/Edition 1, Wiley, 2008 	3. Weste N.H., "Principles of CMOS VLSI Design", Pearson Education, India, 2002
Resources	2. Millman and Grabel, "Microelectronics", 2nd Ed. Tata McGraw-Hill, 1999	3. Weste W.F., Filliaples of Girlos VLSI Design, Fedison Education, India, 2002

Learning Assess	sment			/ PTP	ALC: YELLY	170					
	Bloom's			Conti	nuous Learning Asse	essment (50% weig	htage)			Final Examination	on (50% weightage)
	Level of Thinking	CLA -	1 (10%)	CLA –	2 (15%)	CLA -	3 (15%)	CLA – 4	l (1 <mark>0%)</mark> #	Filiai Examinatio	on (50% weightage)
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %		30 %		30 %		30 %	- 1	30%	-
Level 2	Apply Analyze	40 %	Z: E	40 %		40 %	rte A ∧	40 %		40%	-
Level 3	Evaluate Create	30 %		30 %		30 %		30 %	-	30%	-
	Total	10	00 %	100	0 %	10	0 %	100	0 %	1(00 %

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
1. Dr. D.K. Aswal, National Physical Laboratory, dkaswal@nplindia.org	1. Prof. K. Sethupathi, IITM Chennai, ksethu@iitm.ac.in	1. Dr. Abhay A Sagade, SRMIST
2. Dr. S. Sudhakar, CSIR-CECRI, sudhakar@cecri.res.in	2. Prof. S. Balakumar, University of Madras, balakumar@iunom.acs.in	2. Dr. P. Malar, SRMIST

Cours Code		18NTE316T	Course Name	PHYSICS OF E	ELECTRONIC I	MATERIA	LS				ourse ategory	,	Ε		Pro	fessior	nal Ele	ctive		_ T	F ()	C 3
Co	urses	Nil		Co-requisite Nil							Progre Cour		Nil										
Course	Offering De	partment Nanote	chnology	Data Bo	ok / Codes/Sta	ndards		-		N	il												
Learnir (CLR):	ng Rationale)	The purpose of le	parning this is to:	7 11 1 2		Learni	ing	4/1				Pro	gram I	Learnii	ng Out	comes	(PLO))				
CLR-1	: Unde	erstand the physics of electi	ronic material <mark>s</mark>	- 10		1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		iliarize different physical pro	perties of <mark>electro</mark>	nic materials								ch Ch			ility						 		
CLR-3	: Knov	v-how the various processe	s in ele <mark>ctronic ma</mark>	terials	17.00	(mo	8	(%)	e e		¥	ear			nab		돈		в		ļ Ī		
CLR-4	: Unde	erstand the physics behind	the wo <mark>rking of e</mark> le	ctronic materials based devices	F 23 17	8	ncy	ent	vledc		Development	Research	ge		Sustainability		ا Work		Finance	б		1	
CLR-5	: Gain	a fundamental understand	ing o <mark>f the eme</mark> rgir	ng electronic materials	MO AL	in	ficie	lin lin	Snov	ysis	elop	ign,	Jsa	Culture	& Sı		Team	E	Fir	rnin	 	I	
CLR-6:	Knov	v new materials other than	Si <mark>etc and fu</mark> ture t	echnology roadmap	46.85	Thinking (Bloom)	Pro	Atta	ing A	Analysis	Dev	Design,	00	& Cul			∞ర	icati	lgt. 8	Learning	 		
Learnir (CLO):	ng Outcomes	s	At the end of this	, learners will be able to:		Level of	Ę.	Expected Attainment (%)	Engineering Knowledge	Problem /	Design &	Analysis,	Modern Tool Usage	Society &	Environment	Ethics	Individual	Communication	Project Mgt. &	Life Long	PS0 - 1	PS0 - 2	PSO - 3
CLO-1		knowledge of physics to un	<mark>derstand</mark> the prop	erties of electronic materials	17 74 75	2			М	М	Н	Н	М	Н	Н	М	М	Н	М	Н	Н	Н	Н
CLO-2	: Analy	yze different mechanisms t <mark>ı</mark>	hat determine the	properties of electronic materials		2		70	Н	М	Н	Н	М	М	М	М	М	Н	L	Н	М	М	М
CLO-3	: Dete	rmine the applications of e <mark>l</mark>	<mark>ectronic</mark> materials	based on their properties	6.7950	2	75	70	М	L	Н	Н	Н	Н	Н	Н	М	Н	М	Н	Н	Н	Н
CLO-4	: Evalu	uate the material character <mark>i</mark>	<mark>stics by </mark> applying i	laws of physics		2	80		H	Н	Н	Н	Н	Н	Н	М	М	Н	Μ	Н	Н	М	М
CLO-5	: Deve	elop in depth understandin <mark>g</mark>	<mark>of the p</mark> hysical pi	rocesses of electronic materials		2	80	70	Н	М	Н	Н	Н	Н	Н	Н	М	Н	М	Н	Н	М	М
CLO-6	: Distir	nguish how materials are c <mark>l</mark>	<mark>assified a</mark> nd their	applications				F	М	М	М	М	L	М	М	Н	Н	Н	Н	М	Н	М	М
	. ,						4										1						
L	Ouration (hour)	9		9			9						9							9			
C 1	SLO-1	Defining characteristics a of semiconductors	an <mark>d cla</mark> ssification	Concept of relative permittivity	Definition of	magnetic	dipole	e momer	t	Optica	l prope	erties o	f mate	rials			Ther	mal pr	opertie	s of m	aterial	s	
S-1	SLO-2	Fundamentals of band the semiconductors	neory of	Electric dipole moment and polarizability	Orbital and selectron	spin magr	netic m	oment o		Refrac behavi		dex, R	efractiv	∕e inde	x-wave	elength	h Atom	nistic th	neory o	of heat	сарас	ity	
	SLO-1	Intrinsic semiconductors		Polarization vector and charge	Magnetizatio	on vector				Snell's	law ai	nd tota	l int <mark>err</mark>	nal refle	ection		Quai	ntum n	nechar	nical co	onsider	rations	

Saturation magnetization and curie

Magnetization vector

magnetic permeability

ferrimagnetism

interaction

temperature

Definition of magnetic susceptibility and

Origin of ferromagnetism and exchange

Magnetic materials classification

Dia-, para-, ferro-, antiferro-, and

Case study: fiber optics and LEDs

Interaction of photons with materials

Antireflection coatings on solar cells

Dielectric mirrors

Absorption, transmittance and reflection

Electronic contribution to the heat

Heat capacity and specific heat

Thermal expansion and thermal

Thermal conductivity in metals, alloys,

Einstein and Debye model

capacity

conductivity

and dielectrics

SLO-2

SLO-1

SLO-2

SLO-1

SLO-2

S-2

S-3

S-4

movement

Energy band diagram and carrier

Conductivity of a semiconductor

Electron and hole concentrations

Concepts of p-type, n-type and

Extrinsic semiconductors

compensation doping

density

solids

polarization

permittivity

Electric susceptibility and relative

Electronic polarization in covalent

Ionic, dipolar, interfacial and total

Lorentz field in dielectrics

Clausius-Mossotti equation

S-5	SLO-1	Energy band diagram and electron and hole concentrations	Concept of dielectric loss	Magnetic domains and domain walls	Band to band absorption	Thermoelectricity in metals
3-0	SLO-2	Estimation of the position of the Fermi energy and the resistivity	Dielectric studies and the Cole- Cole plot	Magnetostriction and domain wall motion	Direct and indirect transitions	Seebeck effect and the figure-of-merit
S-6	SLO-1	The temperature dependence of carrier concentration	Dielectric strength and insulation breakdown	Magnetic domains in polycrystalline materials	Light scattering in materials, attenuation in optical fibers	Thermoelectricity in semiconductors
3-0	SLO-2	The temperature dependence of drift mobility	Dielectric breakdown mechanisms	Understanding the M versus H hysteresis curve	Luminescence, phosphors, and white LEDs	Overview of thermoelectric devices
S-7	SLO-1	Degenerate and nondegenerate semiconductors	Capacitor dielectric materials	Demagnetization	Spontaneous and stimulated emission	Two-dimensional electronic materials
3-1	SLO-2	Direct and indirect recombination	Typical capacitor constructions	Soft and hard magnetic materials: Examples and uses	Laser materials and laser action	The Era of graphene and related materials
S-8	SLO-1	Minority carrier life time	Piezoelectricity		Concept of photoluminescence and electroluminescence	Electronic properties at 2D limit
3-0	SLO-2	Carrier injection and diffusion	Piezoelectric spark generator and quartz crystal	Critical current density and superconducting solenoids	Examples for devices working on the principles of PL and EL	Optical properties- layer dependence
S-9	SLO-1	Optical absorption in semi <mark>conductor</mark> s	Ferroelectricity and pyroelectricity	Josephson effect	Electro-optic effects and applications	2D materials based metal, semiconductor and dielectrics
3-9	SLO-2	Direct and indirect band gap semiconductors and the E-k diagram	Practical Applications	Introduction to anisotropic and giant magnetoresistance	Magneto-optic effects and applications	Applications and future perspectives

Learning
Resources

- S O Kasap, "Prin<mark>ciples of</mark> Electronic Materials and Devices" McGraw Hill, Fourth Edition, 2017 Wei Gao, Zheng<mark>wei Li, Ni</mark>gel Sammes, "An Introduction to Electronic Materials for Engineers" World Scientific Publishing Co. Pte. Ltd, Second Edition, 2011
- 3. David Jiles, "Introduction to the Electronic Properties of Materials: Nelson Thornes Ltd, Second Edition, 2001
- David K. Ferry, Jonathan P. Bird "Electronic Materials and Devices" Academic Press, First Edition, 2011.
- Yuriy M Poplavko, "Electronic Materials: Principles and Applied Science" Elsevier, First Edition,
- Rolf E. Hummel, "Electronic Properties of Materials: An Introduction for Engineers" Springer, 1993

Learning Assessi	ment										
	Bloom's		7.54	Conti	inuous Learning Ass	essment (50% weig	htage)			Final Evamination	n (E00/ woightage)
	Level of Thinking	CLA -	1 (10%)	CLA –	2 (15%)	CLA –	3 (15%)	CLA -	4 <mark>(10%)#</mark>	Filiai Examinatio	n (50% weightage)
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember	30 %		30 %		30 %		30 %		30%	_
Level I	Understand	30 //		30 %		30 /6		30 //		3070	-
Level 2	Apply	40 %		40 %	District I	40 %	DESCRIPTION OF THE PARTY OF THE	40 %		40%	
Level 2	Analyze	40 /0		40 /0	TIK THE	40 /6		40 /0		4070	-
Level 3	Evaluate	30 %		30 %		30 %	CHINARY	30 %		30%	
Level 3	Create	30 /0		30 %	-	30 76		30 78	_	3070	-
	Total	10	0 %	10	0 %	10	0 %	10	0 %	10	00 %

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Cour Cod		18NTE317T	Course NANOCATALYSTS Co requisite							/	Е			F	rofes	sional	Elect	ive				L 3	T 0	P 0	C 3
Co	equisite ourses Offering D	Nil Department N	anotechnology		Co-requisite Nil Data I	Book / Co	odes/Standards					gress ourse	11	lil											
Course	Onoming E	oparamone pro-	arrotoormorogy		Data	Book / O	odoo, otandardo	7			1 111														
Learnin (CLR):	g Rational	le Th	e purpose of learr	ning this is to:	1	37	The state of the s	L	earnir	ng					Prog	gram	_earn	ing O	utcon	nes (P	LO)				
CLR-1		the concepts of chemis			- 1			1	2	3		1 :	2 3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		stand the catalytic kinetic									-/			등			ility								
CLR-3 CLR-4		be the reaction kinetics of stand the principles behi					The latest terms of the la	l m	(%)	(%)		ge	+	sear			inat		ž		æ				
CLR-5		nowledge about the wor						<u>8</u>	ncy	ent		/led	9	Re	ge		ısta		Š		auc	D			
CLR-6		be catalytic processes a		n nanocatary no	materials		7 39 7	ing	icie	in In		No.	SIS I	gn,	Jsa	ure	S S		eam	<u>_</u>	ᇤ	ij			
020							Level of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)		Engineering Knowledge	Design & Development	Analysis, Design, Research	T Modern Tool Usage	Society & Culture	Environment & Sustainability		Individual & Team Work	Communication	Project Mgt. & Finance	⊥ Life Long Learning	<u>-</u>	2	3	
(CLO):	ng Outcom	At the end of this, learners will be able to.				As In the	Level	Expect				Decide		Moder	Societ	Enviro	Ethics	Individ	Comm		Life Lo	PSO	PSO-	PSO-	
CLO-1		escribe the mechanisms of nanom <mark>aterials f</mark> or using as catalyst apply the importance of the bottom-up approach to prepare nanomaterials					2	80	75			1 F			М	М	Н		Н	Μ		Н	Н	Н	
CLO-2					nomaterials			2	80	70		H I	1 1		М	М	М	Н	М	Н	L	Н	М	М	М
CLO-3 CLO-4		y the photocatalyst for ease the working of noble n				-		2	75 80	70 75			1 H		M H	H	H	M H	H H	H H	H M	H	H	H	H
CLO-4		ate the needs and future						2	80	70			1 F		Н	М	М	Н	<u>п</u>	Н	IVI	Н	Н	Н	Н
CLO-6		isotherms for different n			naterials			2	80	75			1 N		М	M	М		<u>н</u>	Н	М	H	H		Н
	1 1117				11/27				A			- 17												1	
	ration nour)	9		7	9		9	T.					C	9							9	l			
	SLO-1	Introduction to catalysi	S	Adsorption a	and Desorption Process	ses	Kinetics and photocatalytic a	activity	′		Catalyst									s of N					
S-1	SLO-2	Classifications		Adsorption F	Rate		Introducti <mark>on to photocatalyst</mark>			е	loble m tc)					Rh, Pd				s con st: NO		on usii	ng		
	SLO-1	heterogeneous catalys	is	Desorption F	Rate		Basics of electrochemistry				olymer anopar		zed R	h an <mark>d l</mark>	Ru	i				on usir					
S-2	SLO-2	Reaction on the solid s	eurfaces	500000			Photochemistry				oxide su upports				alysts	s; carb	OH		, hyd	tion of rogena S					:
0.0	SLO-1 Active sites- Activation energy Catalytic activity determination for metal/metal oxide nanostructures			Electronic structure and photo	toabs	orptio	n G	old na	nopart	cle-ba	sed ca	talyst			Greer	n hous	se gas	ses: C	O2 co	onvers	sion				
S-3	SLO-2 Adsorption isotherms Langmuir-Hinshelwood mechanism for nanocatalyst		n for	Jablonskii diagram			Gold vs. Palladium catalysts for the aerob oxidation of alcohols						ic Dissociative mechanism: oxygen reduction reaction using nanocatalyst												
9.4	SLO-1 Physisorption and chemisorptions Mass transport S-4				Structure of photocatalysts			C	oxide ba	ased c	atalys				,	reacti	on us	mech	noca	talyst	_		ion		
3-4	SLO-2 Brunauer-Emmett-Teller (BET) theory Diffusion controlled process			Solar spectrum			C	atalyst)	catalyst (CNT, Graphene based Hydrogen Production using oxide and dichalcogenides based catalyst															
S-5	SLO-1	Total surface area		Adsorption equilibrium on uniform Fundamenta			Fundamental understanding	of		7	ransitio	n met	al dich	alcoge	nides	based	1	Energ	y pro	cessin	ıg: Pr	ocess	es inv	olvec	l in

			surfaces-Langmuir isotherms single-site	semiconductor interfaces	catalyst	crude oil refinery
			(non-dissociative) adsorption			
	SLO-2	Pore volume and pore size distribution	Dual-site (dissociative) adsorption	Principles and relevance to photoelectrochemical mechanism	Microporous materials: Zeolites- Zeotypes	Gasoline production
	SLO-1	Hg porosimetry method	Derivation of the Langmuir isotherm	Photocatalysis mechanism	Overall steps in zeolite crystallization	Cracking
S-6	SLO-2	N2 adsorption-desorption method	Adsorption equilibrium on non-uniform surfaces-Langmuir isotherms	Properties of good photocatalysts	Zeolite synthesis via dry gel route	Fuel cell
	SLO-1	Reaction mechanism	The Freundlich isotherm	Advantages of photocatalysts	Zeolite Y- determination of surface acidity-	Biomass gasification
S-7 SLC	SLO-2	Kinetics of the heterogeneous catalytic reactions	The Temkin Isotherm	Types of photocatalysts	Shape-selectivity	Biodiesel
S	SLO-1	Activation energy (Arrhenius equation, Eyring equation)	Activated adsorption	Homogeneous and heterogeneous photocatalyst	Synthesis of Mesoporous Silica MCM-41	Photocatalyst for self cleaning
S-8	SLO-2	Terminology in catalysis, TO(Turnover),TON(Turnover number), TOF(Turnover frequency)	Catalytic efficiency	Carbonaceous photocatalysts.	Mesoporous Carbon	Purification of water and air
S-9	SLO-1	Sequences involved in a catalysed reaction	Application of metal nanoparticles in organic reactions	Plasmonic photocatalysts.	Sulfated Zirconia	Environmental remediation
	SLO-2	Asymmetric synthesis using a catalyst	Environmental remediation	Application of photocatalyst	Ag/SiO₂ composite nanocatalysts	Future possibilities

Lograina	1. M. Albert Vannice, Kinetics of Catalytic Reactions, Springer, 2008.	B. Kurt W. Kolasinaski, Surface Science: Founda <mark>tions of C</mark> atalysis and Nanoscience, John Wiley &
Learning Resources	2. Nick Serpone and Ezio Pelizzetti, Photocatalysis: Fundamentals and Application, Wiley Interscience, 1st	Sons, England, 2 nd Edition, 2005
Resources	Edition, 1989	Nanoporous Materials: Synthesis and Applications, Edited by Qiang Xu, CRC Press, 1st Edition, 2013

Learning Assess	sment											
_	Bloom's			Cont	inuous Learning As	Final Evamination	n (E00/ weightage)					
	Level of Thinking	CLA -	- 1 (10%)	CLA – 2	? (15%)	CLA -	3 (15%)	CLA – 4	(10%)#	Filiai Examinado	n (50% weightage)	
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	
Level 1	Remember Understand	30 %	5	30 %		30 %	-	30 %		30%	-	
Level 2	Apply Analyze	40 %	1997	40 %	- 4/	40 %	- 9	40 %		40%	-	
Level 3	Evaluate Create	30 <mark>%</mark>	:] :	30 %		30 %	- 10	30 %	77-	30%	-	
Total		Total 100 %			%	10	0 %	100) %	100 %		

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2. Dr. Sudhakar selvakumar, CSIR-Central Electrochemical Research Institute, ssudhakar79@gmail.co	om 2. Dr. A. Kannan, IIT Madras, kannan@iitm.ac.in	2. Dr. M.Alagiri, SRMIST

Cour Cod		18NTE318T	Course Name					ourse tegory E Professional Elective L									L 3	T 0	P 0	C 3					
Pre-requisite Courses Nil Co-requisite Courses											Progressive Courses Nil														
Course	Offering D	Department Nar.	otechnology		Data Book / C	odes/Standards				N	il														
						11.31																			
Course	Learning I	Rationale (CLR): The	purpose of learni	ng t <mark>his course i</mark>	is to:			Lear	rning						Prog	ram L	earni	ing Oı	utcom	ies (P	LO)				
CLR-1 : Acquire knowledge on micro and nano emulsion and its stability									2 3	10	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2:		stand the various propertie				The second second		٦						5			lity								
CLR-3 :		be the concept of Mechan		tion		STATE OF THE PARTY.	Level of Thinking (Bloom)	()	(%)		e		=	Analysis, Design, R <mark>esearch</mark>			Environment & Sustainability		×		a)				
CLR-4 : CLR-5 :		stand the formulation of Na		do.	*				cy		ledc		mer	Res	<u>e</u>		staiı		Wor		Finance	_			
CLR-5:		the applications of emulsic stand the principles of NM			on	The state of the s	_ g	<u>.</u>			MOL	Sis	dol	Ju, I	sag	<u>e</u>	Su		am	_	Ε̈́	in			
CLN-0.	Onders	stand the principles of Min	N and Ollrasound	Criaracterizatio	UII	130	<u> </u>	Exported Braffolgues (%)	Expected Proliciency (%) Expected Attainment (%)		Engineering Knowledge	Problem Analysis	Design & Development	esic	Modern Tool Usage	Society & Culture	nt &		Individual &Team Work	Communication	∞ర	Life Long Learning			
						No. of the last of	Ę	3	ב ק		erin	n Ar	∞ ∞	S, D	2	∞ ∞	me		al &	ni:	Mgi	J GL	_	2	_
		0 (0) 0) 4(4)	1 500		71	THE RESERVE	<u>o</u>	5 5	ecte ecte	1	ine	plen	ign	llysi	Jern	iety	iron	S	vidu	JIII	Project Mgt.	٦	-	-5	PSO - 3
Course Learning Outcomes (CLO): At the end of this course, learne				rse, learners w	vill be able to:	The state of the s	Lev		X X		Eng	Pro	Des	Ana	Moc	Soc	Env	Ethics	Indi	Sol	Proj	Life	PSO.	PSO.	SS
CLO-1:		e basic principles in chem				A PARTY OF THE PAR	2	8	0 75		Н	М	Н	Н	Н	М	М	Η	Η	Н	Μ	М	Н	Н	Η
CLO-2:		nproperties of emulsion by				A 100 A 100 A	2		0 70		Н	М	М	Η	М	М	М	Н	М	Н	М	Н	Μ	М	М
CLO-3:		e the stabilization mechar				Will be a second	2		5 70		Н	М	Н	Н	Н	Н	Н	М	Н	М	Н	Н	Н	Н	Н
CLO-4 :	1-1-1-1	the formulation of micro ar				THE COLUMN	2		0 75		М	Н	Н	М	Н	Н	Н	Н	Н	Н	М	М	Н	Н	Н
CLO-5 : CLO-6 :		ate importance of emulsion				the same of the same of	2		0 70		H	M	H	H	Н	M	M	Н	M H	H	M M	H	H	H M	H M
CLU-6	Utilize	the knowledge on formula	uo <mark>n and characte</mark>	rization of micr	roemuisions		2	0	0 73		П	М	IVI	П	М	М	М	Μ	П	П	IVI	П	П	IVI	IVI
	ration nour)	9		2	9	9							9		Ī						9				
S-1 -	SLO-1	Introduction to Emulsion		A phase diagramicroemulsion	ram approach to n	Mechanism of Emulsific	ation			Nanoparticle formation in microemulsion Characterization and Application Microemulsion							ation (of							
3-1	SLO-2	Introduction to Micro and	Surface forces		Concept of formation in microemulsion:						Introduction in basics and principles of NMR														
	SLO-1	Definition of micro emuls	ion	Microemulsion formation Van der walls interactions			าร	400			ical R	eactio	n					NMR technique for measurement emulsion							
S-2	SLO-2	Definition of nano emulsi	ion	Ordering and	(A) 12 A M M M M M M M M M M M M M M M M M M	Electrical interactions	200	Nucleation					ı	Relaxation measurements on emulsions via CPMG experiments											
S-3 SLO-1		Theory of emulsion and I	Theory of emulsion and methods Temperature Depenmicroemulsion order			Phase inversion phenomena				Exchange mechanism in emulsions					Diffusion measurements on emulsions via PGSE and PGSTE experiments						<i>i</i> ia				
	SLO-2	-2 Theory of Micro emulsions Va			Vapor Composition from Microemulsions Phase behaviorsof emulsion			ons			Autocatalysis					Introduction and basics of ultrasound									
	SLO-1	Theory nano emulsions		Ekwall on the association structures Standard inverse boundary		lary				ani <mark>sm</mark>	of mid	roem	ulsion			Ultrasound characterization for emulsion							n		
S-4	SLO-2	Preparation of microemu	Ision	tant combination	Dynamic inversion				Critical Nucleus Size						Ultrasound characterization for microemulsion										
S-5	SLO-1	Preparation of nano emu	lsion	Physicochemi formation	istry of W/O microemulsion	Dynamic behavior of emulsion				Chemical Reaction Rate					(General features of acoustic measurement									
		Winsor's classification of		Stability of em		Spontaneous emulsifica				Nano				om W	/O en	nulsio				easure					
S-6	SLO-1	Stability of micro emulsion	ons	Droplet cluster	th empha	asis c	on self	W/O 6	emulsi	on pro	cess				ŀ	Physic	coche	mical	chara	acteriz	ation	and			

				emulsification,		characterization techniques types
	SLO-2	Rheology of microemulsion drops	Energetics of Droplet Clustering	Self-emulsification process	Nanoparticle Uptake in Reactive Surfactant Systems	Pharmaceutically applicable microemulsions
S-7	SLO-1	Applications of emulsions	Phenomenon in microemulsion	Organic Reactions in Emulsions		Places of microemulsion and emulsion in cancer therapy
3-1	SLO-2	Ostwald ripening	Percolating phenomenon in microemulsion	Microemulsions	TiO ₂ nanoparticle in micro-emulsion and photophysical properties	In vitro and in vivo evaluation
S-8	SLO-1	Flocculation	Scaling Laws	Symmetric thin liquid film with Fluid interfaces	Optical Absorption and Emission of TiO ₂ Nanoparticles in Microemulsion	Biocatalysis in microemulsion
5-6	SLO-2	Coalescence of drops	Effect of external entity-Microemulsions with mixed nonionic surfactants	Formation emulsified microemulsion	Electron Transfer Dynamics in Catechol- Sensitized TiO ₂ Nanoparticles	Biofluidic Matrices
S-9	SLO-1	Applications of emulsions	Organ chalcogenides,Aromatic Heterocyclic Compounds	Microemulsion properties		Microemulsions as Decontamination Media for Chemical weapons
5-9	SLO-2	Different application of micro and Nano emulsions	Properties of microemulsions with mixed nonionic surfactants	Characterization of emulsified microemulsion	Untertacial electron transfer dynamics	Microemulsions as toxic Industrial Chemicals

Learning 1. Fanun, Monzer., Microemu <mark>lsions: properties and applications, CRC press, 2008.</mark> Resources 2. Sjoblom, Johan., Emulsions and emulsion stability: Surfactant science series/61. CRC Press, 2008.	3. Berg J. C., An Introduction to Interfaces and Colloids: The Bridge to Nanoscience, World Scientific, 2010
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Learning Assessi	ment					Maria Land							
	Bloom's			Contin	uous Learning Asse	Final Evaminatio	n (E00/ woightage)						
	Level of Thinking	CLA -	1 (10%)	CLA – 2 (15%)		CLA – C	3 (15%)	CLA – 4	(10%)#	Final Examination (50% weightage)			
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice		
Level 1	Remember	30 %		30 %		30 %	1 1 1 1 1 1 1	30 %		30%			
Level I	Understand	30 %	_	30 %		30 %	THE PARTY NAMED IN	30 %		30%	-		
Level 2	Apply	40 %	10 to 10 to	40 %		40 %		40 %		40%			
Level 2	Analyze	40 /0		40 /0		40 /0	. 1.14.7	40 /0		4070	-		
Level 3	Evaluate	30 %	The same of	30 %		30 %		30 %		30%			
Level 3	Create	30 %		30 %	- 1	30 %	-	30 %		30%	-		
	Total	10	00 %	100	%	100) %	100) <mark>%</mark>	10	0 %		

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
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2. Dr. D.K. Aswal, National Physical Laboratory, dkaswal@nplindia.org	2. Dr. S. Ramaprabhu,IITM, ramp@iitm.ac.in	2. Dr. N. Venkatramaiah, SRMIST

Cour Cod		18NTE401T	Course Name	NANOROBOTICS		Course Category	/	Е	Professional Elective									L 3	T 0	P 0	C 3		
Co	equisite urses	Nil		Co-requisite Courses					Co	ressiv urses	e _{Nii}												
Course	Offering D	Department Nanotec	hnology	Data Book / 0	Codes/Standards	-			Nil														
						1																	\neg
Course	Learning I	Rationale (CLR): The purp	ose of learn	ing <mark>this course i</mark> s to:		L	.earni	ing					Prog	gram L	_earn	ing O	utcon	nes (P	LO)				
CLR-1:	Provide	e an insight into the fundament	als of nanor	obotics manipulation and assembly		1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2:				<mark>f nanoro</mark> botics in the modern engineering ap	plications							Ļ			lity								
CLR-3:		stand the concept of nanomani			- M = 1-M -] E	8	(%	a	,		arc			iabi		×						
CLR-4:		the techniques of automated m			A STATE OF THE REAL PROPERTY.		<u>ن</u>) -	Do	2	Jeni	ese	4)		tai.		Nor		Finance				
CLR-5 :		nowledge on theoretical and ex		aspects of Nanorobotics		9 (E	enc	mer	olwin.	S	Dpm	, R	age	e e	Sns		/ m		inal	ng			
CLR-6:	Unders	stand the principles of nanomic	ros <mark>copy</mark>		VA. 2007	Ē	Jic	aji	Kny	S	Velc	sigr	Us	草	∞8		Геа	<u>io</u>	∞ ਜ	ï.			
						Level of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society & Culture	Environment & Sustainability		Individual & Team Work	Communication	Project Mgt.	Life Long Learning	<u>-</u>	7	- 3
Course	Learning (Outcomes (CLO): At the er	<mark>id of this</mark> cou	urse, learners will be able to:	As my the	evel	Expec	Expec	Todio	Proble	Desig	Analy	Mode	Societ	Enviro	Ethics	Indivic	Comn	Projec	Life Lo	PSO-	PSO.	PSO-
CLO-1 :	Apply t	the scientific concepts underl <mark>yi</mark>	<mark>ng engi</mark> neen	ing and technological applications in nanoro	botics	2	80	75	F	M	Н	Ĥ	Н	M	М	H	Н	M	M	H	Н	Н	H
CLO-2:		e the knowledge of nanorobo <mark>ti</mark> c				2	80		F		М	М	М	М	М	Н	М	Н	Μ	Н	М	М	М
CLO-3:				dvance nanotechnology applications	WHAT STATE OF THE	2	75		ŀ			Н	Н	Н	Н	Μ	Н	Н	Н	Μ	Н	Н	Н
CLO-4:		miliarize with the new conce <mark>pts</mark>			CONTRACT OF THE	2	75		Λ		Н	М	Н	Н	Н	Н	Н	М	Μ	Н	Н	Н	Н
CLO-5:		the concept of nanorobotics <mark>as</mark>				2	75		F			Н	Н	М	М	Н	М	Н	Μ	Μ	Η	Н	Η
CLO-6:	Utilize	the concept of nanobots for <mark>Me</mark>	<mark>edical a</mark> pplic	ations		2	80	75	F	l M	Μ	Н	М	М	М	Н	Н	Н	М	Н	Н	М	Μ
		,				E. 167					-												
	ration our)	9		9	9	9						9											
S-1	SLO-1	Types of interaction forces		Dieelectric materials	Sensors-classifications				omputer									c- intro					
0-1	SLO-2	Interaction forces in nanomar	ni <mark>pulation</mark>	Dielectric polarization	Art of compressive sensir	ng			CAD mod						,	Nanoi	roboti	с Аррі	licatio	ns			
S-2	SLO-1	Actuation		Electro rotation	Fast imaging system				lutomate bjects	d man	ipulatio	on of <mark>n</mark>	nicro-	nano		Endo	сору	imagi	ing				
3-2	SLO-2	Electro kinetic based actuatio	n	Theory and modelling of electro rotation	Compressive sensing bas system	sed fast i	magi	ng A	\utomate	d man	ipulatio	on of n	anos	tructu	res	Wirele	ess ca	apsule	s ena	loscop	oy ima	ging	
	SLO-1	Carbon nanotubes		Properties of fluid medium	SPMbasics	47 1	m	A	utomate	d man	ipul <mark>ati</mark> d	on of N	<mark>lan</mark> or	ods	Į,	Energ	ıy har	vestin	g				
S-3	SLO-2	Electro kinetic manipulation o nanotubes	AFM based imaging			1	lutomate	d ma <mark>n</mark>	i <mark>pulati</mark> o	on of N	lanov	vires		Energ	y har	vestin	g by ı	nanor	obotic				
0.4	SLO-1				Atomic manipulation in A	-M		1	utomate	d <mark>ma</mark> n	ipulatio	n of n	anoti	ubes	- 1	Gastr	o-inte	stinal	tract-	introd	luction	1	
S-4		2 Nanoparticles Nanoparticles by dielectrophoretic			AFM based nanorobotic s				utomate														
	SLO-1 Biological entities CNT-definition			Augmented reality	-			lugmente							Capsules robot in gastro-intestinal tract Nanorobots - introduction								
S-5	SLO-2					AFM based nanorobotic system enhanced										Nanorobots –basic design							
	SLO-1 Laser based actuation-fundamentals Scanning probes Hardware setup for Sensing			ing		F	Real time	fault d	letectio	n				Соор	erativ	e cont	rol de	sign f	or nar	norob	ots		
S-6	SLO-2				Software setup for Sensin			Methods of real time fault correction Design and application of oncology															

	SLO-1	Optical tweezers	Atomic scale stick-definition	Hardwaresetup for fast imaging system		Drug delivery system
S-7	SLO-2	Applications of optical tweezers	Reducing atomic scale stick	Softwaresetup for fast imaging system		Cooperative control design for nanorobots in drug delivery
S-8	SLO-1	Manipulation of biological entities	Slip motion	Experiments on nanomanipulation of nanoparticles-I	on-line fault detection	Medical applications of nanorobots
3-0	SLO-2	Manipulation of chemical entities	Nanomanipulation by slip motion	Experiments on nanomanipulation of nanoparticles-II		Medical applications of nanorobots: current proposals and designs
S-9	SLO-1	Piezoelectricity	Feedback control	Experiments on nanomanipulation of nanoparticles-III	riypotriesis	Therapy using nanorobots
3-9	SLO-2	Piezoelectric enabled actuators	Slip motion by feedback control nanomanipulation	Experiments on nanomanipulation of nanoparticles-IV	Experimental results of the data to test the hypothesis	Cancer targeted therapy using nanorobots

	 Ning Xi, Guangyoung Li, "Introduction to Nanorobotic Manipulation & Assembly" Artech House Press, 2012 Yi Guo, "Selected Topics in Micro/Nano-robotic for Biomedical Applications", Springer, 2013 	3.	3. Klaus D. Sattler, "Hand Book of Nanophysics: Nano medicine & Nanorobotics", CRC Press, 2010
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Learning Assess	sment				100 may 1								
	Dia ami'a			Contin	nuous Learning Ass	essment (50% weig	htage)			Final Evansination	n (EOO) waishtana)		
	Bloom's Level of Thinking	CLA – 1 (10%)		CLA – 2 (15%)			3 (15%)	CLA – 4	· (10%)#	Final Examination (50% weightage)			
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice		
Level 1	Remember Understand	30 %	10	30 %	To the second	30 %		30 %	-	30%	-		
Level 2	Apply Analyze	40 %	Z- E	40 %		40 %	11年10月	40 %	-	40%	-		
Level 3	Evaluate Create	30 %	-	30 %		30 %	Sale of the	30 %	-	30%	-		
	Total	1(00 %	100	0 %	10	0 %	100) %	100 %			

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
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Cou Coo		18NTE402T Course Name MICRO AND NANOFLUIDS Course Category E Pr								Professional Elective L T P C 3 0 0 3									C 3				
Co	requisite ourses	Nil	Co-requisite Courses						Progre Cour		Nil												
Course	Offering D	Department Nanotechnology	Data Book / C	Codes/Standards	-				Nil														
	5 "			ALC: N																			
(CLR):	ng Rational	The purpose of learning	1753	H. Lawrence		L	.earni	ng					Prog	gram l	Learn	ing Ou	utcom						
	CLR-1: Acquire knowledge on various physical principles related to liquid flow					1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
	CLR-2: Understand theory of fluid flow in micro and nano-size devices.								-			된			Environment & Sustainability								
CLR-3		be the concept of heat and mass transfer ph	and the bottom		of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	ge		ŧ	Analysis, Design, Research			inat		ork		ģ					
CLR-4 CLR-5		s thermal sciences with colloidal sciences, bi	lological sciences			過	ည်	ent	led		me	Reg	ЭС		sta		W		Finance	0			
CLR-5		nowledge on electrochemistry stand the applications of micro and nanofluic	dion			D D	Cie.	Ē	NO.	Sis	dole	gu,	sac	<u>e</u>	S		am	_	ᆵ	ni.			
CLK-0	. Onders	stand the applications of micro and handhald	JICS		-	Ξ	Jo J	Ittai	Engineering Knowledge	Problem Analysis	Design & Development	esi	Modern Tool Usage	Society & Culture	nt &		エ Individual & Team Work	Communication	Project Mgt. &	Learning			
				NO. THE PARTY NO.		Ę	<u>8</u>	b	eri.	n A	8	S, D	2	∞ ∞	me		ıal 8	nic	₩	J G	_	2	3
Learni	ng Outcom	nes Augusta				9	ecte	ecte	in ee	Jen	igi	lysi	lem	iety	<u>.</u> .	છ	vidu	ושר	ect	Life Long	-1		-
(CLO):		At the e <mark>nd of this</mark> , lea	arners will be able to:	A DOWN		Level	S.	없	ling	5 C	Des	√na	Noc	300	N.	Ethics	ndi	Son	70	<u>i</u> ę	PSO	PSO	PSO-
CLO-1		the principles of liquid flow	The second second			2	80	75	Н	M	Н	Н	H	M	М	H	H	Н	M	H	H	H	H
CLO-2		ze flow of fluid in micro and n <mark>ano-size d</mark> evice		The state of the state of		2	80	70		М	М	Н	М	М	М	М	Μ	Н	М	Н	М	Μ	Μ
CLO-3		the knowledge of micro and <mark>nanofluidi</mark> c devi		WELL CO.		2	75	70		М	Н	М	М	Н	Н	М	Н	Н	Н	Н	Н	Н	Н
CLO-4	: Utilize	the opportunities in the eme <mark>rging fiel</mark> d of mi	cro and nanofluids			2	80	75		Н	Н	М	Н	Н	Н	Н	Н	Н	М	Н	Н	Н	Н
CLO-5		the concept electrochemistry		and the state of the state of		2	80	70	Н	М	Н	Н	М	М	Н	Н	Μ	Н	М	Н	Н	Н	Н
CLO-6	: Utilize	e the new concepts of real-tim <mark>e nanom</mark> anipul	lation & assembly			2	80	75	Н	М	М	М	Н	М	М	М	Н	Н	М	Н	Н	М	Η
D	ıration		The second secon			-	-									I							
	hour)	9	9	9 9 Heat transfer phenomena in channels and Elements of electrochemistry and the						9													
S-1	SLO-1	Microscale liquid flow - Introdu <mark>ction</mark>	Microscale viscous flow - Essentials	Heat transfer phenom tubes				6	Elements of electrical <mark>d</mark> o							Elem	ents (of cell	biolo	gy and	d appi	licatio	ns
	SLO-2	Micro and Nanofluidics	Structure of flow in a pipe or channel	Mass transfer phenon tubes	nena in	chan	nels	and	The structur	re of v	water :	and id	onic s _l	<mark>oe</mark> cie:	S	Nucle	eic ac	ids an	d pol	ysacc	haride	es	
0.0	SLO-1	Micro and Nanofluidics devices	Poiseuille flow in a pipe	One-dimensional temperature distribution channel flow				ons	Chemical bo	onds	in bio <mark>l</mark>	ogy a	nd ch	emist	ry	Prote	ins : I	Proteii	n fund	ction			
S-2	SLO-2		Poiseuille flow in a pipe – derivation of maximum velocity	Temperature distributions in ch (Quantitative approach)			nel flo)W	Hydration o	f ions						Prote	in str	ucture)				
S-3	SLO-1		The velocity in slip flow - gases	Thermal and mass transfer e regions			се		Chemical po	otenti	al					Some	e com	mon p	orotei	ns			
	SLO-2	Constitutive Laws	The velocity in slip flow - Liquids	Mass transfer entrance regio					Chemical po	otenti	al (Qu	antita	ative a	pproa	ach)	Few p	polyp	eptide	chair	ns are	usefu	ul	
C 4	SLO-1	Determination of transport proportion	Flow in a thin film under gravity	The temperature distribution developed tube flow			ly		The Gibbs f		,				,	Prote		•					
S-4	SLO-2	Determination of transport properties –	Flow in a thin film under gravity – film flow rate	Nusselt number		Chemical equilibrium					Cells - The cell membrane												
S-5	SLO-1		Fully developed suction flows	The Graetz problem for	or a cha	annel			Electrochemical potential					Membrane transport									

	SLO-2	Continuum approximation and its limitations	Velocity profile – suction flow	The Graetz problem for a channel (Quantitative approach)	Acids, bases, and electrolytes	Ion channels
S-6	SLO-1	Kinematics - Surface forces	Developing suction flows	Mass transfer in thin films	Site-binding models of the silica surface	Applications - DNA transport
3-0	SLO-2	Body forces	Darcy's law	A thin liquid film falling under gravity	Polymer surfaces	DNA current
S-7	SLO-1	Navier-Stokes equation	Surface tension driven flow	Classical Taylor–Aris dispersion	Qualitative description of the electrical double layer -	Development of an artificial kidney : Background
3-1	SLO-2	Navier–Stokes equations in Cartesian coordinates	Surface tension driven flow (Quantitative approach)	Classical Taylor–Aris dispersion (Quantitative approach)	Qualitative description of the electrical double layer - triple layer model	The nanopore membrane for filtration, Hindered transport
S-8	SLO-1	Energy transport	Stokes flow past a sphere	The stochastic nature of diffusion	The electrical double layer on a cylinder	Biochemical sensing : Biosensor, Receptor -based classification of biosensors
	SLO-2	Energy transport - conduction heat transfer	Stokes flow past a sphere – drag calculation	Brownian motion	The electrical double layer on a sphere	Transducer-based classification of biosensors
S-9	SLO-1	Two-dimensional, Steady flow	Sedimentation of a solid particle	Unsteady mass transport in uncharged membranes	Electrical conductivity in an electrolyte solution.	Evaluation of biosensor performance
3-9	SLO-2	Incompressible flow	Simple model for blood flow	Temperature and concentration boundary layers	Electrophoretic effect	Nanopores and nanopore membranes for biochemical sensing.

Learning Resources	 Terrence Conlisk "Essential of Micro and nanofluidics: with applications to biological and chemical sciences" Cambridge University Press, 2018. Joshua Edel "Nanofluidics" RCS publishing, 2016.
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- Henrik Bruus "Theoretical Microfluidics" Oxford Master Series in Physics, 2007.
 Patric Tabeling "Introduction to Microfluids" Oxford U. Press, 2005.
 Christ of M. Niemeyer & Chad A. Mirkin, "Nanobiotechnology: Concepts, Application and Perspectives", Wiley VCH, 2004.
 Sarit K.Das, Stephen U.S. Choi, Whenhua Yu & T. Pradeep, "Nanofluids Science and Technology" Wiley Interscience, 2007.

Learning Assessn	nent										
	Bloom's			Continu	ious Learning As	sessment (50% wei	ghtage)			Final Examination	n (E00/ weightege)
	Level of Thinking	CLA –	1 (10%)	CLA – 2 (15%)		CLA -	- 3 (15%)	CLA – 4	(10%)#		n (50% weightage)
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember	30 %		30 %		30 %		30 %		30%	
Level I	Understand	30 %		30 %	- 1	30 %	-	30 76		30%	-
Level 2	Apply	40 %	17500	40 %		40 %		40 %		40%	
Level 2	Analyze	40 /0		40 /0	_	40 /0	-	40 70		4070	-
Level 3	Evaluate	30 %	- 11	30 %		30 %	17.5%	30 %		30%	
Level 3	Create	30 /		30 /6		30 /0		30 /6		3070	-
	Total	10	0 %	100	%	1	00 %	100) %	10	00 %

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Course Designers		
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2. Mr. Mohammed Shafi, Holmarc Opto-Mechatronics Pvt. Ltd, Cochin, optics@holmarc.com	2. Dr. Dillip K. Satapathy, IITM, Chennai, dks@iitm.ac.in	2. Dr. Surya K Ghosh, SRMIST

Cou		18NTE403T	Cours Name	$N\Delta N(t) = 0$	CHNOLOGY FOR	ENERGY SYSTEMS		ourse t <mark>egory</mark>		Е				Profe	ssiona	Elec	tive				L 3	T 0	P 0	C 3
Co	requisite ourses	Nil		Co-requ Cours	ses						Progre Cou		Nil											
Course	Offering D	Department Nanoteci	nnology		Data Book	/ Codes/Standards	1	-			Nil													
Learni (CLR):	ng Rationa	The purp	ose of learning	g this is to:	18.5	Z III	1	L	earnin	g					Progra	am Le	earnin	g Outco	omes (PLO)				
CLR-1		the importance of renewable er	ergies for the	safe survival of hum	an kind on the ear	th		1	2	3	1	2	3	4	5	6	7	8 9	10	11	12	13	14	15
CLR-2		stand the basics of green energ								7	7			U			ility							
CLR-3		stand how nanotechnology can			i <mark>on from various s</mark> e	ources		om)	(%)	(%)	a e		Ħ	ear			nab	¥	[Ф				
CLR-4 CLR-5	. Acquir	e the methods of hydrogen pro e knowledge on the fabrication			s useful for energy	production, transporta	tion and	ng (Blo	ciency	nment	owled	Sis	lopmer	jn, Res	sage	a <u>r</u>	Sustai	JW me		Finano	Jing			
CLR-6	storage: Acquir	e e knowledge on design, fabrica	ati <mark>on, char</mark> acte	erization of advanced	l energy systems		H.	Thinki	d Profi	d Attai	ring Kr	Analy	& Deve	, Desig	Tool U	& Culti	nent &	% % C	nication	Mgt. &	g Learning			
Learni (CLO):	ng Outcom	nes At the en	<mark>d of this</mark> , lear	rners will be able to:	- 100	h health	14.5	evel of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society & Culture	Environment & Sustainability	Ethics Individual & Team Work	Communication	Project Mgt. & Finance	Life Long	PSO - 1	PS0-2	PSO - 3
CLO-1	14-45	y the urgency of energy solution	ns and the exp	pectations of Nanoted	chnology in providi	ng long term solutions	to these	2	80	75	Н	М	Н	Н				<u>н</u> -		М	Н	Н	Н	Н
CLO-2	. Descri	be the concepts of heteroge <mark>nee</mark>	ous catalysis,	and further apply in t	he designing of va	rious nanocatalysts for	energy	2	80	70	Н	М	М	Н	М	м	Н	н л	1 M	Н	Н	М	М	М
CLO-3		Nanotechnology and nanom <mark>ate</mark>				ems and fuel cell techn	ologies	2	75	70	Н	М	Н	Н				M F			Н	Н	Н	Н
CLO-4		the Nanotechnology and nan <mark>on</mark>						2	80	75	M	Н	Н	М				H F			Н	Н	Н	Н
CLO-5 CLO-6		the thermoelectric principles <mark>an</mark> Nanotechnology in the sensin <mark>g</mark>				noelectric devices	- 1	2	80	70 75	H	H	H M	H				M N		H	H	Н	H M	H
020 0	. propry	rvanoteennology in the sensing	and remodiat	ion or politicanto in an	dia water				00	70		- "	101	.,	"	IVI	101	101		101		11	171	
	uration hour)	9		refer to	9	1////	9				7		9							ç)			
	SLO-1	Energy Challenge in the 21st	Century	Terawatt challenges i	in photovoltaics	Bulk thermoelectri					w tempe	rature	fuel c	ells				troducti notech		to to hy		tribut 1 prod		of 1
S-1	SLO-2	Fuel share of world total prin	nary <mark>energy</mark> i	How can photovoltaic <mark>racti</mark> on of energy der	es meet a significar mand?	Franz relationship	re of merit	, Wiea	leman	n- de	pact on i velopme							ethods portan						
S-2	SLO-1	Nanotechnology in energy res		Limits in conversion e		Bulk thermoelectri Selection criteria f materials				-,	thode ar	id a <mark>no</mark>	de rea	ction				anomat emical		bas	sed	pho	toeled	tron
3-2	SLO-2	The importance of nanotechnimproving the nanoscale ener	av devices	The <mark>oretical limits of</mark> p and poss <mark>ible improve</mark> approaches		Important three gu					ryge <mark>n rec</mark> actions, r						PE pro	anocrys EC sola oducing	r cells, g hydro	Wate ogen	r splitt	ing fo	r	
S-3	SLO-1	Conventional fossil fuels Unconventional fossil fuels		Hybrid concepts Effect of size of the quantum nanowires on the conversion classical and quantum size el			efficie	ency,	ncy, Practical fuel cell catalysts and Electrolytes such as nanotubes and dis production of hydrogen		nd disc		pholo	<i>9y</i>										
	SLO-2	Discussion about greenhouse	gases,	Combining organic and inorganic cells, Thermoelectric properties of					scale:							n, Hydrogen storage:								

		Clean energy sources and advantages	concept of heterojunction-type photoactive layer, hole-electron pair	modeling	temperature cell, Non-precious catalysts, electrolytes	technological barriers
S-4	SLO-1	Nanotechnology in fuel production	Semiconductors optical properties	Understanding thermoelectric properties on the nanoscale using modeling	High-temperature polymer electrolyte membranes, membrane-electrode assembly	Methods of improving efficiency of cells, HOMO-LUMO gap, several examples of sensitization
•	SLO-2	Making efficient and economical engines	Basics of semiconductors, bandgap	Importance of characteristic length scale, Bi nanostructures	High temperature fuel cells	Hydrogen storage technology –potential storage materials hydrogen sorption
S-5	SLO-1	Renewable energy sources-Photovoltaics	charge carrier transport in semiconductors	Importance of Bi nanowire and its diameter in thermoelectricity	Development of cells that operate up to 700°C	Hydrogen storage by Physiosorption and chemisorption methods
S-3	SLO-2	Emission spectra and color as a function of particle size of a quantum dot	Optical properties of semiconducting thin films, Optical absorption	Silicon nanowire and importance at nanoscale	High temperature ceramic electro catalysts	Properties of materials: physical storage, thermodynamic and kinetics
S-6	SLO-1	Example of nc-CdTe film on ITO-coated glass solar cell	Narrow and wide band gap materials, importance of optical absorption		temperatures triple phase boundary	Bond strengths for Physiosorption and chemisorption, The desirable range of bonding energies
•	SLO-2	Gratzel Cell Examples of nanostructured films used for PV cells	Selection of Dye sensitizer for better optical absorption, n-CdS band gap	Thermionics nanocomposites	Porous Ni-Ceramic electrolyte (YSZ), LaSrMnOe ceramic electrolyte	Nanostructured carbon
	SLO-1	Hydrogen production	Dye molecular engineering	Description of electron motion across the barrier	Application of high temperature ceramic electro catalysts	MWNT, SWNT, carbon nanorods and aerogels etc.
S-7	SLO-2	Mechanisms of dye sensitization and sensitization by composite semiconductors	HOMO-dye, LUMO gap	Si/SiGe superlattice nanowire, prototype InP/InAs superlattice nanowire	Various examples of high temperature fuel cells where ceramic electro catalysts are used	zeolites- clathrates- polymers
S-8	SLO-1	Hydrogen energy system. Advantages of hydrogen fuel	Stable self-assembling dye. Monomolecular layer	Thermoelectric nanocomposites	Solid oxide fuel cells (SOFCs)	Reversible occlusion of gases. Metal- organic frame works and their storage efficiency
5-0	SLO-2	Fuel cells, REDOX potentials, electrochemical reactions in different types of fuel cells	Structure of the Z-907 amphiphilic Dye	PbTe-PhSeTe quantum dot	Mechanical properties, Efficiency, operating temperatures	Metals and complex hydrides- chemical hydrides nanocomposites
S-9	SLO-1	Microbial fuel cells, polymer electrolyte fuel cells	Electron transfer mechanism from TiO2 to Dye, Dye excitation and relaxation mechanisms	PbTe-PbSe bulk alloys, superlattice systems	Dry hydrocarbons in SOFC	Hydrogen storage by chemisorption, basic structures of metal and complex hydrides, chemical hydrides, Nanocomposites
	SLO-2	Introduction to Thermoelectricity	The nanostructured semiconductors	Application of thermionic and thermoelectric nanocomposites	Applications of Fuel cells	Some examples of storing hydrogen with the above materials

Learning	1. Javier Garcia-Martinez, Nanotechnology for the Energy Challenge, WILEY-VCH Verlag GmbH & Co., 2010	3.	Darren P. Broom, Hydrogen Storage materials: The characterization of their properties,
Resources	2. 2. Anatoli Korkin, David J, Nanoscale Applications for Information and Energy Systems, Springer, 2013		Springer, 2011

	Bloom's			Conti	nuous Learning Ass	essment (50% weigh	ntage)			Final Examination (50% weightage		
	Level of Thinking	CLA – 1 (10%)		CLA – 2 (15%)		CLA – 3	3 (15%)	CLA – 4	l (10%)#	Filiai Examination	i (50% weightage)	
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	
Level 1	Remember Understand	30 %	- 1	30 %	Law William	30 %		30 %	-	30%	-	
Level 2	Apply Analyze	40 %		40 %	JUL.	40 %	1 6	40 <mark>%</mark>	-	40%	-	
Level 3	Evaluate Create	30 %	-	30 %	-	30 %	311/20	30 %	-	30%	-	
	Total	10	0 %	100	0 %	100) %	10) %	10	0 %	

CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.

Course Designers	是在15年10日本 · · · · · · · · · · · · · · · · · · ·	
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Cour Cod		18NTE404T	Course Name	PHOTOVOLTA	AIC TECHNOLOGY	Cour Categ		Е		Professional Elective						L 3	T 0	P 0	C 3			
	equisite urses	Nil	Co-requisite Courses	Nil						ressive urses	Nil											
Course	Offering D	Department Nanotechnology		Data Book / Co	odes/Standards				Nil													
				124	AVAI																	
Course	_		rning t <mark>his course i</mark> s to:	1000			Lear	rning						am Le	earnin	g Outco						
CLR-1		the basic principles and design of photov		3.2			1 2	2 3	1	2	3	4	5	6		8 9	10	11	12	13	14	15
CLR-2		stand the key properties of semiconductor		ology			Э.					U			iity							
CLR-3	Learn	about basic photovoltaic device structure	and design	10 1 1	COLUMN TWO		(E) (S	8 8			¥	ear			nab	돈		a)				
CLR-4		p an understanding of the primary photo		nd their design	5 3 5 5 6	i i		int Cy	Da Da	æ.	mer	Ses	Ф		stail	§		Finance	_			
CLR-5		xposure to the various application <mark>s of ph</mark> e knowledge on advanced conce <mark>pts expl</mark>) gi		No.	Sis.	lop	Ju, F	sag	<u>e</u>	Sus	a	_	Ei	ing			
CLK-0	Acquire	e knowledge on advanced concepts expr	orea in photovoltaics		277		IN I	ttail oil	\frac{1}{2}	aly	eve	esic		H H	t &	<u> 1</u>	atior	∞ర	earr			
			1	-		į	of Thi	ted A	eering	em Ar	n & D	sis, D	m Toc	ty & C	nmer	dual &	nunica	t Mgt	ong L	-	-2	က
Course	Learning (Outcomes (CLO): At the end of this o	ourse, learners will be able to):	A. Jak		Level of Thinking (Bloom)	Expected Proliciency (%) Expected Attainment (%)	Fnoineering Knowledge	Problem Analysis	Design & Development	Analysis, Design <mark>, Research</mark>	Modern Tool Usage	Society & Culture	Environment & Sustainability	H Ethics H Individual & Team Work	Communication	Project Mgt.	Life Long Learning	PSO-	PSO-	PSO - 3
CLO-1	: Differe	entiate between different type <mark>s of phot</mark> ovo	oltaic technologies					80 75	Н	Н	Н	H	Н	Н	М			Н	Н	Η	Н	Н
CLO-2	: Interpr	et important properties of se <mark>miconduc</mark> tor	s relevant to photovoltaics		The second			80 70			М	Н	М	Н		H M		Н	Н	М	М	М
CLO-3		different photovoltaic device <mark>design c</mark> onc		3.9VIV.5	No. of Section 1			75 70			Н	Н				M M			Н	Н	Н	Н
CLO-4		iate advancement of differe <mark>nt genera</mark> tion		712000				80 75			Н	М	Н	Н		H H	Н	М	Н	Н	Н	Н
CLO-5 CLO-6		riate the advanced concepts <mark>and expl</mark> ora			The same of the sa			30 70 30 75	H		Н	H	H	M		<u>Н М</u> Н М		H	H	H	H M	H
CLO-6	. Penon	m photovoltaic device testing <mark>and calc</mark> ula	uons	-		-	2 8	0 73	п	IVI	М	П	п	М	М	H M	П	IVI	П	П	IVI	П
	ration nour)	9	9			9	H	1.0			9							9)			
	SLO-1	Renewable energy technologies	Optical absorption		Solar Cell parameters	3			Si photovo	Itaics					<i> -</i>	-V photo	ovoltaio	cs				
S-1	SLO-2	Present and future global issues	Carrier photogeneration		Device testing				Fabricatio		solar (ells				ılti-junc			lls			
	SLO-1	Historical development of PV; drivers-	Band gap		Efficiency calculation	<u> </u>			High effici				Si sola	ar cell		ectral s						
S-2	SLO-2	Commercialization/economic factors	Direct vs. indirect bandga		(EFF, VOC, JSC) for		•		Si PV des			<i>y</i> = 10				aInP/G			iunc	ion sc	lar ce	الد
S-3	SLO-1	asic components of PV systems Minority carrier transport properties- Non-idealities Polycrystalline/microcrystalline Si s					olar		ndgap			•		nar oc	-							
3-3	SLO-2	Mechanism of PV	Carrier recombination-lifet	time and defects	Series resistance, sh	unt recieta	nco		Amorphou	e Si er	lar co	le			Sc	lar spe	otrum i	natch	ina			
	SLO-2	Sun as a source of energy	Band to band and Shockle		Optical loss mechanis		ince		Heterojun							nnel jui			iriy			
S-4	SLO-1	The solar spectrum	High injection effects	,	Implications on device		anaa		p-i-n and r							ırrent m			otiono			
	SLO-2	Measuring sun light	Surface and interface reco		Electrical loss mecha		aiice		p-ι-ιι αιια ι Thin film I							ncentra)	-
S-5	SLO-1	Atmospheric effects	Implications on device per		Implications on device		anco		Chalcopyr						_	ncentra			เสเบร	UFV)	-	\dashv
			Basics of solar cell de											V cells	_	uos,				\dashv		
S-6	S-6 SLO-2 Air mass (AMO, AM1, 5) Carrier transport under broad spectrum Mini			Minimization of losse		ce design CdTe/CdS thin film solar cells CPV cells Superstrate structure Terrestrial CPV					V systems											
nurrimation				Lateral design and Ve	artical dos	ian		CulnGaSe	21040	thin fi	lm col	tochr	ologi	os Sr	aca nh	atovolt	aice					
3-1	JLU-1	Orassilication of photovoltalc	i notocuirent		Lateral uesign and Ve	riical ues	iyii		GuiriGaSt	2/003	ann II	ııı cel	(CCIII	uiugi	es of	ace pii	JUVUIL	αιυδ				

		technologies				
	SLO-2	Generations of solar cells	Spectral response	Cyclotron frequency	Earth abundant alternatives	Radiation effects in semiconductors and solar cells
S-8	SLO-1	1st generation photovoltaics	Current transport models	Optical versus electrical tradeoffs and optimization	Dye-Sensitized solar cells	New concepts
	SLO-2	Silicon technology	Non idealities	Band gap and other material properties	QDSSCs	Quantum dots, wires
S-9	SLO-1	2nd generation photovoltaics	Real p-n diodes	Spectral utilization	Organic photovoltaics	Intermediate band solar cells
3-9	SLO-2	3rd generation photovoltaics	Temperature effects	Light management	Hybrid solar cells	Multiple exciton generation

Learning	 Solanki C.S., "Solar photovoltaics - fundamentals, technologies and applications", 3rd edition, PHI LearningF	1 3.	Moller H.J., "Semiconductors for Solar Cells", Artech House, 1993. Green M.A., "Third Generation Photovoltaics: Advanced Solar Energy Conversion", Springer, 2006Fundamentals of Solid State Engineering, Manijeh Razeghi, KLUWER ACADEMIC PUBLISHERS, 2002
Resources	Ltd, New Delhi, India Fonash S.J., "Solar Cell Device Physics", Academic, 2010	4.	

Learning Assessi	ment				1845.3	ALCOHOL: N						
	Bloom's			Conti	nuous Learning Ass	essment (50% weig	htage)			Final Evamination	on (50% weightage)	
	Level of Thinking	CLA – 1 (10%)		CLA – 2 (15%)		CLA –	3 (15%)	CLA – 4	∤ (1 <mark>0%</mark>)#	Filiai Examinado	on (50% weightage)	
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	
Level 1	Remember	30 %		30 %	317000	30 %	10000	30 %		30%		
Level I	Understand	30 %	100	30 %		30 %	200	30 %		30%	-	
Level 2	Apply	40 %		40 %	TO SECUL	40 %	100	40 %		40%		
Level 2	Analyze	40 /0	/ W	40 /0		40 70	Aller St.	40 /0		4070	-	
Level 3	Evaluate	30 %		30 %		30 %	15 ST 14 ST	30 %		30%		
Level 3	Create	30 /		30 /6		30 /0		30 /8		3076	-	
	Total	10	0 %	100	100 %				0 %	100 %		

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Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
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Cour		18NTE405T	Course Name	NANO	TECHNOLOGY IN COSMET	CS				Cou Categ		Е		Pr	ofess	sional	Electi	/e		L -	Γ F	C 3
Co	equisite urses Offering D	Nil Department Nanotechnology	Co-requ Course	es IVII	Codes/Standards					gress ourse		Nil										
000.00		indicate in the second of the		2010 20011		7			1													
(CLR):	ng Rationa	The purpose of lea	rning <mark>this is to:</mark>	100,	History III	- 1	_earn						Prog	gram L	_earn	ing O	utcom	es (PL				
CLR-1		stand the basis of cosmeceuticals				1	2	3		1	2 3	3 4	5	6	7	8	9	10	11	12	13 1	4 15
CLR-2		the classification and various types of co							1			5			ili Ili							
CLR-3		e knowledge about ingredients and eff <mark>ec</mark>	t of inclusion of nanopartic	cles in cosmetics	CONT. 100 P. CO.	l (mo	8	(%)		Э	7	ear			nab		춪		a)			
CLR-4		quainted with current trends in the fi <mark>eld c</mark> quainted with future aspects of cos <mark>metic</mark>				음	ें	ent (led	Š	Zes Ses	a)		stai		8 N		anci	_		
CLR-5		quainted with future aspects of cosmetic quainted with future aspects of a <mark>esthetic</mark>) gu	Ser	nme		NOL .	SIS	J. L.	sag	<u>ne</u>	S		an	_	Finance	ie			
CLIN-0	Gel ac	qualified with future aspects of aesthetic	IIIIpianis	LIVE TO	THE RESERVE OF THE PERSON NAMED IN		Expected Proficiency (%)	Expected Attainment (%)		Engineering Knowledge	Wroblem Analysis	Analysis, Design, Research	T Modern Tool Usage	Society & Culture	Environment & Sustainability		エ Individual & Team Work	Communication	Project Mgt. &	Life Long Learning		
			RESERVE STATE	Ę	P P	P P		rij.	A G	, O	P	& C	me		a 8	ig	Mg	J G				
Learnir	ning Outcomes At the and of this degrees will be able to						ecte	ecte		Jue I	len len	Analysis,	em	ety	5	SS	/jgr	핕	ect	l l	PSO - 1	H PSO -3
(CLO):	ig Gutooiii	At the <mark>end of this</mark> ,	learners will be able to:	PRACTICAL PROPERTY.	A DOMESTIC OF THE PARTY OF THE	eve	ı X	dx		ing .	20 20	Ana	Pop	Soci	Ē	± Ethics	ρĺ)	ō	<u>i</u> e	ည္က ၂	ر ا کا
CLO-1							80	75		H	M	H	H	M	М	Н	H	Н	M	H	H	HH
CLO-2	Disting	uish effects of using nanopa <mark>rticles ove</mark> r o	conventional methods in c								M		М	М	М	Н	М					И М
CLO-3	Analyz	e about current trends in the field of cosr	metics	2.5.9	William Commence	2	75			Н	M H	H H	Н	Н	Н	М	Н	Н	Н	Н	Н	н н
CLO-4		basic cosmetic concepts in m <mark>aking na</mark> noi		73 11 10 10 10 10	CHANGE OF THE	- 2	80			M .	H F	н М	Н	Н	Н	Н	Н		М	Н	Н	Н Н
CLO-5		knowledge in making organo <mark>silicone f</mark> orr	mulation			2	80					Н Н	Н	М	М	Н	Μ					Н Н
CLO-6	: Apply I	knowledge in making aesthe <mark>tic implan</mark> ts	(4)	Control of the		2	80	75		Н	M	1 H	Н	М	М	Н	Н	Н	М	Н	H	ИН
				1000						ш.	- %											
	ration nour)	9	9		9				<u>II</u>		4	9				9						
S-1	SLO-1	Introduction to cosmetics	Oily materials: introduction wax	ction, oils and fats,	Film formers			sy	/stems			s novel		ery				elivery	•			
	SLO-2	Purpose of cosmetics	Hydrocarbons		Polymers as film formers			N	anoem	ulsion	in cos	metics						elivery				
S-2	SLO-1	Meaning of cosmetics	Higher fatty acids		Thickeners			N	ano <mark>c</mark> ry	stals i	n cosr	netic <mark>s</mark>		i	(contai	ning v	f dual ı itamin	e for	cosm	etics	
0-2	SLO-2	SLO-2 Classification of cosmetics Higher alcohols, esters, silicones Types of thickners						S	ilicones	s and I	beyon	d						f dual ı itamin				
S-3	SLO-1	Cosmeceuticals	Surface active agents	: introduction	Polymers in hair colouring		1		rganon									ation o ntainin			delive	ry
5-3	SLO-2	Pharmaceuticals in cosmetics	Anionic surfactant		Types of polymers in hair c	olour			ew este			<mark>g pr</mark> ope ones	erty foi	•				racteri			niques	used
C 4	SLO-1	Quality characteristics	Cationic surfactants		Conditioning polymers				licones							Ortho	oedic .	implan	t			
S-4	SLO-2	Quality assurance	Amphoteric surfactant		Surfactants in conditioners		Minimalizing undesirable								Conventional types of Orthopedic implant						nplant	
	SLO-1 Development process of cosmetics Non-ionic surfactant Cleansing agents					0.1010			Substantive silicones C					Orthopedic implant titanium rods								
S-5	S-5 SLO-2 Cosmetics for Skin Other surfactants Ethoxylated alcohols					Icohols Effect of substantive silicones Advantages of C				f Orthopedic implant of												
S-6	S-6 SLO-1 Cosmetics for hair Humectants : introduction Silicones						Organo-modified delivery systems Preparation of keratin coatings for															

						orthopedic implant titanium rods
	SLO-2	Cosmetics for nails	Choice of humectants	Emulsions	Types of Organo-modified delivery systems	Characterization of keratin coatings
S-7	SLO-1	Cosmetics colour materials	Unusual humectants	Types of polymeric systems	Silicones personal care delivery system	Nanotherapeutics as a treatment for inflammation
	SLO-2	Cosmetics and fragrances	Special uses of humectants	Natural polymers	Liposomes in cosmetics	Cosmetic repair and restoration
	SLO-1	Oral care cosmetics	Antioxidants: introduction	Stimuli responsive polymeric systems	Niosomes in cosmetics	Moisturization of skin
S-8	SLO-2	Body cosmetics	General oxidative theory, measurement of oxidation	pH-responsive	Microemulsion in cosmetics	Fortification of the skin barrier
	SLO-1	Physical chemistry of cosmetics	Assessment of oxidant efficiency	Thermal responsive	Nanoemulsion in cosmetics	Contact lenses types
S-9	SLO-2	Stability of cosmetics	Choice of antioxidant	Photo responsive	Cyclodextrin complexes in cosmetics	Beauty from contact lenses beyond vision correction

	Learning Resources	1. 2.	New Cosmetic Science, Mitsui T., Elsevier, 1998 CosmeticNanotechnology: Polymers and Colloids in Cosmetics, Sarah E.M., Kathleen O.H., Robert Y.L.,American Chemical Society, 2006	3.	Delivery System Handbook for Personal Care and Cosmetic Products, Meyer R.R. ,William Andrew ASP, 2005.
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Learning Ass	essment			47.7		United States	ALC: U				
	Bloom's			Contin	uous Learning Ass	sessment (50% weig	htage)			Final Examination	n (50% weightage)
	Level of Thinking	CLA -	1 (10%)	CLA - 2	(15%)	CLA -	3 (15%)	CLA – 4	· (10 <mark>%)#</mark>		
	Level of Thirking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %	7: 1	30 %	755	30 %		30 %	-	30%	-
Level 2	Apply Analyze	<mark>40</mark> %		40 %	11.0	40 %		40 %		40%	-
Level 3	Evaluate Create	<mark>30 %</mark>	Geral I	30 %		30 %	, during	30 %		30%	-
	Total	10	00 %	100	%	100	0 %	100) %	10	% 00

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Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
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2. Dr. Nagesh Kini, Thermax, Pune, Maharastra, nagesh. kini@gmail.com	2. Dr. Sampath Kumar T.S, IIT Madras, tssk@iitm.ac.in	2. Dr. Selvamurugan, SRMIST

Pre-req Course O					OGY Ca	tegory	/	Ε					Profes								3	0	0	3
	ses	Nil		Co-requisite Nil					Pr	ogress	sive	Nil												
Course O				Courses						Course	es	IVII												
	ffering De	epartment	Nanotechnology	Data Book / C	Codes/Standards				Nil															
		II.																						
Learning (CLR):			The purpose of learni		William III Control	1	_earn	J							ram L	.earni	ing Ou			,				
CLR-1:	Familia	rize with the field of to	raditional manufactu <mark>rii</mark>	ng to green manufacturing		1	2	3		1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2:				ple green manufacturing	1 3 3 2 3 4 4 5 3 2 4 4 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5				-				ਨ			E.								i
CLR-3:			gy concepts in In <mark>dustri</mark>		-0-36 (0.55)	l É	8	8		Ф			ear			ap		논		4)			ļ	I
			l policies and <mark>operatio</mark>	ons in industry			ે જ	T E		be	•	Jen	Ses	a)		į į		δ		Finance			ļ	I
CLR-5:		and the list of metric			The state of the s	g (F	e.	me		NC.	<u>.v</u>	ob	, R	age	e.	Sus		E		ina	ing		ļ	I
CLR-6:	Familia	rize the life cycle prod	cess of indu <mark>strial prod</mark>	uction	Charles Wallet	ίŽ	li Gi	ai		Α̈́	alys	Vel	sign	N	It It	∞5		Lea	io	∞ ~	arn			i
				Level of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)		Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	⊥ Modern Tool Usage	Society & Culture	Environment & Sustainability		☐ Individual & Team Work	Communication	Project Mgt. &	Life Long Learning	_	2	က		
Learning	Outcome	es	At the end of this . lea	arners will be able to:		<u>e</u>	Sec	Sec		gine	ple	sign	alys	der	ciet	Ę.	Ethics	i≥i	ш	jec	2	ö	0	PSO - 3
(CLO):			, III		A STATE OF THE STA	Le	Ä	Ĭ.		E .	P	De	Ä	⊗	So		亩	밀			Life	PSO	PSO	S
		ne concepts of green		2	80					Н			М	М	Н			Μ	Н	Н	Н	Н		
CLO-2:	Solve th	ne general problems	associ <mark>ated with</mark> the su	ustainable green manufacturing		2	80			Н	М	М	Н	М	М	М	Н	М		Μ	Н	М	М	М
CLO-3:			ces eff <mark>ectively in</mark> indus	strial process	ANTEREST OF ALL PROPERTY.	2	75			Н	М	Н	Η	Н	Н	Н	М	Н		Н	Н	Н	Η	Н
			in ind <mark>ustrial pro</mark> cess		CONTRACTOR OF THE	2	80			М	Н	Н	М	Н	Н	Н	Н	Н		М	Н	Н	Н	Н
CLO-5:				nalyzing machine tools		2	80			Н	М	Н	Н	Н	М	М	Н	М		М	Н	Н	Н	Н
CLO-6:	Utilize	green manufacturing	in sem <mark>iconduct</mark> or mai	nufacturing process		2	80	75		Н	М	М	Н	Н	М	М	Н	Н	Н	М	Н	Н	Μ	Н
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Dura		1	9	9	9							9								9				
(hou											-													
		Green manufacturing	9	Social, business & policy environment	Metrics for green manufactu	ring			Closed								Semico					g		
		Sustainability		Need for change	Current metrics				Life cyc								Semico							
	SLO-1	Regulation pressure		Internal stake holders	Financial metrics				Econon							/	Micro f	abrica	ation p	roces	SS			
S-2	SLO-2	Economic incentives		External stake holders	Metrics for ecology				Redu <mark>c</mark> ti resourc		invesi	tment	t & inc	reas	e of	L	Lithogr	aphy						
		Comprehensive adva		Components of next transition	Metrics for society			1	Machine	e tools	3						Oxidati	on &	annea	aling				
;		Barriers	Linear to circular transition	Multiple metrics				Energy								Cleanii								
	SLO-1	Environment impact	Product production to service provision	Impact assessment			L	Life cyc	le ass	essm	ent m	nachir	e too	ols	I	Facility	syste	ems –	reso	urce u	se			
S-4	SLO-2	Toxic chemical relea	ses	Integrated, information – Rich Communication	Risk assessment			/	Method	s & re	sults						Abaten							
S-5		Energy consumption emission	and carbon	Policy environment – Changing policy trends	Material flow analysis			F	Process	s para	meter	r optin	nizati	on		(Green	manu	factur	ring in	indu:	stry		
(SLO-2	Strategies for green	manufacturing	Fostering co-operation	Energy flow analysis			(Constar	nt feed	d per i	tooth				(Conce	ots &	challe	nges				
		Green supply chain		Principles of green manufacturing	Metric development method	ologie	S		Constar								Use ph							
S-6		Motivation for green											Analysis phase of semiconductor manufacturing											
S-7 S	SLO-1	Definition of GSC	1st principle of green manufacturing					pstream materials																

				Supply	lubrication	
	SLO-2	Issues in GSC	2 nd principle of green manufacturing	Metrics development for component systems	Health & environmental hazards	Chemicals, silicon, water
S-8	SLO-1	Level of approach	3rd principle of green manufacturing	Green energy supply	Remanufacturing – product recovery & industrial practice	Infrastructure & equipment
	SLO-2	General problems in GSC	4th principle of green manufacturing	Green energy technologies	Challenges & opportunities	Electricity
S-9	SLO-1	Techniques of GSC	Mappi <mark>ng of principles</mark>	Solar photovoltaics, wind energy	Reuse	Semiconductor manufacturing
3-9	SLO-2	Future of GSC	Solutions	Application potentials of green energy	Approaches for sustainable factory design	Transportation & use phase

Learning Resources	1.	Green Manufacturing- Fundamentals and Applications, David A Dornfeld, Springer science publishing, 2013	2.	Green Nanotechnology <mark>: Solutions fo</mark> r Sustainability and Energy in the Built Environment, Geoffrey B. Smith, Claes-Goran S. Granqvist, CRC Press, 2010

Learning Ass	essment				100	74.16.1					
	Bloom's			Continu	ous Learning As	ssessment (50% weigh	tage)	#7/L		Final Examination	n (50% weightage)
	Level of Thinking	CLA –	<mark>1 (</mark> 10%)	CLA – 2	(15%)	CLA - 3	(15%)	CLA –	4 (10%)#		ii (50% weightage)
	Level of Thirking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	3 <mark>0 %</mark>	1	30 %	sk ment	30 %	Les Vie	30 %	114-	30%	-
Level 2	Apply Analyze	<mark>40 %</mark>	19-24	40 %	Man 1	40 %	1. 5. 10.	40 %	-	40%	-
Level 3	Evaluate Create	<mark>30 %</mark>	3	30 %		30 %	in a su	30 %	-	30%	-
	Total	10	0 %	100	%	100	%	10	0 %	10	00 %

Course Designers		
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Cou Co		18NTE407T	Course Name	A	DVANCED COMPUTATIONA	TECHNIC	QUES					Cours Catego		Ε		Pro	fessio	nal Ele	ective	13	- T	· F)	C 3
С	requisite ourses e Offering [Nil Department Na	notechnology		equisite Nil Data Book / Codes/S	tandards					N	Progre Cour		Nil										
		100						7.																
Cours		Rationale (CLR):		lear <mark>ning this cour</mark> se			.earning							Pr	ogram	Learn	ing Οι	utcome	s (PLC))				
CLR-1	: met	hods can help to understa	and the properties	<mark>and at nano</mark> scale	r scales: how computational	1	2	3		1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		uire knowledge on molect	ular and optica <mark>l co</mark> i	mputing									5			ility								
CLR-3	: Kno	w the basis of Biomedica				Omo	(%)	(%)		ge		+	ear			nab		Ę		(I)				
CLR-4		elop concept on the phys				e B	5	int (led		mer	Ses	<u>o</u>		stai		8		ЯÚС	_			
CLR-5		uire knowledge on paralle			and architecture) BL	cier	JIL		δO	Sis	lopi	J,	sag	<u>e</u>	Sus		am	_	Ë	ing			
CLR-6	R-6: Understanding the various computing techniques in advance level					돌	rofic	ttair			aly	eve	esiç		Culture	t &		& Team Work	atior	∞ .	earr			
						Ē	дρ	d b		ring	A	Z O	Ŏ	70	۵ ۵	ner		<u>∞</u>	nice	Mgt	g Le			
Cours	e Learning	Outcomes			10 mg + 10 mg	evel of Thinking (Bloom)	Expected Proficiency (%)	স Expected Attainment (%)		Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society &	Environment & Sustainability	တ္လ	Individual	Communication	Project Mgt. & Finance	Life Long Learning	-	- 2	- 3
(CLO		Catoomoo	A <mark>t the end</mark> of th	is course, learners w	vill be able to:	eve	xpe	xpe		igi	go	esi	nal	lod	ÖC	IN	Ethics	lĕ	mo;	ŢŌ.	<u>ie</u>	PSO	PSO	H PSO
CLO-1		ly the knowledge of the p	roperties of nanom	aterial in advance c	omputina	2	80	75		Н	M	Н	Н	H	Н	Н	Н	M	Н	M	Н	Н	Н	H
CLO-2						2	80	70	30.0	Н	М	Н	Н	М	М	M	Н	Н	Н	М	H	М	М	M
CLO-3		ly the knowledge of Biom		-	The Later of the l	2	75	70		Н	L	Н	Н	Н	Н	Н	Н	Н	Н	М	Н	Н	Н	Н
CLO-4		cute the basic of Qubit pr		epth knowledge abo	out Quantum Computing	2	80	75	70	Н	М	Н	Н	Н	М	М	Н	Н	Н	М	Н	Н	Н	Н
CLO-5		ly knowledge of computin				2	80	70			- 1		Н				.,		Н					
CLT-6	Den	nonstration of the ability to	o d <mark>esign new</mark> funct	ional materials	Commission of the same	2	80	70	Н	М	Н	П	Н	М	М	Н	М	П	М	Н	Н	Н	Н	
				The same of the same of		-		400		41.5				25										
	uration hour)	9		21	9	B))		9						4	9						9			
	SLO-1	History of computing – I	Nanocomputing	Molecular Compu	rtina	Introduction	on to Bi	ochem	ical Co	omputir	na	Bit and	d Qubit					Para	allel co	mputin	a			
S-1	SLO-2	Nanocomputing Technolog	ologies <mark>– Alterna</mark> tiv		olecular Computing	Examples											-	Memoi	ry Clus	sters				
	SLO-1	Quantum Computing		Modeling molecul	les	Applicatio	n of DF	T in bio	ologica	al svste	m	Conce	pt Coh	erence	9			Para	allel alg	orithm				
S-2	SLO-2	Quantum Computing: A	pplications	Modeling clusters		Applicatio					n	Conce Examp	pt of E			with						exam	ple	
0.0	SLO-1	Nano Information Proce	essing	Overview of vario	us first-principles methods	Genetic A	Mgorithr	n	m	17%	120	Theory		tum P	arallelis	sms					of Moi stems	no and	l	
S-3	SLO-2	Prospects and Challeng	ges	Discussion on Lin	nitation and Application	Applicatio	on of G	A to Bio	ologica	al Syste	ms	Applica	ati <mark>on o</mark>	f Quar	tum Pa	aralleli	sms		lication			Multip	rocess	sor
C 4	SLO-1	Digital Signals		Density Functiona	al Theory (DFT)-	Biological	Neuro	าร				Classic Operat		es – F	Reversii	ble			e cons		ons to	Paralle	el	
S-4	SLO-2 Digital Gates Density Functional Theory (DFT)- HX and KS equations					processing					on Sqrt (NOT) Operation						Usefulness of Parallel processing in various device applications							
S-5	SLO-1 Concept Silicon Nanoelectronics Structural, Electronic of nanomaterials from calculations (Examples only)										n Concept of Quantum Algorithm						Influence of Delay Time							
	SLO-2 Application of Silicon Nanoelectronics Magnetic properties (examples only)						Function of neuron cell on silicon						licon for Application Quantum Algorithms Performance effici						iency (on Del	ay tim	e		

				Signal processing		
S-6	SLO-1	Introduction to Carbon Nanotube Electronics	Concept of Optical Computing	Modeling of neuron cells by VLSI circuits	Challenges to large Quantum Computers	Power Dissipation
3-0	SLO-2	Application of CNT electronics	Application of Optical Computing	Problems on Modeling of neuron cells by VLSI circuits	Fabrication, Testing Architectural Challenges	Power Dissipation in different system
S-7	SLO-1	Concept of Silicon Nanoelectronics	Current use of optics for Computing in Industry	Neural networks and distributed data processing	Working Concept of Quantum dot cellular automata	Architecture for Processing in Nanosystems
3-1	SLO-2	Application of Silicon Nanoelectronics	Optics for Computing: Future Applications	Problems on Neural networks and distributed data processing	Application with Example of Quantum dot cellular automata	Classic Systolic Arrays
C 0	SLO-1	Concept of Carbon Nanotube Electronics	Optical Computing Paradigms	Working concept of DNA Computer	Introduction and Working principle of Computing with QCA	Processor with large memory
S-8	SLO-2	Application of Carbon Nanotube Electronics	Optical Computing Paradigms: Examples	Application of a DNA Computer	Application of Computing with QCA	Application of Processor with large memory
S-9	SLO-1	Modeling of Carbon Nanotube	Working concept of Photonic Switches.	Information Processing with Chemical reactions: Working Concept	QCA Clocking.	Processor array with SIMD
3-9	SLO-2	Field Effect Transistors based on CNT	Application of Photonic Switches.	Information Processing with Chemical reactions: Example	QCA Design Rules.	PIP Architectures.

Learning
Resources
1103001003

- Vishal Sahni et.al, Nanocomputing: The Future of Computing, Tata McGraw-Hill Education, 2008.
 Feliciano Giustino, Materials Modelling using Density Functional Theory: Properties and Predictions, Oxford: Oxford University Press, 2014.

 - J.M. Thijssen, Computational Physics, Cambridge University Press, 2007.
 Andrew R. Leach, Molecular modelling: principles and application, Pearson Education, 2001

Learning Assess	sment					THE STATE OF							
	Dla am'a			Conti	nuous Learning Ass	essment (50% weig	htage)			Final Examination	n (EOO) weightege)		
	Bloom's	(1/ 1/10)		CLA –	2 (15%)	(15%) CLA – 3 (15%)			· (10%)#		n (50% weightage)		
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice		
Level 1	Remember	40 %	No.	30 %		30 %		30 %		30%			
Level I	Understand	40 %	100	30 %		30 %	-	30 %		30%	-		
Level 2	Apply	40 %	100	40 %		40 %		40 %		40%			
Level 2	Analyze	40 /0	1,000	40 /0	- 11/	40 /0	-	40 /0		4070	-		
Level 3	Evaluate	20 %		30 %	11/2	30 %		30 %		30%			
Level 3	Create	20 /0		30 %		30 /6	11/1/20	30 %		30%	-		
	Total 100 %		0 %	100 %		10	0 %	100) %	100 %			

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Cou		18NTE408T Course Name	NANOTECHNOLOGY IN TEX	TILES	Cour Categ		E				Pr	ofessio	onal E	lectiv	re				L 3	T 0	P 0	C 3
	equisite	Nil	Co-requisite Nil						ogres		Nil											
	urses		Courses						Course	es	IVII											
Course	Offering D	Department Nanotechnology	Data Book / C	Codes/Standards				Nil														
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(CLR):	ng Rationa	The purpose of lear.				Lea	arning			ш		Pro	ogram	Lea	rning O	utcom	,	•				
CLR-1		e knowledge on nanotechnology for textile				1	2	3	1	2	3 4	5	6	7	8	9	10	11	12	13	14	15
CLR-2		the smart materials and devices for textil <mark>e</mark>		1000000000							ع	=		≟								
CLR-3		the various nanostructures for improvi <mark>ng t</mark>		and the Address	1	Ē	8	(%)	Φ		_ 3	5		jabi		¥		43				
CLR-4		stand the nanomaterials processing <mark>for te</mark> .			- I -	쯢ㅣ	5	ĭ	bpe	٠,	ner S	2		<u>-</u>		Noi		nce				
CLR-5		various nanodevices for improvin <mark>g the tex</mark>		100		g (E	iei	ae B	N/C	S	ndc	ade	o o	Sign		E		ina	ng			
CLR-6	Get far	miliarize with the integration of na <mark>nodevic</mark> e	es in textiles	7.5 E. 2227	1 :	Ξ) Je	a a	Α̈́	llys	Vei	S S	量	~	;	Геа	<u>.</u>	∞	Learning			
					į	Level of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	Problem Analysis	Design & Development	T Modern Tool Usage	Society & Culture	Environment & Sustainability		エ Individual & Team Work	Communication	Project Mgt. & Finance	ng Le	-	-2	33
Learnii	ng Outcom	ies At the and of this	learners will be able to:	- 18	-	<u>e</u>	ect	Dect	gine	ple .	ngis	den	Siet	<u></u>	H Ethics	ivid	TH.	ject	Life Long	0	ö	PSO - 3
(CLO):		At the end of this , i	learners will be able to.	A STATE OF THE PARTY OF THE PAR		Fe	M L	X	EL)	P C	S C		Soc	E E		lud	S	Po	Life	PSO	PSO	PS
CLO-1		the scientific concepts of nanotechnology		No. of the last of			80 7	75	Н	M				M	l H	Н	Н	М	Н	H	Н	Н
CLO-2		the nanoparticles & nanofibe <mark>rs in texti</mark> le fa		The state of the s				70				H M		M		М	Н	М	Μ	Μ	М	Μ
CLO-3		arize the characteristics and <mark>classifica</mark> tion		OFFICE STATE				70				H H		Н		Н	Н	Н	М	Н	Н	Η
CLO-4		various nanocoating method <mark>ologies fo</mark> r im		CONTRACTOR OF THE				75				1 H		Н		Н	Н	М	М	Н	Н	Н
CLO-5		arize with new concepts of N <mark>anotechn</mark> olog						70				H H				М	Н	М	Н	Н	Н	Н
CLO-6	: Apply t	the various nanostructures a <mark>nd materi</mark> als	in textiles fabrics			2	80 7	75	Н	M	M F	1 H	М	M	l H	Н	Н	М	Н	М	М	Н
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	ration	9	9	9							9											
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	SLO-1	Introduction to smart nanotextiles	Responsive Polymers	Nanocomposites for texti	es			Nanoco	atings	for te	xtiles				Nanog	genera	ators f	or tex	ctiles			
S-1	SLO-2	Nanotechnology & nanomaterials	Classification of stimuli-responsive polymers	Classifications				Various			nano	c <mark>oatin</mark> g			Worki	-	_					
	SLO-1	Nanofibers	Responsive polymers as sensors	Structure & properties				Sol-gel	Proce	ssing					Classi	ificatio	n of n	anog	enera	tors		
S-2	SLO-2	Advantages of nanofibers	Responsive polymers in drug delivery systems	Production methods of na	посог	mpos	sites	Sol-gel	coatin	ig meti	nodolo	gy			Piezo	electri	c Nan	ogen	erato	rs (PE	NG)	
S-3	SLO-1	Nanofibers fabrication	Responsive polymers in cell application	Carbon structures			Til	Photoc	atalytic	c self-c	leanir	g			Triboe	electri	: Nand	ogene	erator	s (TE	NG)	
5-3	SLO-2	Electrospinning	Responsive polymers based filters	Nanocellulose				Super I	nydrop	hobic	self-cl	eaning			Theor	etical	origin	of Na	anoge	nerat	ors	
C 4		Enhancing the mechanical properties	Nanowires for textiles	Conducting polymers				Antibac				Ū			Fiber							
S-4		Large scale production of fibers	Properties of nanowires in textiles	Nanoparticles, clays & wi	es			UV-Pro							Textile	e base	ed PEI	NGs				
C.E	SLO 1 Formation of year & fabric Palancing transparency and conductance Laminated par					d fibe	ers	Impreg							TENG							
S-5	SLO-2 Moisture management & waterproof High specific surface area Membran				, coatings, & Hydrogels Cross link						d				Fibers	base	d TEN	VGs				
0.0	SLO-1	Thermoregulation	Direct charge transport path	Sensing of Nanocomposi	ites Plasma surface activation Textiles based																	
S-6	SLO-2	Personal protection											NGs									
S-7		Wearables and sensors	Metal conducting Nanowires									2D fabrics for TENGs										
5-1	SLO-2							Carbon	mater	rials	_				3D wo	ven t	extile [*]	TENG	3s			
S-8	SLO-1	Nanosols as coating agent	Fire protection			Phase change materials in thermal Integrating energy harvesting devices						ices										

					regulation	
	SLO-2	Applications of nanosols in textiles	Sulphide semiconducting Nanowires	Fire retardant materials	Nanowires in thermal regulation	TENGs with solar cells
S-9	SLO-1	Photocatalytic and light responsivity of nanosols	Other semiconducting Nanowires	Self-cleaning	Carbon based conducting coating	Integrating energy storage devices
3-9	SLO-2	Antimicrobials and bioactive systems	Current and future perspective of Nanowires	Energy harvesting of Nanocomposites	Metal based conducting coating	Future prospects of Nanogenerators

Learning	1. Nazire D. Yilmaz, Smart Textiles, Wearable Nanotechnology, 1st Ed., Scrivener Publishing, 2019	3. Nanotechnology in Textiles: Theory and Application, Jiří Militký and Rajesh Mishra, Elsevier
Resources	2. P. J. Brown and K. Stevens, Nanofibers and nanotechnology in textiles, CRC Press, 2007	Publications, 2018

-	DI			Conti	nuous Learning Ass	sessment (50% weigh	tage)			Cin al Cuancia atia	- (FOO(: abt)
	Bloom's Level of Thinking	CLA –	1 (10%)		2 (15%)	CLA - 3		CLA – 4	<mark>1 (10%</mark>)#	Finai Examinatio	n (50% weightage)
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 <mark>%</mark>	100	30 %	Di Sand	30 %		30 %		30%	-
Level 2	Apply Analyze	4 <mark>0 %</mark>		40 %	SI SECTION	40 %	Sec. Ye	40 %	-	40%	-
Level 3	Evaluate Create	30 %	STATE OF	30 %	3/47	30 %	15 5.00	30 %	-	30%	-
	Total	10	0 %	10	0 %	100	%	10	0 %	10	0 %

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
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Cou Co		18NTE409T	Coo Na	urse CA	ANCER NANOTE	CHNOLOGY			Course ategory	,	Е			Prof	essio	nal E	lectiv	Э			L 3	T 0	P 0	C 3
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CLR-1		standing the basis of					1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
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CLO-4 CLO-5		these nanosystems for the concepts of nano					2	80		H		Н	-M -H		H M	M	Н	H	Н	M M	H	Н	<u>п</u>	Н
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	ıration hour)		9	9	Sales of the last	9						9								9				
S-1	SLO-1	The biology and ger organisms	netics of ce <mark>lls and</mark>	Cell immortalization		Theranostic cancer biomari	ers		fo	lagnetic or MRI ap	plication	on			Ţ.	t	Pancre argets	s for a	diagno	ostics				
0 1	SLO-2	The nature of cance	er	Tumorigenesis	2	Targetted cancer theranost	ics		fo	lagnetic or th <mark>e</mark> rap	eutic a	oplicat	ion			t	Pancre argets	s for t	therap	y				
S-2	SLO-1	Tumor viruses		Cancer development	45 V.TI	Molecular imaging in cance	r thera	nosti	cs a	ltrasound rug deliv	ery car	riers				C	Nanon cell tai			oproa	ches	for ca	ncer .	stem
3-2	SLO-2	DNA oncoviruses		The biology of angiogenes	ais	Imaging-guided cancer the	ару			lltrasound ene deliv			nano	particle	es as	F	Persoi	nalize	ed car	icer tr	reatm	ent		
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S-3	SLO-2	Non-human oncovir	uses	Metastasis		Nanomaterials for theranos cancer	tics of	gastr	ric C	ancer th	theranostics with Gold nanoparticle Lipid based nanosystem for th				thera	nosti	ctics							
S-4	SLO-1	Cellular oncogenes		Types of cancers		Photo triggered drug delive For cancer theranostics	ry stra	tegies	gies Cancer theranostics with Silver Lipid based nanosystem for nanoparticle siRNA					delive	ery of	f								
	SLO-2	Growth Factors		Liver cancer		Proteomics-based theranos	tics			letal oxid		ancer	therar	ostics			Gene		py for	canc	er			
S-5	SLO-1	Growth Factor recep	otors	Lung cancer		Radionuclide imaging of ca	ncer th	nerap.	y C	ancer th	eranos	tics wi	th can	bon-ba	ased		Gene .					es		

					nanoplatforms	
	SLO-2	Cytoplasmic signal circuitry program	Skin cancer	Nanotargetted radionuclide imaging	CNT and grapheme based theranostics	Gene silencing ribozymes
S-6	SLO-1	Traits of Cancer	Colon cancer	Bioluminescence imaging of cancer therapy	Cancer theranostics with silica nanoparticle platform	Gene silencing by antisense DNA
3-0	SLO-2	Tumor Suppressor genes	Stem cells and cancer	Imaging in luciferase labeled cancer cells	Silica tethered particles for cancer theranostics	Gene silencing by microRNA
S-7	SLO-1	Types of Tumour Suppressor genes	Molecular genetics of cancer	Magnetic resonance imaging of cancer therapy	Polymerbased nanotechnologies for cancer theranostics	Rationale for immunotherapy
3-1	SLO-2	Characteristics of pRb	Chemical modifications of chromatinassociated proteins	CT based imaging of cancer therapy	Protein-based nanotechnologies for cancer theranostics	Adoptive immunotherapy
	SLO-1	pRb gene-Control of cell cycle clock	Genetic alterations in cancer cells: mutations	Boron capture therapy and imaging	Production of theranostic nanoparticles	Antibody based therapy
S-8	SLO-2	Characteristics of p53	Three types of mutation	Ultrasound imaging of cancer therapy	Scale-up of theranostic nanoparticles	Galectins as targets for novel and specific antibody therapies in gynecologic cancer therapies
S-9	SLO-1	Mutation of p53 and apoptosis	Chromosomal abnormalities	Gene expression microarrays	Market considerations	Glycans and mucins as targets for novel and specific antibody therapies in gynecologic cancer therapies
	SLO-2	Role of p53 in cell cycle progression	Acquired abnormalities	Tissue arrays	C,	Commercial development of antibodies as drugs

Resources 2. Cancer Biology, Raymond W. Ruddon, Oxford University press, 2007.	Learning Resources	1. 2.	The Biology of Cance <mark>r, Robert</mark> A. Weinberg, Garland Science, 2010. Cancer Biology, Ray <mark>mond W.</mark> Ruddon, Oxford University press, 2007.		3.	Cancer Theranostics, Chen &Wong,Academic Press, 2014.
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Learning Asse	essment					1700	TOTAL STATE OF				
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Level 3	Evaluate	30 %		30 %		30 %		30 %		30%	_
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[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
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Cour		18N I = 410 I	ourse VACUUM ANE	HNOLOGY	Course Categor		Ε				I	Profes	sional I	Electi	ve			-	L 3	T 0	P 0	C 3	
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CLR-3:		nowledge on various physical and c			Contract to the second	<u>ê</u>	6	(°)		<u>o</u>			ear		2	g	논		4				
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CLR-5:		nowledge on various characterization				9		ue le	H	owl	<u>.v</u>	obu	n,	gag	2 5	5	E		ina -ina	Learning			
CLR-6:	Acquire	e knowledge on various physical, <mark>op</mark>	<mark>tical an</mark> d chemical properties of thir	n tilms	25 20	— jē	ij	tain calc		조	alys	ve	sigi	ool Usaç	0	5	<u>6</u>	ig.	∞	arı			
						Level of Thinking (Bloom)	Ċ	Expected Proliciency (%) Expected Attainment (%)		Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Course & Cuctainability	<u></u>	□ Individual & Team Work	Communication	Project Mgt. & Finance) Le			
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	g Outcom	es At the end of a	his , learners will be able to:		A second	Ne l		bed		igi	igo.	ssig	laly	ode Si		Ethics	ÌŠ	E	oje	e.	PS0 - 1	PSO	H PSO
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CLO-1:		he functionalities of vacuum system				2		30 75 30 70		H	М	Н		ΗΛ				Н	Н	Н	Н	Н	
CLO-2 :		the knowledge acquired to o <mark>perate t</mark> hin films using various physi <mark>cal and</mark>			various regimes	2		0 70 0 70	- 71	Н	H M	H		H H		1 Н 1 М	H	H	M H	H	M H	M H	M H
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CLO-4 :		he concept of various chara <mark>cterizati</mark>		unickness using v	ranous techniques	2		80 70		Н	Н	Н		H			Н	Н	Н	Н	Н	Н	Н
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	ration our)	9	9		9					7		9							9)			
S-1	SLO-1	Over view of vacuum systems and technology	Over view of Physical vapo techniques	or deposition	Introduction to chemica	al depositio	on		Basic pa films lay				istry b	ehind t	hin	Thin	films	charac	cterist	ics			
3-1	SLO-2	Units and different regions of vacu	Thermal evaporation, Resistant RF-heating	stive heating	Electrodeposition				Nucleat	ion ar	nd ea	rly sta	ges o	fil <mark>m g</mark> ı	owth	Торс	graph	ıy					
0.0	SLO-1	Kinetic theory of gases	Flash evaporation		Electrolytic deposition				Thermo	dynai	nic a	spects	of nu	cleat io	1	Struc	ture i	ntegrit	y- X-r	ay diff	ractio	n (XF	:D)
S-2	SLO-2	Gas flow and Mean free path	Laser evaporation		Electro less deposition				Thin film									electro				•	
S-3	SLO-1	Conductance	Co-evaporation	WIND WAR	Anodic oxidation	100		Tra	Capillar	y the	ory							ion ele				/	
3-3	SLO-2	Different types of pumps	Electron bombardment hea		Spray pyrolysis	100			Volmen	-Web	er gr							persiv					
	SLO-1	Mechanical pumps	Sputtering plasma, dischar		Dip coating and Spin co	oating			Frank-v	an de	r Me	rwe (F	M) gro	wth		Auge	r elec	tron s	pectro	oscopy	/		
S-4	SLO-2	Diffusion and turbo molecular pum	Sputtering variants, yield all sputtering	uttering variants, yield and low pressure Chemical vapor deposition					Stransk							X-ray	phot	oelect	ron sı	pectro.	scopy	,	
S-5	SLO-1	Ion pumps	RF-sputtering						Thic <mark>kne</mark> films				•	es of th	in	Ruth	erford	backs	scatte	ring s _i	pectro	scop	/
	SLO-2	Measurement of vacuum	Reactive sputtering		CVD reactions				Thickness measurements Secondary ion mass spectrometry							/							
	SLO-1 Direct and indirect gauges Magnetron sputtering Hydrogen reduct											robe											
S-6	SLO-2	Pirani gauge	Magnetron configurations		Halide disproportionation reactions	on, transfe	er		Electric	al me	hods	3				Resi	stance	e – 4 - p	ooint p	robe			

S-7	SLO-1	Capacitance gauge	Bias sputtering	CVD processes and systems	Microbalance monitors	Optical properties
3-1	SLO-2	Penning gauge	Evaporation versus sputtering	Low pressure CVD	Quartz crystal monitor	Characterization of layered structures
S-8	SLO-1	Vacuum system	Pulsed laser deposition (PLD) design and basics	Laser enhanced CVD	Mechanical method (stylus)	Atomic force microscopy (AFM)
3-0	SLO-2	Components and operation of vacuum system	PLD operating procedure and its various application	Metalorganic CVD (MOCVD)	Optical interference methods	X-Ray Reflectivity (XRR)
S-9	SLO-1	Safety practices in vacuum systems		Plasma Assisted Chemical Vapor Deposition (PACVD)	Ellipsometry	Reflection high energy electron diffraction (RHEED)
	SLO-2	Applications of vacuum technology	MBE operating procedure	Safety considerations	Interference fringes	In-situ RHEED

Learning Resources 1. M. Ohring, Materials Science of Thin Films: Deposition and Selsevier), 2002. 2. K.L.Chopra, Thin Film Phenomena, Robert E.Krieger Publisi	3. S. Campbell, The Science and Engineering of Microelectronic Fabrication, 2nd Ed., OUP, 1990. 4. Kaufmann, Characterization of Materials, 2nd Ed., Wiley, 2003
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earning Assess	sment										
_	Diagraia			Conti	nuous Learning Ass	essment (50% weig	htage)			Final Evaminatio	n (FOO) weightege
	Bloom's Level of Thinking	CLA –	1 (10%)	CLA -	2 (15%)	CLA -	3 (15%)	CLA – 4	1 (10%)#		n (50% weightage)
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember Understand	30 %	STOWN IN	30 %	West had	30 %	14 5.00	30 %	-	30%	-
Level 2	Apply Analyze	40 %	3 10	40 %		40 %		40 %	-	40%	-
Level 3	Evaluate Create	30 %		30 %		30 %	1	30 %	-	30%	-
	Total	10	0 %	10	0 %	10	0 %	10	0 %	10	00 %

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2. Mr. Ramanujam, HHV, India	2. Dr. M. S. Ramachandra Rao, IIT Madras, msrrao@iitm.ac.in	2. Dr. E. Senthil Kumar, SRMIST

Course Code	18NTE411T	Course Name ATOMISTIC MODE				.ING				Cour Categ		Е		Р	rofessi	onal E	ective	!		L T	- F)	C 3
Pre-requis Courses Course Offer	INII	nology	Co-requisite Courses	Nil Data Book / C	Codes/Stanc	dards	c	1		1	Progre Cou lil	essive rses	Nil										
Course Learn (CLR):	ning Rationale The	purpose of learning th	is course is to:	100	100	L	_earnin	g	1/1	1		T.	Pr	ogram	Learn	ing Ou	ıtcome	s (PL0	D)				
	Learn about basic modeling		1			1	2	3	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-3 : CLR-4 : CLR-5 :	Understand the DFT for materials mo Understand the MD simulation Gain knowledge about Monte Carlo S Learn advance-modeling technique. Learn materials modeling to understa	Simulation	S			evel of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society & Culture	Environment & Sustainability		Individual & Team Work	Communication Com	Project Mgt. & Finance	Life Long Learning	1	2	3
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	Acquire the basics of design and man					2	80	75	Н	Н	Н	Н	Н	Н	M	Н	Н			Н	Н	Н	Н
	Gain knowledge DFT and related me				To all the	2	80	70	Н	Н	Н	Н	Н	Н	M	Н	Н	Н	M	Н	М	М	М
CLO-3 : CLO-4 :			ics and its application ot solve materials problem			2	75 80	70 75	H	H	H	H	H	H M	H M	H	M	H	M M	H	H	H	H
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	Explain the structural, electronic and			ies di Materiais		2	80	70	Н	М	Н	Н	Н	Μ	Н	Н	М	Н	М	Н	Н	Н	Н
OLIV-U.	Explain the structural, electronic and	magnetic properties of	a given material				00	70															
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S-1 SLO-2	problems	Limitations of BO app	roximation	2	Detail time	steps			Startir	ng stru	cture -	- energy	/ cutof	f	Ba	sic DF	T outp	outs					
SLO-1	Potential energy-Definition and Concept	Intr <mark>oduction to</mark> DFT	335	L- CY	The basic i	MD algo	orithm		State	space	sampl	ing	T	П	Ba	sic out	tput of	QM co	ode				
SLO-2	Basic pair potentials and their limitations	Hohenberg-Kohn The	orems	WIT KAN	The MD st	eps	14	0.4	Class	ical mo	mentu	ım			En	ergies	, electi	ronic s	tructur	e			
SLO-1	Definition - Elastic constant	Kohn-Sham Equation			Taylor exp				Metro	polis a	lgorith	m			Us	ing the	enero	gies: m	nolecul	ar stat	ics, ME	D, MC	
S-3 SLO-2	Calculation of elastic constants from potential function		etation of KS equations Verlet alg					•	Exam	ples w	ith a pi	roblem			Us	ing the	e energ	gies: M	1C				
S-4 SLO-1	Potentials for ionic systems		on functions and LDA/GGA Predictor-corrector algorithm				Monte Carlo simulation analysis Using the electronic structure: optical propert							perties	;								
SLO-2	Potentials for ceramics Systems	Accuracy of LDA/GG/	GGA Discussion with Examples							e Carlo		ations						nic sta	tes				
SLO-1	Concept of Many-body potential	Pseudopotentials			MD in diffe	rent en	semble	s	Introd	ucing	ensem	ble sin i	МС				l condu						
S-5 SLO-2	Many -body potentials for metals				MD in cons	stant ter	mperat	ure	Kineti	c Mon	e Carl	0				obility o ntes	of elec	trons, s	scatter	ring of	electro	ns bet	veen

S-6	SLO-1	Many-body potentials for covalently bonded systems	Brillouin zone	Molecular dynamics in constant pressure	Key concepts: starting structure in MD	Excited electron states due to thermal (or optical) excitations
	SLO-2	Comparative Study	K-points, Monkhorst-Pack mesh, Gama point	Examples of MD in constant temperature and pressure	Key concepts: starting structure in KMC	Type of bonding - tunneling rates
	SLO-1	Energy optimization	Concept of Basis Set	Energies: molecular statics	Convergence criteria	Excited electron states due optical excitations
S-7	SLO-2	Significance of Lowest energy structure	The need for self-consistency	Problems on Molecular Statistics	Scaling with lattice parameters	Example with a Material problem
S-8	SLO-1		Setting up structures, key parameters, Volume optimization Metals vs. insulators	MD Simulation analysis	Understanding the electronic structure	Understanding the electronic structure from different Methods, Comparative study
	SLO-2		Basis sets, energy cutoff, exchange-correlation function, K-points	Limitations of MD	Electrical conductivity, Excited electron states	Wave functions, charge density, band structure, density of states
	SLO-1	Thermo statistics	Convergence and scaling with lattice parameters,	Application of MD as Case Study: 3D system	Application of MC method as Case Study: Temperature effect	Confinement effect on Electronic Structure
S-9	SLO-2	Problems on Thermo statistics problems	DOS and BAND Structure	Application of MD as Case Study: 2D system	Determination of Tc	3D, 2D, 1D Carbon based materials as example

Learning	1.	Jörg-Rüdiger Hill, Lalitha Subramanian and AmiteshMaiti, Molecular modeling techniques inmaterial sciences,	3.	R. Martin, Electronic Structure: Basic Theory and Practical Methods, Cambridge University
		Taylor & Francis/CRC Press: Boca Raton, 2005		Press, 2004
Resources	2.	Andrew R. Leach, Molecular modelling: principles and application, Pearson Education, India, 2001	4.	J.M. Thijssen, Computational Physics, Cambridge, UK: Cambridge University Press, 2000

Learning Assess	sment		7 1	A 1 10 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1		STATE OF		31 /			
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	Bloom's Level of Thinking	CLA –	1 (10%)	CLA – 2	(15%)	CLA -	3 (15%)	CLA – 4	l (10 <mark>%)#</mark>		ii (50% weigiilage)
	Level of Hilliking	<u>Theory</u>	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember	30 %	mercan to	30 %	111111111111111111111111111111111111111	30 %		30 %		30%	_
Level I	Understand	30 70				30 /0		30 70		3070	_
Level 2	Apply	4 <mark>0 %</mark>	55 V	40 %		40 %	_	40 %		40%	_
LCVCI Z	Analyze	40 70		40 70		40 70		40 70		4070	_
Level 3	Evaluate	30 %		30 %	77.	30 %		30 %		30%	
Level 3	Create	30 /8		30 /8		30 /6	- mark	30 //		30%	-
	Total	10	0 %	100	%	10	0 %	100	<mark>0 %</mark>	10	00 %

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers	Programme and the second secon	
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
1. Dr. Hemant Dixit, GlobalFoundaries, aplahemant@gmail.com	1. Dr. Ranjit Kumar Nanda, IITM Chennai, nandab@iit <mark>m.ac.in</mark>	1. Dr. C. Preferencial Kala, SRMIST
2. Dr. Murali Kota, Global Foundaries, USA, kvrmmurali@gmail.com	2. Prof. G.P. Das, IIT M, KGP, msgpd@iacs.res.in	2. Dr. Saurabh Ghosh, SRMIST

Cou		18NTE412T	Course Name	SOCIETAL IMPLICATIONS OF NANC	DTECHNOLOGY	Course Category	/	Ε				ı	Profe	ssiona	l Elec	ctive					L 3	T 0	P 0	C 3
Co	requisite ourses Offering [Nil Department	Nanotechnology	Co-requisite Courses Nil Data Book / C	Codes/Standards	-				rogres Cours		Nil												
					Alle M.	-			7															
Course	Learning	Rationale (CLR):	he purpose of learning	n <mark>g this course</mark> is to:		L	.earni	ing						Progr	am L	.earni	ing Οι	utcon	nes (P	LO)				
CLR-1				implications of nanotechnology		1	2	3	10	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15
CLR-2	: Provid	le an insight into the fun	damentals of so <mark>cial-</mark>	economic implications of nanotechnology	No. 11		3		-				ç			£								
CLR-3	: Under	stand the implications o	f nanotechnology in	quality of life	ACCUMANTAL OF THE	_ Ê	%	(%		Ф			earc			iabi		논		4				
CLR-4 CLR-5		stand the legal risks related to				1 1 2 2) 5	ut (edg	50	neu	Ses	(D)		stair		δ		age				
CLR-6		stand the problems of g			THE SHAPE		Sen	l me		Mo	Sis	lopr	II,	sag	<u>e</u>	Sus		am	_	Finance	ing			
OLIVO	. Onder	stana the problems of g	overnance of handle	Commonagy		Level of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)		Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, R <mark>esearch</mark>	⊤ Modern Tool Usage	Society & Culture	Environment & Sustainability		TIndividual & Team Work	Communication	∞ŏ	Life Long Learning	1	2	3
Course	Learning	Outcomes (CLO):	At the <mark>end of this</mark> cou	rse <mark>, learners will be able to:</mark>	The state of the	evelo	Expect	Expect		=ngine	Proble	Design	Analys	Modern	Society	Enviror	Ethics	ndivid	Somm	Project Mgt.	ife Lo	- OSd	- OSd	PSO -
		the knowledge of ethica			Charles to Alban	2	80	75		Н	Н	Н	Н		H	Н	H		Н	Μ	Н	Н	Н	H
CLO-2		ss the socioeconomic in	nplica <mark>tions of n</mark> anote	echnology	352377 20	2	80			Н	Н	М	Н		Н	Н	М	М	Н	М	Н	М	М	М
CLO-3		e the quality of life		A STATE OF THE STA		2	75		13	М	М	Н	Н		Н	Н	М	М	Н	М	Н	Н	Н	Н
CLO-4 CLO-5		ss the legal risks related the issues related to p				2	80		- 3	H	Н	M H	H		Н	H M	Н	H	H	М	H	H	H	H
CLO-5		ss the problems of gove			-	2	80		L.E	М	M	М	Н		M H	Н	M M	M M	Н	H M	Н	Н	М	Н
								wi																
	uration hour)	9		9	9							9								9)			
S-1	SLO-1	Economic Impacts and Commercialization of	Nanotec <mark>hnology</mark>	Ethics, Law and Governance – Introduction	Social Scenarios - Introd	duction			Conve	rging	Techr	nologie	es - In	trodu	ction		Public							
J-1	SLO-2	Introduction to societa nanotechnology	al implications of	Ethics and law	Nanoparticle toxicity and	l risk			Integra	ative T	echn	ology					Public nanos			1S-SOC	cietal	implic	ation	s of
S-2	SLO-1	Socio-economic impassience : initial results		Ethical issues in nanoscience and nanotechnology: reflections and suggestions	Navigating nanotechnolo	ogy throug	gh so	ciety	Nanote quality	echnoi of life	logy's	implio	cation	s for t	he	,	An age	enda	for pu	ıblic iı	nterad	ction r	esea	rch
	SLO-2	Socio-economic impa science : nanobank		Concerns of Nano scientists and engineers in Ethics and law	Public and private goods	3	1		Social	implic	cation	s				(Comm	unica	ating r	nanot	echno	ologica	al risl	(S
S-3	SLO-1	Managing the nanoted	chnology revolution	Ethics and nano: a survey	Nanoparticle Toxicity an	d risk			Manag techno	logies	3				-	nt I	Risk A	sses	smen	t				
	SLO-2	Malcolm Baldrige nati	onal quality criteria	Recent developments in nanotechnology	Nanotechnology, surveil	lance, and	soc		The "ir							I	Risk C	omn	nunica	tion				
S-4	SLO-1	Emergence of Nanoed		law in a new frontier	Methodological issues				Social issues						<i>3y</i>		Proble							
0-4	SLO-2	Key drivers, challenge	es and opportunities	An exploration of patent matters associated with nanotechnology	Innovations for social re	search			Nanob Dimen		nolog	gy: The	e Scie	ence			A prop nanote						ding	of

S-5	SLO-1	Moore's law	U.S. Patent Statute	Nanotechnology: societal implications: individual perspectives		Nanotechnology in the media: a preliminary analysis
3-0	SLO-2	Transcending Moore's law with molecular electronics	The Ethics of Ethics	Nanotechnology: individual perspectives	• .	Public engagement with nanoscale science and engineering
	SLO-1	Molecular electronics – a next paradigm	Environmental Impacts of nanomaterials	Nanotechnology and social trends;	Regulatory structures and society	Nanophobia
S-6	SLO-2	Transcending Moore's law with nanotechnology	Problems of governance of nanotechnology	Five nanotech social scenarios	Social impacts of nanobiotechnology issues	Public Engagement with nanotechnology
S-7	SLO-1	Transition from Microelectronics to nanoelectronics	Negotiations over quality of life in the nanotechnology initiative. Governance	#Finics in an age of commercialization	The use of analogies for interdisciplinary research in the convergence of nanotechnology	Nanotechnology: moving beyond risk
3-7	SLO-2		Societal implications of emerging science and technologies: a research agenda for science and technology studies (STS)	Implications of Experiential data recorder		Communication streams and nanotechnology: the (Re) interpretation of a new technology nanotechnology
S-8	SLO-1	Sustaining the impact of nanotechnology on productivity	Institutional impacts of government science initiatives		Interdisciplinary research in the convergence of information technology	Societal implications- individual perspectives
3-0	SLO-2	Sustaining the impact of nanotechnology on sustainability, and equity	Challenges for government and universities	Institutionalizing Multi-Disciplinary Engagement	Converging technologies: innovation, legal risks, and society	The case of Cold Fusion
S-9	SLO-1	Implications of Information	Nanotechnology for national security	Post-hoc Versus Therapeutic Ethics	Converging technologies and their societal implications	The case of Recombinant DNA
3-9	SLO-2	Non-Nano effects of nanotechnology on the economy	Nanotechnology in Defense	Nano revolution implications for the artist		Historical comparisons for anticipating public reactions to nanotechnology

Learning Resources 1. C.R. Mihail, and S.B. William, Nanotechnology: societal implications, Springer publication, 2011 (978-1-4020-5432-7) 2. Ronald Sandler, Nanotechnology the Social & Ethical Issues, Woodrow Wilson, 2009	3. Mihail C. Roco and William Sims Bainbridge, Societal Implications of Nanoscience and Nanotechnology, National Science Foundation, 2001.
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Learning Assess	ment			Land San W.		1 10 10 10							
	Bloom's		100	Cont	inuous Learning Ass	Final Evamination	n (E00/ woightage)						
	Level of Thinking	CLA – 1 (10%)		CLA – 2 (15%)		CLA –	3 (15%)	CLA -	4 (1 <mark>0%)#</mark>	Final Examination (50% weightage)			
	Level of Thinking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice		
Level 1	Remember Understand	30 <mark>%</mark>	- 6	30 %	- 1	30 %		30 %	-	30%	-		
Level 2	Apply Analyze	40 %	- 8	40 %		40 %		40 %	# 11 -	40%	-		
Level 3	Evaluate Create	30 %	-	30 %	We've	30 %	FHAN	30 %	-	30%	-		
	Total	100) %	10	00 %	10	0 %	10	0 %	10	00 %		

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers		
Experts from Industry	Experts from Higher Technical Institutions	Internal Experts
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2. Dr.Tanvi Sharma ,Nanoshel LLC, Chandigarh, India, tanvisharma@nanoshelcom	2. Dr. Asish Pal, Institute of Nanoscience and Technology, Punjab,apal@inst.ac.in	2. Dr. P. Sivakumar, SRMIST

Cou Coc		18NTE413T	Course Name	NANOTEC	CHNOLOGY IN T	ISSUE EN	GINEERING			Cou Cate		E			Prof	essior	nal Ele	ctive			L 3	T 0	P 0	C 3
Co	requisite ourses	Nil		Co-requisite Courses	IVII		W-2004				Co	ressive urses	Nil											
Course	Offering D	Department	Nanotechnology		Data Book / 0	Codes/Star	ndards	7			Nil													
Learnii (CLR):	ng Rationa	ile	The purpose of learr	ning this is to:	16.21		# 1	ı	Learn	ing					Program	Lear	ning C	utcor	nes (P	LO)				
CLR-1		stand the general scie		<mark>sue engineer</mark> ing				1	2	3	1	2	3	4	5 6	7	+	9	10	11	12	13	14	15
CLR-2 CLR-3 CLR-4 CLR-5 CLR-6	: Acquir : Get ac : Unders	equainted with the curr stand the tissue respo	e role of nanote <mark>chno</mark> ent trend in tissue ei nses to biom <mark>ater</mark> ial	logy in tissue engineering and regenerative tissue scaffold generation		medicine		Level of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)	Engineering Knowledge	nalysis	Design & Development	⊤ Analysis, Design, Research	ol Usage	Environment & Sustainability	,	Team Work	ation	: & Finance	Learning			
Learnii (CLO): CLO-1	ng Outcom	nes basic knowledge of tis		earners will be able to:				2 Level of Th	% Expected P	52 Expected A	Fngingering	▼ Problem Analysis	⊥ Design & D	≖ Analysis, D	T Modern Tool Usage Society & Culture			⊤ Individual & Team Work	□ Communication	Project Mgt.	⊤ Life Long L	H PS0 - 1		H PSO - 3
CLO-2		e the basic challenge:			TVATE	1		2	80	70	Н	М	M	Н	ММ			М	Н	М	М	M	М	М
CLO-3		concepts of tissue eng		cal applications	THE WAY	77:31	76.77	2	75		Н		Н		Н Н	Н		Н	Н	Н	М	Н	Н	Н
CLO-4 CLO-5	: Apply i	these nanosystems fo concepts in making na	r the th <mark>erapy</mark>	ativa aubatvataa				2 2	80		H		H		Н <u>Н</u> Н М			H	H	M M	M M	H	H	H
CLO-5		the tissue engineering			100	- 4		2			H		М		H M			Н	Н	M	Н	Н	М	Н
	ration		9	9			9	10	**				9							9	1			
	SLO-1	The Cell		First Cultures: culture con	ntainers	Characte	eristics of bioma	aterials		E	Electrospi	nning	Ŧ				Electrospun Nanofibers for Neural Applications				1			
S-1 -	SLO-2	The cell as a function	nal unit	First Cultures: culture med	dia	Design o	of biomaterials			Ε	xperime	ntal set	up a <mark>n</mark> d	basic	p <mark>rinci</mark> pl	Nonofiber Boood Integra				es	•			
S-2	SLO-1	Tissue types		Serum free culture media	14- VY	Fundam to bioma	ental aspects o terials	f tissue re	spons	ses E	ffects of	oaram	eters <mark>o</mark>	n elect	<mark>ros</mark> pinn	ing	Rege	nerat						
3-2	SLO-2	Soft and Hard tissue		Growth factors	Para	Types of	f tissue respons	ses		S	olution p	aramet	ters				Engir	neerin	ıs Mat g and	Rege	nerati	on		ue
S-3	SLO-1	Extracellular matrix		Cell Culture Techniques	ture Techniques Repair and regeneration			7			nvironm						Guid	ed Ce	g Soft II Res _l	oonse)			
J-J	SLO-2	Extracellular matrix of function	components and	Hybridomas	Evaluation of biomateria			al behavio	r	n	Biomedical Applications of electrospun nanofibres					n	Nanoparticles-Incorporated Scaffolds for Tissue Engineering Applications							
S-4	SLO-1	Emergence of tissue		Cardiomyocites cultivation	n		n, migration and			Nanofibres as 3D scaffold for tissue regeneration						Tissu	e Ėng	n Psei gineeri	ng Ap	plicati	ions) for	
3-4	SLO-2	Germ layers and Gro	ound tissue	Cryopreservation			es of biomateria in vivo experim		ed		Nanofibre scaffolds for interface Nano-enabled Platforms regeneration Malignant Melanoma				ns for	Metas	static							

S-5	SLO-1	Regeneration	Slow programmable freezing	Hydrogels	Techniques to improve porosity	Immune Response to Implanted Nanostructured Materials
3-5	SLO-2	Various phase of regeneration	Vitrification	Types of hydrogels used in tissue engineering	Techniques to improve cell infiltration	3D Bioprinting – introduction
S-6	SLO-1	Concept of tissue construction	Persufflation	Chitosan as biomaterial for tissue engineering	Hybrid fibres for bone regeneration	3D Bioprinting-priciples
	SLO-2	Three steps of tissue development	Tissue culture: Migration	Nanobiomaterials for regeneration	Hybrid fibres for ligament regeneration	CAD based bioprinting
S-7	SLO-1	Stem cells- types	Tissue culture: new formation	Carbon Nanobiomaterial	Hybrid fibres for tendon regeneration	CAM based bioprinting
3-1	SLO-2	Embryonic stem cell	Dedifferentiation	Self assembling nanobomaterials	Bioactive nanofibres	Laser based bioprinting
	SLO-1	Mesenchymal stem cell	Organ culture: principles	Polymeric Nanobiomaterials	Types of Bioactive nanofibres	Bioprinted scaffolds
S-8	SLO-2	Adult stem cells	Plasma clot method	Types of Polymeric Nanobiomaterials	Application of Bioactive nanofibres	Challenges and future development of 3D bio printing
	SLO-1	Stem cells properties and source	Agar gel method	Ceramic nanobiomaterials	Biomolecules on nanofibers	Materials used for bio printing
S-9	SLO-2	Responsible use of stem cells	Formation of organ from tissue	Types of Ceramic nanobiomaterials	Methods for immobilizing biomolecules	Bioprinting based tissue engineering applications

	1.	W.M.Will, Raimund Strehl <mark>, Karl Schu</mark> macher, Tissue Engineering: From Cell Biology to Artificial Organs,
Learning		WileyVCH, 2005.
Resources	2.	Ketul Popat, Nanotechnology in Tissue Engineering and Regenerative Medicine, CRC Press/Taylor and Francis,
		2011

3. Lijie Grace Zhang, John P Fisher, Kam Leong, 3D Bioprinting and Nanotechnology in Tissue Engineering and Regenerative medicine, Elsevier, 2015

Learning Assess	sment			- 15 m 1 / / / m -	The state of		The second	- 39					
_	Dloom's			Contin	uous Learning Ass	essment (50% weig	htage)			Final Evamination	n (E00/ waightaga)		
	Level of Thinking	Bloom's CLA -		CLA – 2	(15%)	CLA –	3 (15%)	CLA – 4	(10%)#	Final Examination (50% weightage)			
	Level of Thirtking	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice		
Level 1	Remember Understand	30 %	Carried V	30 %		30 %	. die	30 %	1 5-1	30%	-		
Level 2	Apply Analyze	4 <mark>0 %</mark>	551	40 %		40 %	-	40 %		40%	-		
Level 3	Evaluate Create	30 <mark>%</mark>	120	30 %	- 1/	30 %	- 9	30 %		30%	-		
	Total	10	0 %	100	%	100	0 %	100) %	10	00 %		

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

Course Designers	Address of the same and the sam	
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1. Mr. K. Chandru Trivitron Healthcare Pvt. Ltd. Chennai, chandru.k@trivitron.com	1. Dr.Amit Kumar Mishra , IIT Jodhpur, amit@iitj.ac.in	1. Dr. Devanandh Venkata Subbu, SRMIST
2. Dr.Nagesh Kini,Thermax,Pune,Maharastra,nagesh.kini@gmail.com	2. Dr. T.S Sampath Kumar, IIT Madras, tssk@iitm.ac.in	2. S. Anandhakumar, SRMIST

Cour Cod		18NTE414T	Course Name		NANOMAGNETISM AN	D SPINTRONICS					Course Catego			E		Profe	essioi	nal E	Electiv	e Col	ırse		L 3	T 0	P 0	C 3
Co	equisite urses	Nil Department	Nanotechnology	Co-requisite Courses	Nil Data Book	/ Codes/Standards	S		gress ourse		Nil															
Course	, Onloning L	Sopartmont	rvariotodiniology		Butta Book	- Codos/Otaridarde																				
Learnir (CLR):	ng Rationa	le	The purpose of learning	ng <mark>this is to:</mark>	1.3,			L	earnir	ng						Progra	am Le	arnii	ng Oı	utcom	es (Pl	LO)				
CLR-1					d magnetic properties of	materials		1	2	3		1	2	3	4	5	-	7	8	9	10	11	12	13	14	15
CLR-2			about low dimensi <mark>ona</mark>												5											
CLR-3:			ion behavior of m <mark>agnet</mark>		and tnin nims ze magnetic nanostructure			moo	%) /	%)		ge		ju	sea			aina		o ^K		g				
CLR-5					f contemporary topics in the			<u>B</u>	l Co	Jent		Wed	"	bme	8 8	ge	4)	nste		٦ 		Finance	g			
CLR-6			of spin polarized curre			(E.H. 50/A)		king	fice	aj.		Ŝ	lysis	/elo	gig	nss	ture	S S		-ear	Б	& Fi	Ţ.			
				5	型面		THE SA	Level of Thinking (Bloom)	Expected Proficiency (%)	Expected Attainment (%)		Engineering Knowledge	Problem Analysis	Design & Development	Analysis, Design, Research	Modern Tool Usage	Society & Culture	Environment & Sustainability		Individual & Team Work	Communication	Project Mgt.	Life Long Learning	_	2	-3
	ng Outcom	es	At the e <mark>nd of this</mark> , lea	arners will be able t	to:	180		le ve	cbec	cbec		gine	ople	sigi	lalys	ode	ociet	Nico	Ethics	divic	mu	ojec	e Lo	PSO-	PSO-	- OSA
(CLO): CLO-1	Poolize	the importance of "r			r the advancement of new	tochnology		2	<u>ம்</u> 80	75		山 H		H	₹ H			ம் M	П	<u>≧</u> H	З Н	M M	当 H	H	<u>7</u>	H
CLO-1					operties in low dimension	technology	201	2	80	70		Н						Н	Н	M	Н	M	Н	M	M	M
CLO-3					and properties of the magr	netic nanostructure	es	2	75	70		Н						Н	М	Н	М	Н	Н	Н	Н	Н
CLO-4			racteriz <mark>ation tech</mark> nique					2	80	75		М	Н	Н			Н	Н	Н	Н	М	М	Н	Н	Н	Н
CLO-5	Analyz	e the mechanism of ing technology	spin tra <mark>nsport in</mark> magn	netic nanostructure	s and its relevance in adv	rancing the existin	ng magnetic	2	80	70		Н	Н	Н	Н	Н	М	Н	Н	М	Н	М	Н	Н	Н	Н
CLO-6	: Gain th	ne conceptual knowle	edge rel <mark>ated to na</mark> noma	<mark>agnetism an</mark> d spintr	ronics for energy efficient	devices		2	80	75		Н	М	М	Н	Н	М	М	Н	Н	Н	М	Н	Н	М	Н
		1						1																		
	ration lour)		9	12 V	9		9							9								9				
	SLO-1		m, Units in <mark>magnetis</mark> m	Concept of Magne	etic ordering	Magnetism in thin	n films			L	ntrodu	ction t	o vari	ous m	agne	omet	ers	li	ntrodu	ıction	to sp	in trai	nspor	t		
S-1	SLO-2	Introduction to ferro paramagnetism, dia	magnetism	Magnetic ordering	in low dimensions	Magnetism in mu					Vorking	g prin	ciple d	of mag	netor	neters	S	S	Spin a	ngula	r mon	nentu	m			
S-2	SLO-1	ferromagnet			Magnetic anisotropy	Fabrication of nar techniques	nomagnets	using	vario	- '	/ibratin	_	-	ŭ				S	Spin C	Currer	nt					
3-2	SLO-2	Origin of various type behavior		Shape anisotropy anisotropy	and Magnetocrystalline	Top down and bo	ottom up app	proaci	h		Superce Device	onduc	eting C	Quantu	ım Int	erfere	nce	S	Spin v	alve d	device	s				
0.0	SLO-1	Magnetization curve loops, Saturation m		Dipolar anisotropy anisotropy	, Interface magnetic	Single domain ve behavior	ersus multi a	domaii	η	٨	Лagnet	ic ima	aging i	techni	ques			C	Giant i	magn	eto re	sistar	nce (C	GMR)	1	
S-3	SLO-2	Coercive field, Magi	natic suscentibility		<mark>/ scale determining</mark> py	Chemical synthesis of magnetic na				٨	//agnet	o-opt	ical K	err eff	ect			S	Spin d	epen	dent s	catte	ring			
S-4	SLO-1	Formation of magne			<mark>agnetization re</mark> versal,	Self assembly of magnetic nanopa					ongitue effect	dinal,	Trans	sverse	and	Polar	Kerr	V	/alet-i	Fert n	nodel	for Gi	MR			
	SLO-2	Domain walls, Dom	ain wall width	Coherent rotation		Magnetic nanowir				F	arada	y effe	ct					Magnetic tunnel junction								
S-5	SLO-1	Various type of dom	nain walls	Fanning, curling		Physical vapor de films		magn	etic ti	hin									neto i			(TMR	?)			

	SLO-2	Bloch walls and Neel walls	Domain wall movement	Physical Vanor denosition of militilavers	Scanning electron microscopy with polarization analysis	Application of GMR and TMR
S-6	SLO-1	Quantum mechanical picture of Heisenberg exchange interaction	Introduction to Gilbert damping	DC and RF Sputter deposition of Magnetic materials	thin films and nanostructures	Spin transfer torque
3-0	SLO-2	Role of Heisenberg exchange interaction in magnetism	Significance of Gilbert damping in choosing magnetic material for application	Magnetic Material deposition using E-beam evaporation technique	Magnetic contrast from nanostructures	Spin-orbit coupling induced phenomena
S-7	SLO-1	Energy scales involved in magnetism	In-plane magnetic anisotropy		Spin-polarized scanning tunneling microscope (SP-STM)	Spin dynamics
5-1	SLO-2	Zeeman energy	Magnetic domains in in-plane magnetized materials	Domain walls and magnetization reversal nanostructures	Interpretation of SP-STM results	Advanced spintronics based devices
C 0	SLO-1	Magnetic anisotropy energy, exchange energy	Perpendicular magnetic anisotropy	Magnetic properties of nanostructured soft magnetic materials NiFe	Introduction to magnetic recording	Domain wall based memory
S-8	SLO-2	Discussion on Magnetostatic energy	Magnetic domains in out-of-plane magnetized materials		Magnetic recording principles	Magnetic random access memory
S-9	SLO-1	Introduction to hard magnetic materials		Magnetic materials of nanostructured hard magnetic materials FePt		Heat assisted magnetic recording
5-9	SLO-2	Introduction to soft magnetic materials	Formation of antivortex and Skyrmions	Magnetic properties of nanostructured hard magnetic materials CoPt	Read and write head	Microwave assisted magnetic recording

Learning	1. Principles of Nanomagnetism, by Alberto P. Guimaraes, XII, Springer Berlin Heidelberg New York, 2009	3. Spin dynamics and damping in ferromagnetic thin films and nanostructures, by Anjan Barman and
		Jaivardhan Sinha, Springer, Switzerland, 2018

Learning Assess	sment							_			
	Bloom's	Continuous Learning Assessment (50% weightage)								Final Examination (50% weightage)	
	Level of Thinking	CLA – 1 (10%)		CLA – 2 (15%)		CLA – 3 (15%)		CLA – 4 (10%)#		Tillal Examination (50% weightage)	
		Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice	Theory	Practice
Level 1	Remember	3 <mark>0 %</mark>	151	30 %		30 %	-	30 %	-	30%	-
Level I	Understand										
Level 2	Apply	40 <mark>%</mark>	124	40 %	-	40 %	- 17	40 %		40%	-
Level 2	Analyze										
Level 3	Evaluate	30 %	1	30 %		30 %	- 1224	30 %	# 1-	30%	-
Level 3	Create										
	Total	100 %		100 %		100 %		100 %		100 %	

[#] CLA – 4 can be from any combination of these: Assignments, Seminars, Tech Talks, Mini-Projects, Case-Studies, Self-Study, MOOCs, Certifications, Conf. Paper etc.,

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